

CHAPTER 7

Growth mechanism and microstructure of nanostructured CeO₂ and doped-CeO₂: (Gd³⁺, Zr⁴⁺) films by CSD

7.1 Motivation

In the previous chapter we have achieved high quality TFA- YBa₂Cu₃O₇ film on processed vacuum deposited CeO₂ cap layers. However, for the cost-effective production of high-temperature superconductor applications, physical vapor deposition-derived ceria cap layer may be replaced by MOD grown film, but some problems have to be overcome [139].

Previous studies on epitaxial growth mechanism and microstructure evolution of nanostructured CeO₂ films on (100)-YSZ substrates deposited by chemical solution, showed that films grown in a reducing 95%Ar/5%H₂ (Ar/H₂) atmosphere were inherently granular as a result of a grain growth inhibition mechanisms induced by grain boundary contamination with C, see Fig. 7-1. Incorporation of carbon was caused by inefficient reactions of decomposition of C-rich precursors [38].

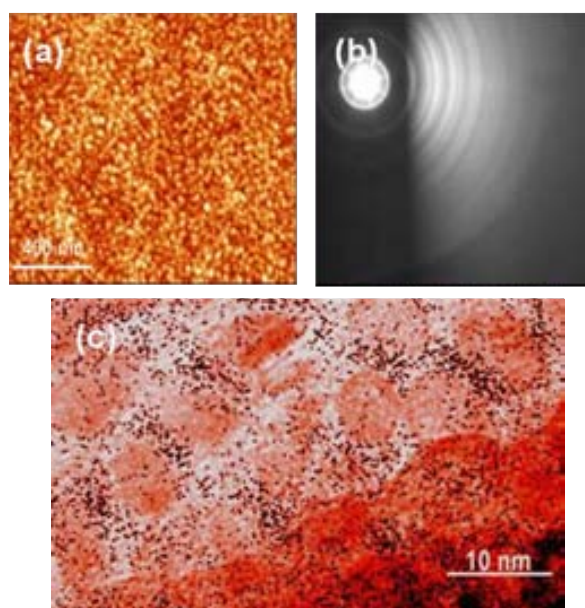


Fig. 7-1 Morphological and microstructural characterization of MOD-CeO₂ film grown in 95%Ar/5%H₂ atmosphere (a) Typical atomic force microscopy (AFM) image exhibiting a granular morphology with rounded grains. (b) RHEED image exhibiting a ring pattern indicating a disordered surface. (c) EELS mapping of the C distribution through the cross-sectional area, superposed on XTEM image viewed along the <100> direction of the mapped area, showing a nanometric granular microstructure [70].

Thermal processing at 1000°C under oxidizing atmospheric conditions, which enhanced atom mobility in ceria, was required to consume the missoriented grains allowing the epitaxial grains to grow to the surface. This transformation yields to a whole film reconstruction stabilizing (001) polar surface [38]. Indeed, this process allowed us to successfully grow TFA-YBCO films on MOD CeO₂ cap layer on IBAD-YSZ/SS substrate [48]. But unfortunately, these post processing conditions are not compatible with Ni-NiW substrates because uncontrolled oxidation of the Ni-alloy occurs. Thus, there is a clear need to develop an alternative route to enhance mobility in our MOD-CeO₂ films to unblock granular growth and eliminate C impurities preserving reducing conditions for coated conductor development.

Based on the results obtained on sputtering-CeO₂ films described in the previous chapter, our purpose in the following discussion will be to favour epitaxial growth and development of atomically flat terraced surface of CeO₂ cap layer in reducing atmosphere. At the same time it would allow us to establish a better understanding of ceria kinetics growth process. In this context it was necessary to look into number of different topics such as diffusion, grain boundary mobility, and chemical properties of pure and doped ceria [183].

7.2 Mobility in CeO₂ films

It is well established that the elimination of grain boundary area within the polycrystalline film is the driving force for MOD-CeO₂ epitaxial growth [38,176]. For changes in microstructure it is necessary that the atoms could jump from its present site to a neighbouring site, i.e., diffusion. In Fig. 7-2(a) it is schematized an individual atomic jump from grain A to grain B across the boundary. Diffusion process was well described by Fick's laws which in the simplest case relates the flux of particles, J , with the concentration gradient, dC , through a proportionality constant termed D : diffusivity,

$$J = -D \left(\frac{dC}{dx} \right) \quad \text{Eq. 7-1}$$

The diffusivity is a material property and it is perhaps the most useful parameter for characterizing the rate of diffusion. Moreover, the jump frequency or atoms diffusion is a thermally activated process which could be expressed by Eq. 7-2

$$D = D_0 \exp\left(\frac{-Q}{RT}\right) \quad \text{Eq. 7-2}$$

where D_0 is a constant and Q is an experimentally determined activation energy, see Fig. 7-2(b). Notice that the influence of defect concentration, crystal structure and composition of the medium in which diffusion is taking place has not yet been taken into account. In fact Q contains other energy terms such as defect formation and migration energy, which in turn depends on the availability of jumps sites [207].

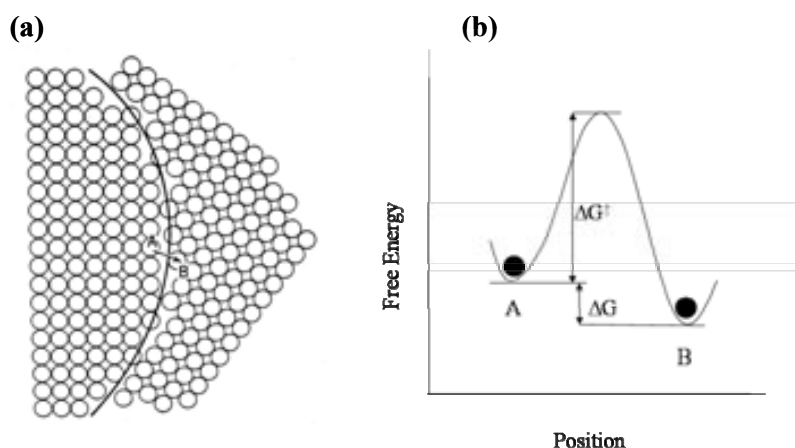
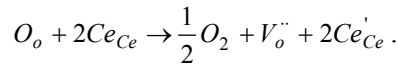


Fig. 7-2 (a) Structure of boundary (b) energy change for atomic jump, ΔG [207]

Referring back to CeO₂ material, it is well known that in CeO₂ takes place several defect reaction along with charge balance since Ce⁴⁺ can easily reduce to Ce³⁺, recall Eq-6.1 :



Consequently, it is expected that the formation of these defects would modify atom diffusion and therefore it could provide us a powerful tool to handle mobility in our CeO₂ films. To do that it is firstly required a good knowledge of the mechanisms that control or change this defect reaction.

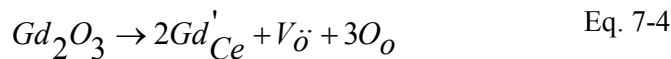
Applying the law of mass action (assuming no interaction between the various defects) on Eq-6.1 gives,

$$[V_o^{\bullet\bullet}][Ce'_{Ce}]^2 P(O_2)^{1/2} = \text{constant} \quad \text{Eq. 7-3}$$

Considering the above reaction, it is easily understood that oxygen partial pressure, P(O₂), will naturally affect the equilibrium by changing the concentration of oxide vacancies [208,209].

Chen and coworkers by investigating the microstructure of CeO₂ pellets synthesized at different oxygen partial pressure atmospheres found out an inverse dependence on mobility data [210]. Indeed, they associated enhancement in mobility with oxygen vacancy formation, being consistent with Eq. 7-3. Moreover, this mobility data was used to deduce the diffusion mechanism in CeO₂ and they suggested an interstitial mechanism controlled by cation diffusion [211].

The same authors carried out an alternative strategy to increase mobility in CeO₂ lattice. They doped CeO₂ with metal oxides with lower valencies, e.g. by dissolution of Sr²⁺, Ca²⁺, Gd³⁺,



From the above equation it is deduced that by the incorporation of Gd³⁺ into ceria lattice, the dopant agent occupies Ce⁴⁺ site of host lattice and therefore by charge compensation oxygen vacancies are formed.

In both studies (P(O₂) and dopant agent) they found that oxygen vacancies are the key parameter to introduce mobility in CeO₂ specimen [211]. In addition, the grain boundary mobility in CeO₂ is further influenced by the dopant concentration, valence and ionic radius, as it is further exposed below.

7.2.1 Concentration of dopant

(a) At low dopant concentration mobility is controlled by the diffusion of host atoms across the boundary plane, as is shown in Fig. 7-2(a), the mobility is termed intrinsic. Here, aliovalent dopant can create available sites for atom diffusion by charge-compensating effect and, as a consequence, enhances grain boundary mobility reducing its associated activation energy (Q).

(b) At high concentration of dopants the accumulation of solute ions in the structural core and /or the vicinity of grain boundaries reduce grain boundary mobility to the extent at which the dopants accumulate at the grain boundaries. This is generally attributed to the formation of associations between dopants and oxygen vacancies and /or the ordering of oxygen vacancies [212]. As a result, the solute distribution should be carried along with the moving boundary [213] and the mobility is controlled by solute drag through the lattice [214]. Solute diffusion in the near boundary region is usually slower than the intrinsic diffusion of host atoms across the boundary plane, and becomes rate-limiting. Actually, this is the role of carbon in our MOD-CeO₂ films.

7.2.2 Nature of dopant

In choosing the type of cationic dopant, we have taken into account the following facts;

(1) Rare-earth precursors with a trivalent cation are known to be the best possible dopants for ceria because rare-earth elements can easily replace cerium on its regular site due to the closeness in their electronegativity to that of cerium [215].

(2) The structural integrity of the fluorite lattice is best preserved if the lattice parameter of the dopant is the same as that of ceria and there is no variation in the lattice parameter after doping, see Table 7-I. This background suggests that Gd could be an excellent candidate as dopant for CeO₂ [183].

Table 7-I Ionic radius and lattice parameter of M_nO_m [211,216]

M	Ionic Radius (Å)	M _n O _m lattice parameter(Å)
Ce ³⁺	1.07	3.891 ; 6.059
Ce ⁴⁺	0.97	5.411
Gd ³⁺	1.05	10.812
Zr ⁴⁺	0.84	5.14

Finally, it is very important to consider that besides the above strategies to enhance mobility in CeO₂, chemical solution deposition and particularly MOD process offers the possibility to modify final microstructure by tuning processing conditions, chemistry of precursors and solvents in comparison to physical deposition methods. The influence of chemistry of precursors have been earlier investigated in our group by Cavallaro [139], therefore we are going to focus on the processing conditions and to probe the influence of solvents.

Prompted by these findings, to surmount the energy barriers for grain boundary mobility, under the particular experimental constraints of the present study, we proposed three approaches:

(a) firstly, it was investigated the influence of slightly oxidizing atmosphere during CeO₂ growth, then

(b) it was investigated the influence of solution chemistry precursor [66],

(c) and finally, we studied the effect of trivalent and tetravalent cations on CeO₂ growth and microstructure based on studies of defect interaction in boundary mobility and cation diffusivity in CeO₂ [210,211].

In all these approaches, CeO₂ properties have been studied from the standpoint of cap layer application for YBCO coated conductor. However, YBCO growth on these (doped)-CeO₂ cap layers will be described in the next chapter.

7.3 Effect of atmosphere on CeO₂ growth

The impossibility of using a pure oxidizing post-processing atmosphere to unblock grain boundaries and to reconstruct CeO₂ surface in technical substrates made us find an alternative route to enhance epitaxial growth of CeO₂ and stabilize (001) surface as well, by introducing different combinations of oxygen level in the gas process. Based on Eq. 7-3 it was believed that low concentration of oxygen in the carrier gas could be effective to increase mobility in CeO₂ lattice and consequently clean carbon from grain boundaries and enhance grain reorientation favouring epitaxial CeO₂ growth. CeO₂ precursor solution preparation is described in section 3.3.3.1.

Two approaches have been investigated: the one-step and the two-step processes. Briefly, in the two step process, the metal salt solution has been directly heated in oxygen in an initial decomposition step. Once the organic precursor should be completely decomposed, the oxygen gas has been changed to Ar/H₂ (to preserve metallic substrate from oxidation) and the film has been subsequently heated to high-temperature crystallization step. Based on weight losses measurements performed in O₂ atmosphere, Fig. 7-3 (a), CeO₂ precursors are fully decomposed

around 210°C, whereas in Ar/H₂ atmosphere the decomposition ends ~600°C. Therefore, in our case, a temperature of 300°C was established for the initial decomposition step and then, precursor films were heated up to 900°C for 8 hours, (see Fig. 7-3 (b)). Alternatively, in the one-step process (heating profile described in Fig.3-16 (b)), organic removal and crystallization are accomplished in the same processing atmosphere at 900°C for 8 h: Ar/H₂/H₂O mixture, (adding water vapour (P(H₂O)=2.2%) in the former gas (95%Ar/5%H₂)), supported by the good results obtained on processed sputtering-CeO₂ in Ar/H₂/H₂O atmosphere in the previous chapter [217]. The influence of atmosphere on CeO₂ epitaxial growth, was investigated in comparison with a CeO₂ film grown at 900°C for 8h in Ar/H₂ and in O₂ following the work started in the group [139]. At this point we should remark that all samples have been synthesized from the same precursor solution using acetic acid as solvent (section 3.3.3.1).

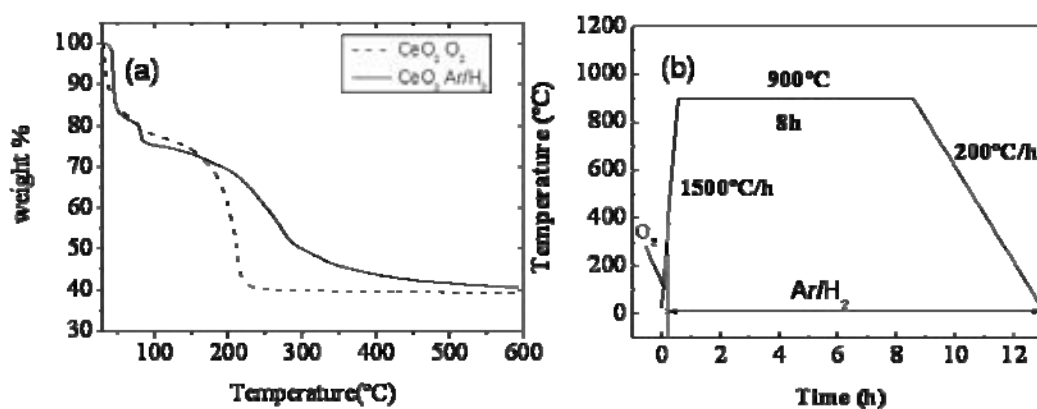


Fig. 7-3(a) TGA of CeO₂ precursors dissolved in acetic acid. The heating rate was 300° C h⁻¹ between 35°C and 300°C and 1500°C h⁻¹ between 300°C and 600°C performed in O₂ (dashed line) and performed under Ar/H₂ atmosphere (straight line). (b) Heating profile of two step processing CeO₂.

7.3.1 Structural and morphological characterization

In Fig. 7-4 it is shown XRD θ - 2θ scans measured from 25 to 38°. A considerable weak (*h*00) CeO₂ reflections at $2\theta = 33.3^\circ$ have been detected for the three reducing atmospheres here investigated (Ar/H₂, Ar/H₂/H₂O and O₂-Ar/H₂). Furthermore, very weak off-axis (111) CeO₂ peak was also present, indicating the existence of misoriented grains. In this figure it has been also included a θ - 2θ scan from CeO₂ processed in O₂ for 8h at 1000°C (in green). Based on XRD and TEM investigations [38], we considered this sample 100% epitaxial and thus, will be referred to as reference sample.

We would like to note that contrary to what predicted Eq. 7-3 and Chen [210,211], oxygen processing atmosphere strongly enhanced mobility in MOD-CeO₂ film. This is not surprising considering that our system contains C impurities and this parameter is not considered in the reported bibliography. We suggested that the main role of oxygen in this system is the elimination of carbon and consequently facilitate film reconstruction resulting fully epitaxial film.

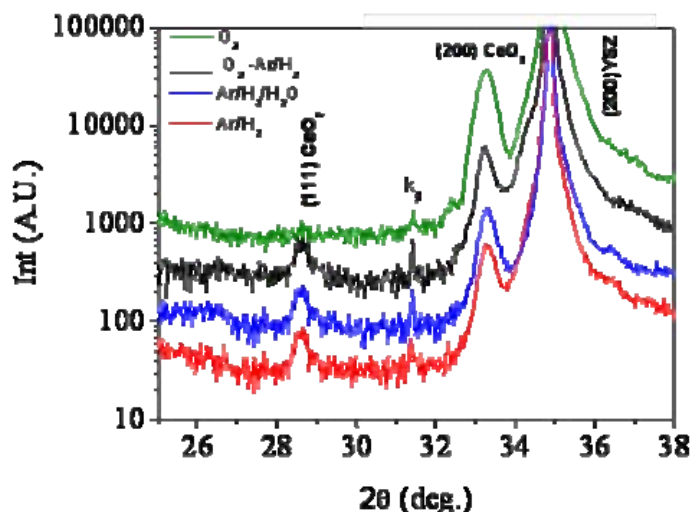


Fig. 7-4 $\theta/2\theta$ XRD patterns of MOD-CeO₂ films grown under different atmospheres: Ar/H₂ (in red), under Ar/H₂/H₂O (blue), under O₂ and Ar/H₂ (black) and under oxygen (green). All the films were grown at 900°C for 8 h.

By comparing the area of (*h*00) CeO₂ Bragg line reflection of the different samples here studied with the area of (*h*00) CeO₂ Bragg line reflection from reference sample, we have determined quantitatively the degree of epitaxial fraction of our CeO₂ films processed in different atmosphere. We have selected XRD θ -2 θ (400) CeO₂ peak since it provides higher separation from YSZ peak substrate than (200) CeO₂ peak although this reflection is not shown in Fig. 7-4 because its corresponding 2 θ value is 69.7°. Table 7-II displays the evolution of this parameter. It reflects that no significant improvement has been achieved from the viewpoint of epitaxial fraction by incorporation low content of oxygen in the processing gas.

Typical ϕ -scans of the (111) CeO₂ reflection from these films showed four peaks 90° apart signalling a unique in-plane orientation (Fig. 7-5). Further investigation of the peaks revealed that consist of two contributions, one broad peak and a superposed narrow one. By contrast, for film grown in pure oxygen atmosphere the broad contribution disappears. Earlier TEM investigations identified the narrow contribution to heterogeneously nucleated epitaxial

grains whereas the broad contribution was attributed to grains nucleated on top of the epitaxial grains with poor texture [139]. These results are well consistent with epitaxial fraction listed in Table 7-II

Table 7-II Summary of percentage of epitaxial fraction for different processed MOD-CeO₂/YSZ samples

Processing atmosphere	% epitaxial fraction (± 2)
Ar/H ₂	19
Ar/H ₂ /H ₂ O	20
O ₂ - Ar/H ₂	28
O ₂	100

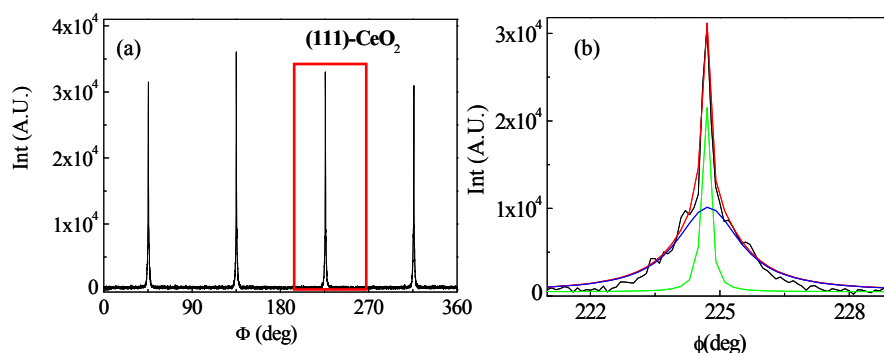


Fig. 7-5 In-plane texture of CeO₂ film (a) ϕ -scan of the (111) reflection (b) detail of one peak of ϕ -scan showing two contributions $\Delta\phi_{(1)} = 1.4^\circ$ (blue) and $\Delta\phi_{(2)} = 0.2^\circ$ (in green).

In collaboration with IFW-Dresden, further texture assess was carried out by x-ray diffraction pole figure analysis. The (220) CeO₂ peak was selected because it provides a clear separation of the YSZ peaks and they also give a high intensity. Pole figure analysis of CeO₂ film processed in Ar/H₂ and CeO₂ film processed in O₂ followed by Ar/H₂ are displayed in Fig. 7-6. From pole figure of CeO₂ grown in Ar/H₂ it can be deduced that the grains are not aligned in a preferred orientation. Thus, the film is non-textured, Fig. 7-6(a). From pole figure of CeO₂ grown in O₂ followed by Ar/H₂ it can be scarcely detected four poles among a randomly oriented matrix, therefore it is partially textured, Fig. 7-6(b). They agree well with structural data presented above. These results suggest that low content of oxygen in the processing atmosphere is not enough to enhance mobility in CeO₂ film to attain fully epitaxial growth.

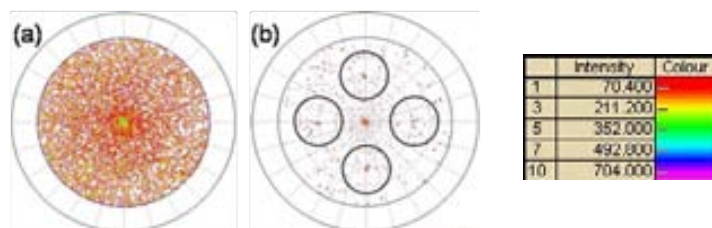


Fig. 7-6 X-ray diffraction pole figures of (220) CeO₂ planes from (a) CeO₂ grown in Ar/H₂ atmosphere and (b) CeO₂ grown in O₂ followed by Ar/H₂ atmosphere.

Structural and morphological properties of these films were further studied by RHEED and AFM analysis. AFM images are shown in Fig. 7-7. All films processed under low content of oxygen presented surface morphology dictated by rounded grains, Fig. 7-7(a-c), far from the terraced one found in samples grown in pure oxygen atmosphere, Fig. 7-7(d) [38]. Surface roughness varied from rms \sim 2.5 nm for two step growth atmosphere to rms = 6.5 nm for Ar/H₂/H₂O growth atmosphere. Previous studies carried out on CeO₂ cap layer requested atomically flat area rather than low rms value to reach high quality of TFA-YBCO film (chapter 6, [38]). Consequently, we have focused on the quantification of atomically flat area of these films.

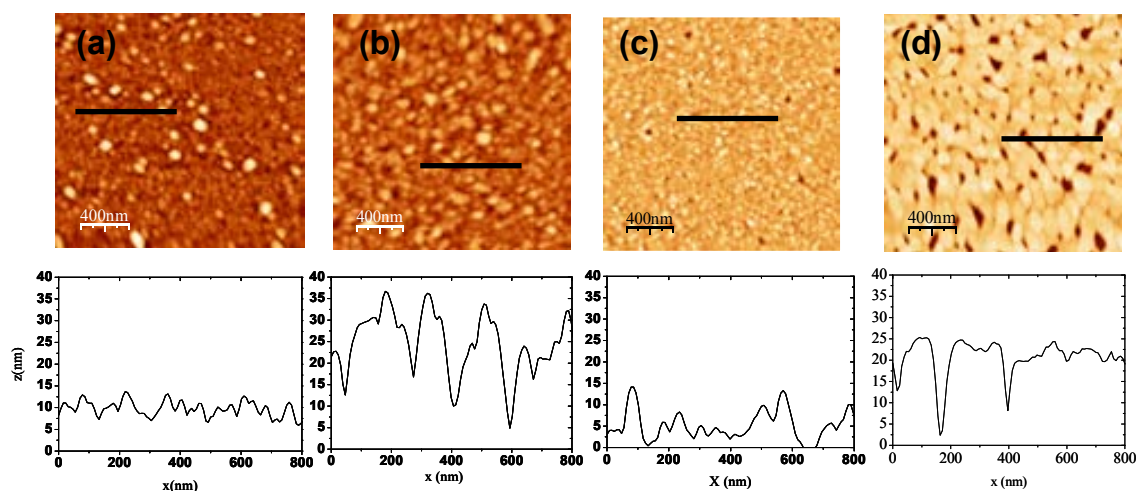


Fig. 7-7 2x2 μ m scans of AFM of (a) CeO₂ under Ar/H₂ rms =3,2 nm, (b) CeO₂ under Ar/H₂/H₂O rms =6,5 nm, (c) CeO₂ under O₂ - Ar/H₂ rms =2.5 nm (d) CeO₂ under pure O₂ rms =4.4 nm

We have quantitatively estimated this parameter for the three samples here presented and we have obtained in all cases percentages lower than 13%. In particular, in Fig. 7-8(a) it is shown a typical binary image obtained from CeO₂ sample processed in Ar/H₂ atmosphere. We

would like to note that CeO₂ film grown under pure oxygen atmosphere shows 70% of atomically flat terraced surface, see Fig. 7-8(b).

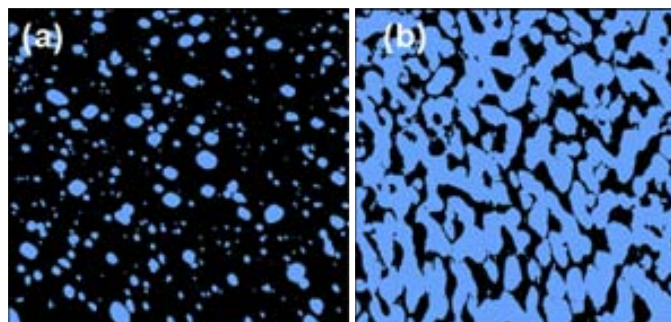


Fig. 7-8 Binary image from AFM topographic image (a) from CeO₂ film grown under Ar/H₂ atmosphere Fig. 7-7 (a) with 13% of atomically flat area; and (b) from CeO₂ film grown under pure O₂ atmosphere, Fig. 7-7 (d) with 70% of atomically flat area.

RHEED patterns performed along the $\langle 100 \rangle$ and $\langle 110 \rangle$ substrate directions are shown in Fig. 7-9. Inspection of RHEED images for ceria grown under Ar/H₂/H₂O and Ar/H₂ revealed a ring pattern, indicating a randomly oriented surface (Fig. 7-9(a) and (b)). These results agree well with the pole figure measured from Ar/H₂ processed CeO₂ film. In contrast, ceria grown under O₂ + Ar/H₂ presents a spotty like pattern, Fig. 7-9 (c). It is an indication of textured surface. Even though this result is in apparent disagreement with the pole figure presented above, Fig. 7-6(b), if we look in detail the RHEED pattern in Fig. 7-9 (c), we will find a weak background signal which is attributed to randomly oriented grains. Therefore these two contributions superposed correlate well with the XRD results and to the percentage of epitaxial fraction quantified above.

Finally, by comparison, it has been included a RHEED pattern from reference CeO₂ film shown in Fig. 7-10. Spotty pattern identifies textured grains but differing from O₂+Ar/H₂ processed CeO₂ films, here the shape of the spots are elongated, called streaks. This indicates that there are regions in the surface which are atomically flat, i.e. 2D contribution.

As a result, we can identify an evolution from 3D (rounded grains) to 2D surface (flat regions) by increasing the content of oxygen in the former gas confirming the surface morphology observed previously by AFM in Fig. 7-7.

It is interesting to emphasize that CeO₂ films with low epitaxial fraction displays surface morphology governed by rounded grains. As far as surface morphology evolves to terraced morphology the epitaxial fraction strongly increases. Therefore, the investigations here reported on MOD-CeO₂ samples allow us to establish a correlation between epitaxial fraction computed

from XRD θ - 2θ scan measurements and surface morphology investigated by AFM and RHEED analysis. All along this chapter we are going to explore the validity of this scenario.

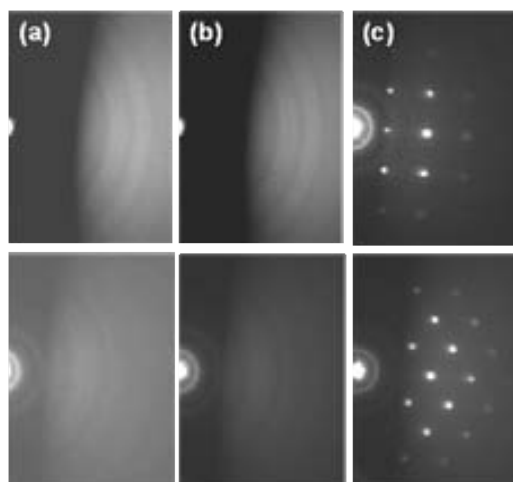


Fig. 7-9 RHEED image of CeO₂-MOD buffer layer on YSZ single crystal grown in (a)Ar/H₂ (b) Ar/H₂/H₂O and (c) O₂ and Ar/H₂ double step process. Images above correspond to <100> direction and images below correspond to RHEED pattern along <110> direction of the substrate.

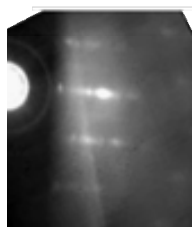


Fig. 7-10 RHEED pattern along the <100> substrate direction of CeO₂ film on YSZ single crystal substrate grown under pure oxygen atmosphere [38]

Then, XPS measurements were carried out in order to investigate if the gas processing atmosphere has induced changes in the chemical surface composition that could give us an evidence to understand the blocking mechanism of CeO₂ epitaxial growth.

7.3.2 Chemical surface characterization

XPS measurements have been performed in the three samples differently grown after being exposed to air. XPS operating conditions for recording spectra were described in 2.1.3, as well as the processing data acquired.

C(1s) spectra is shown in Fig. 7-11, Ce(3d) is shown in Fig. 7-13 and O(1s) spectra is shown in Fig. 7-14.

In C(1s) spectra, all samples show a main peak at 285.1 eV assigned to C adsorption from environment (contamination carbon, specially hydrocarbons). However Ar/H₂ processed ceria, and in less extension Ar/H₂/H₂O, show a low binding energy feature on the main C(1s) peak, namely C_{282.5} in Fig. 7-11. Chemical shift observed in XPS spectra is the result of the overall electronegativity by which the analysed element is surrounded. Peak shape and peak position of C_{282.5} is very close to the values usually reported for carbide compounds [218], and therefore is likely due to Ce-C bond. Moreover, the existence of CeC₂ and Ce₂C₃ compounds has been known for several years [219]. Based on previous studies performed in our group [38] we suggest that carbon from organic precursors captured (at least) in ceria surface, resulted in carbide formation due to the reducing processing conditions.

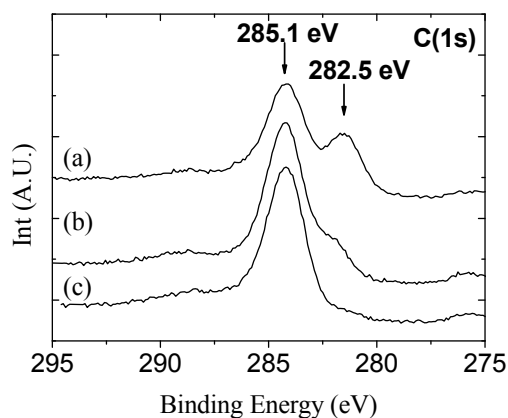


Fig. 7-11 C (1s) XPS spectra of MOD-CeO₂ film on YSZ single crystal grown at 900°C for 8 hours in Ar/H₂ (a) in Ar/H₂/H₂O(b) and in O₂ followed by Ar/H₂ (c).

We have estimated the percentage of carbide content retained in ceria for each processing atmosphere here evaluated. We calculated the atomic percentage of C, O and Ce with the software package Eclipse using Shirley base line and the following sensitivity factors: Ce3d: 12.06, O1s: 0.66 and C1s: 0.25 (reported in detail in section 2.1.3.1.3). From the above

considerations we obtained a percentage of carbide of 33% in Ar/H₂ atmosphere, 15% in Ar/H₂/H₂O atmosphere and <5% in two step annealing process (i.e O₂ and Ar/H₂ atmosphere). From these calculations it is clearly seen that in wet atmosphere carbide content has been slightly reduced and in O₂:Ar/H₂ atmosphere it has been almost completely eliminated (near de surface). Hence, it has been suggested that pure oxygen atmosphere favoured the elimination of trapped carbide.

Since previous studies have shown that by the elimination of carbon, ceria film evolves from partially to totally epitaxial film [38], here we have investigated the dependence of the percentage of carbide content on the CeO₂ epitaxial fraction previously determined by XRD analysis. Fig. 7-12 shows that higher percentage of carbide content in CeO₂ films yields to lower epitaxial fraction. These results evidence and support that carbon retained in the film does block the epitaxial growth in MOD-CeO₂ films. Thus, we have established that as long as reducing atmosphere was replaced by pure oxygen gas C trace was disappeared and polycrystalline matrix evolves to epitaxial film.

However from these results we cannot conclude that carbides have been completely eliminated through the whole thickness because the XPS technique is only sensitive to the surface of the films.

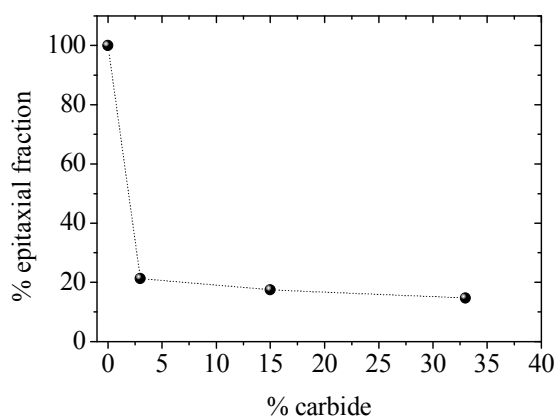


Fig. 7-12 Representation of percentage of epitaxial fraction in MOD-CeO₂ on YSZ single crystal on percentage of carbide retained from samples processed at different atmospheres.

Concerning Ce(3d) spectra we observe that Ce⁴⁺ is the main oxidation state in all samples, however slight contribution of Ce³⁺ from samples grown in Ar/H₂ and Ar/H₂/H₂O atmosphere has been detected, indicated by arrows in Fig. 7-13. For these samples it was determined the percentage of Ce³⁺ following the quantitative approach described in section 2.1.3.1. We have obtained that sample grown in Ar/H₂ contains 10% of Ce³⁺, sample grown in Ar/H₂/H₂O contains 7% of Ce³⁺ and in sample grown in O₂ followed by Ar/H₂ contains <2% of

Ce³⁺. It is interesting to note that samples grown in Ar/H₂ and Ar/H₂/H₂O atmospheres we previously identified the presence of carbide whereas sample grown in O₂ followed by Ar/H₂ does not. From these results it has been computed the ratio carbide : Ce³⁺ in order to find out if all carbide are bound to Ce³⁺ specimen (Ce₂C₃). In both cases we obtained higher content of carbide than the expected by evaluating the stoichiometric ratio in Ce₂C₃. Therefore, we have proposed that carbide specimen might be bound to Ce³⁺ and Ce⁴⁺.

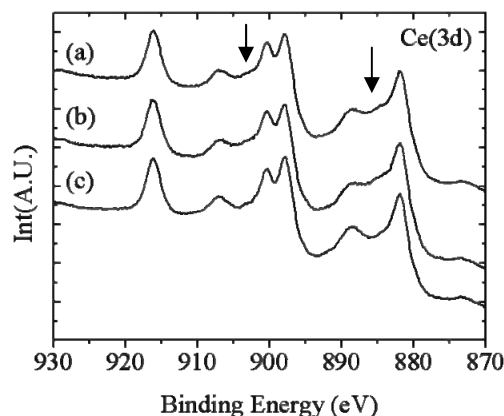


Fig. 7-13 Ce(3d) XPS spectra of MOD-CeO₂ film on YSZ single crystal grown at 900°C for 8 hours in Ar/H₂ (a) in Ar/H₂/H₂O (b) and in O₂ followed by Ar/H₂ (c).

Fig. 7-14 shows the corresponding O(1s) spectra. Main peak is around 529.7 eV, due to lattice oxygen. It is very similar to the reported value for pure CeO₂ [220]. The shoulder peak at about 532.2 eV, as already mentioned in section 6.3.2.4, originates from a combination of a number of species, including surface hydroxyl groups and adsorbed water. It results from the exposure of the samples to air. Thus, from O(1s) spectra, gas processing atmospheres do not cause any remarkable difference.

The combination of these probes allows us to confirm the inefficiency of using only a slightly oxidizing processing atmosphere to enhance mobility to obtain fully epitaxial growth of CeO₂ film.

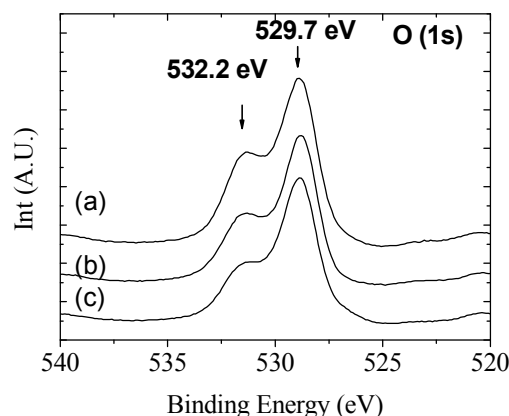


Fig. 7-14 O (1s) XPS spectra of CSD-CeO₂ film on YSZ single crystal grown at 900°C for 8 hours in Ar/H₂ (a) in Ar/H₂/H₂O (b) and in O₂ followed by Ar/H₂ (c).

In summary, it can be concluded from XRD and AFM investigations that CeO₂ grown in Ar/H₂/H₂O or Ar/H₂ atmospheres resulted an untextured film exhibiting a granular surface. These results have been correlated by carbon impurities detected by XPS analysis which probably hinders mobility in CeO₂ lattice blocking the epitaxial growth. Using the two step process, low temperature O₂ anneal followed by Ar/H₂ growth, the carbide content from the surface was minimized. It is very likely that pure oxygen atmosphere enhanced the movement of grain boundaries simultaneously by favouring the elimination of carbon. However, from XRD θ -2 θ scan and pole figure measurements and RHEED images it was observed that still some fraction of the film remained randomly oriented which suggested that carbon throughout the film thickness has not been successfully eliminated. The presence of carbon-containing species on or near the surface can inhibit the epitaxial growth of subsequent YBCO layer since underlying layer is not completely epitaxial. Therefore, these growth conditions make this buffer layer not suitable for YBCO CC- fabrication.

7.4 Influence of precursor solution on the final film quality

The presence of impurities (water, acids, C_xH_x, C_aH_bO_c) is one of the main drawbacks of the chemical methodologies, giving final oxide films with a substantial decrease in their properties, as we previously observed in the preparation of TFA-YBCO and now in CeO₂ films. Thus, the search for chemical precursors that produce films with a lower content of impurities

and good reproducibility is an area of permanent interest in the field of the synthesis of metal oxide films.

Here, we proposed the replacement of acetate precursors for propionates by modifying the solvent: glacial acetic acid has been replaced by a mixture 1:1 of propionic acid and isopropanol (see section 3.3.3.2). They give a stable solution for a long time (~ 3 months versus 2 days of acetic acid based solution). The comparison of XRD θ -2 θ scan obtained for CeO₂ films derived from both acetic acid and propionic acid is shown in Fig. 7-15. These scans indicate the presence of (*h*00) peaks for CeO₂ films fabricated from both solvents. The CeO₂ film fabricated from propionates displays higher intensity of (200) peak and, in addition, it does not show (111) texture reflection. We calculated the percentage of epitaxial fraction from (400) CeO₂ Bragg line reflection by using as a reference specimen MOD-CeO₂ processed in O₂ using acetic acid as solvent. We obtained ~38% of epitaxial fraction. Even though the epitaxial fraction has been improved from original specimen (~19%), it is clear that further investigation has to be carried out.

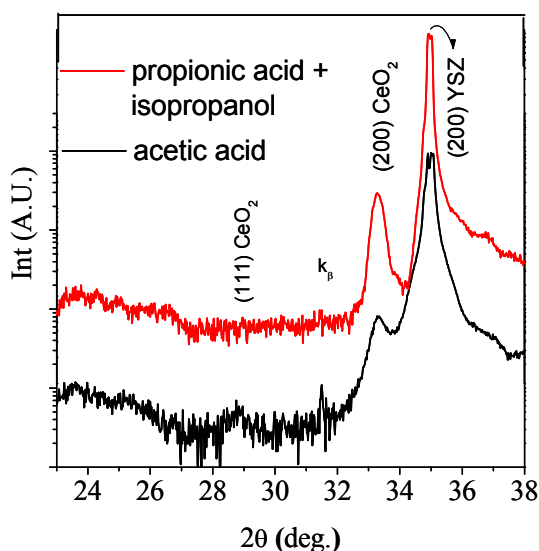


Fig. 7-15 (a) $\theta/2\theta$ scan of MOD- CeO₂ buffer layer on YSZ single crystal grown at 900°C for 8 h in Ar/H₂, from new solvent propionic acid and isopropyl alcohol (in red), and from glacial acetic acid (in black).

AFM image of CeO₂ film derived from new precursor solution, shows a uniform general appearance with fine grain size which have a globular shape (~15% of flat grains), Fig. 7-16 (a). The morphology actually appears very similar to that of CeO₂ films presented earlier, Fig. 7-7 (a). When surface texture was investigated using RHEED we observed clear spots with a high background, indicative of an inhomogeneous surface (random and good oriented grains) Fig.

7-16 (b), being in well agreement with partially epitaxial film detected from XRD θ - 2θ scan analysis. We demonstrate that just replacing acetates by propionates precursors, keeping Ar/H₂ atmosphere, ceria surface have changed from untextured to partially textured. This experimental result corroborates the importance of precursor choice because it can drive the microstructure and properties of the film, as we already introduced in section 1.2.3.1.

We suggest that propionic acid and isopropanol solvents besides increasing lifetime solution, may help to promote a decomposition pathway of organic precursor through formation of propylene as a reaction product. As a result, it is likely that this controlled decomposition favours the elimination of carbon content, and therefore, we assume that exist a reduction of the activation energy (Q) associated to grain boundary migration (recall Eq. 7-2). This appears to be the reason of slightly enhancement of epitaxial fraction of CeO₂ (38% vs 19%).

However, since there is room to improve CeO₂ film quality, in the next section we are going to work on modifying this 'new' precursor solution.

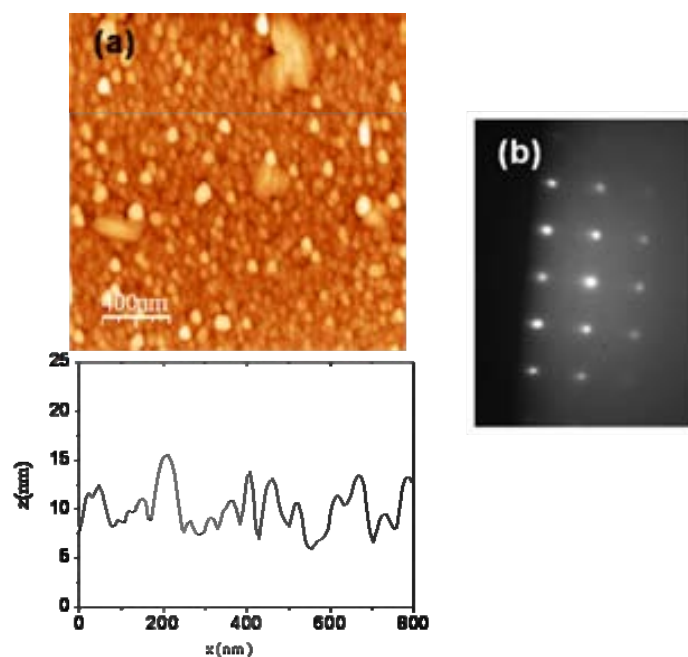


Fig. 7-16(a) AFM image of CeO₂ buffer layer on YSZ single crystal deposited from propionic acid and isopropyl alcohol precursors. Rms (2 x 2 μ m scan) = 3.2 nm. Profile scan of the previous AFM image showing granular surface morphology and (b) RHEED pattern along the $\langle 100 \rangle$ substrate direction.

As a final remark, it is important to note that recently promising results on nitrates-based precursors have been obtained, also in our laboratory [221]. Little research has been done on producing films from nitrate solutions because of several problems, including the hydroscopic nature of the reagents, the necessity of decomposing nitrates from the film during heat treatment, and difficulty in getting the solution to wet the oxide substrate. However, the addition

of polyvinyl acetates (PVA) makes the solution viscous enough to form a soaplike film and no drop off in YBCO performance has occurred. Further investigation is now on the way.

7.5 Effect of dopant

During the past 10 years, Gd-doped ceria oxides have been of special interest because of their applications to high-temperature fuel cells and oxygen sensors and there are several books and numerous review articles that cover this topic [222,223,224,183]. Recently, other authors have chosen this film as a promising buffer layer for YBCO coated conductor with the aim of avoiding crack formation of CeO₂ [225]. However, J_c value of TFA-YBCO on MOD-Gd doped CeO₂/Ni tape was about 10^5 A/cm² at 77K [226]. But in thesis, the aim of doping ceria is the enhancement of grain boundary mobility through oxygen vacancies formed by charge compensation favoring the elimination of both carbon contamination and grain boundaries in the nanocrystalline film [38,211].

7.5.1 Gadolinium doping in CeO₂

The first purpose of this work was to synthesize and optimize gadolinium-doped ceria cap layer on YSZ monocrystalline substrates, as a model system in view of the development of coated conductor architectures based on LZO (pyrochlore)/Ni-NiW substrates, by chemical solution deposition [227]. The results on the structural and morphological properties and also surface chemical modification will be presented and discussed in this section.

7.5.1.1 Optimization of Gd- content

In choosing the right amount of dopant, we must consider solubility data to obtain a true solid solution with cubic fluorite structure and preserve good lattice matching with YBCO. Fluorite structure is very tolerant to dissolution of lower valent metals above 40% [228,215], there is, however, a lot of contradicting information in the literature about the solubility limits.

Therefore, in order to investigate the range of compositions in which good epitaxial growth is obtained, we prepared Ce_{1-x}Gd_xO_{2-x/2} solid solution films with a thickness of 30 nm, henceforth indicated as CGO. They have been fabricated on YSZ single crystal substrates with different Ce and Gd compositions following the procedure described in section 3.3.3.3, i.e, 900°C for 8h in Ar/H₂ atmosphere, in which propionic acid and isopropanol were used as common solvents. From now, samples will be identified in accordance to the percentage of

gadolinium content, thus $x=0.001$ as CGO01, $x=0.01$ as CGO1, $x=0.1$ as CGO10, $x=0.2$ as CGO20 and $x=0.4$ as CGO40.

7.5.1.1.1 Structural characterization

It is very important to mention that from now to the end of this Thesis XRD analysis have been performed in a PHILIPS PW 3710 MRD from ‘Serveis Científico-tècnics de la Universitat de Barcelona (see section 2.2.1).

The results from XRD θ - 2θ scan indicated that the films were grown with c-axis perpendicular to the surface of the substrate for all compositions here studied ($x=0.001$, $x=0.01$, $x=0.1$, $x=0.2$ and $x=0.4$). For example, in Fig. 7-17 (a) it is shown a typical XRD θ - 2θ scan of a CGO10 film. The peaks at 34.93° and 73.80° are reflections associated with the substrate YSZ (200) and (400) respectively as well as the reflections identified as K_β in the θ - 2θ scan in Fig. 7-17 (a). In addition to the substrate peaks, only two diffraction peaks from the film are observed at about 33.17° and 69.60° , which corresponds to the (200) and (400) reflection of CGO, proving some epitaxial growth. The broad feature around $2\theta \approx 53^\circ$ is an instrumental artifact. Fig. 7-17 (b) shows the evolution of $I(200)$ of CeO₂ Bragg line reflection with percentage of Gd³⁺ incorporated. Maximum degree of epitaxy was observed for CGO10 film.

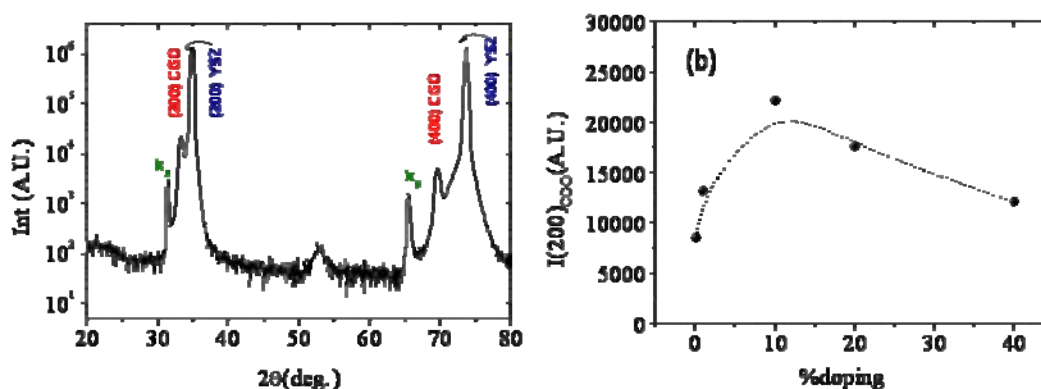


Fig. 7-17 (a) Typical XRD θ - 2θ scan for the 10% Gd-CeO₂ epitaxial film on YSZ single crystal. The 2θ scan indicates a single phase and highly oriented with cubic fluorite structure like that of pure CeO₂. bl-857 (b) (200) CeO₂ intensity reflection peak from θ - 2θ scan dependence on Gd percentage doping.

We have quantified the percentage of epitaxial fraction in CGO solid solutions by integrating (400) CeO₂ peak reflection from θ - 2θ scan, as we described in section 7.3.1. It is very important to mention that the reference sample employed to calculate the epitaxial fraction in the previous samples has been changed. Some doped CeO₂ films displayed higher epitaxial fraction than pure CeO₂ film processed in O₂. We anticipate that Zr-doped CeO₂ film grown in

O₂ atmosphere displays maximum epitaxial fraction and therefore it has been adopted as reference sample. This sample will be further characterized in section 7.5.2.

Table 7-III shows that the epitaxial fraction increases on incorporation of Gd³⁺ reaching a maximum for 10% of Gd³⁺ but then, decreases again at higher Gd³⁺ concentration, following, as we expected, the I(200) Bragg line trend found in Fig. 7-17(b). We would like to remark that doping CeO₂ with 10% of gadolinium represents an improvement in the epitaxial fraction of a factor ~ 2 from undoped CeO₂ film.

Table 7-III List of the percentage of epitaxial fraction for CGO films

Sample	% epitaxial fraction (± 2)
CeO ₂	39
CGO01	39
CGO1	38
CGO10	77
CGO20	44
CGO40	24

For CGO films with percentage of epitaxial fraction lower than 44% we have observed bimodal ϕ -scan line shape, revealing the existence of grains with different degree of texture (recall 7.3.1). Instead, CGO10 solid solutions with 77% of epitaxial fraction offers a ϕ -scan from (202) reflection with single and narrow contribution with $\Delta\phi = 1.4^\circ$, see Fig. 7-18.

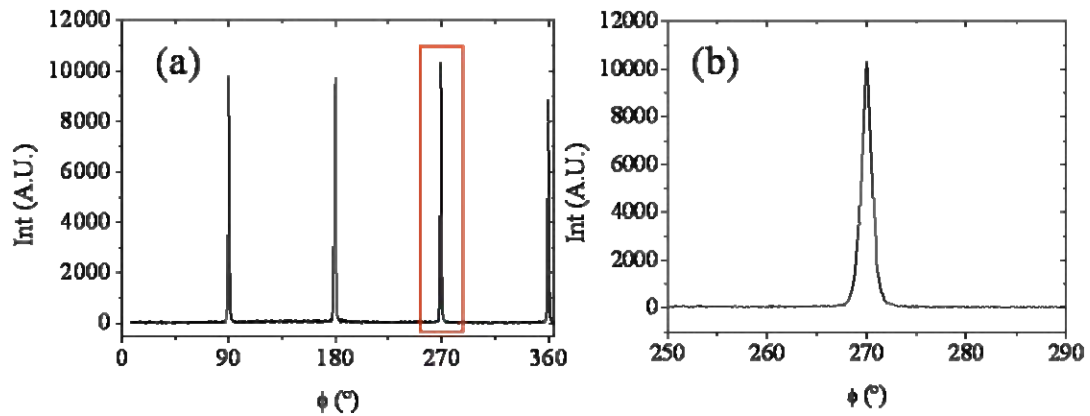


Fig. 7-18 (a) ϕ -scan taken through the (202) reflection corresponding to a CGO10 film grown on YSZ single crystal substrate. (b) detail of one of the four peaks observed in (a)

This effect on epitaxial fraction depending on the percentage of gadolinium content is the first indication that incorporation of gadolinium on CeO₂ lattice modifies the activation energy for grain boundary mobility. The dramatic increase of epitaxial fraction from 1 to 10% of gadolinium is believed to be due to oxygen vacancies formed when Gd³⁺ is incorporated in CeO₂ lattice, as predicted Eq. 7-4. By increasing defect concentration (V_o'') it is likely that more available jumps sites will be available minimizing the activation energy for grain boundary mobility. Low gadolinium content, 0-1%, might generate few oxygen vacancies to move carbon trapped in grain boundaries and we suggest that C diffusion still governs the mobility of atoms across the grain boundary obstructing the transport necessary to achieve epitaxial film, as was previously described in undoped MOD-CeO₂ films.

With increasing Gd content above 10% the decrease in the epitaxial fraction is not explainable in these terms. For a better understanding of the effect of Gd content on lattice and grain boundary mobility, further structural and morphological analysis are required. Therefore, it was calculated the lattice parameter for all Gd concentrations here investigated as could be seen in Fig. 7-19. Lattice parameter was determined from the (400) CeO₂ Bragg line reflections of XRD θ -2 θ scans.

Like a simple solid solution CGO lattice parameter should follow Vegard's rule, i.e., a linear relationship between lattice parameter and the concentration of the solute. Hence, for comparison, the theoretic Vegard line for Gd³⁺ [229] is also shown in Fig. 7-19. We point out two observations: Firstly, the smaller lattice constant detected even for pure CeO₂ films. This modification can be easily understood considering the misfit with the underlying substrate, YSZ ($a=5.14$ Å) $\epsilon=4.9\%$. To accommodate such large lattice mismatch, misfit dislocations are probably formed at the interface leading to a semicoherent interface. These results contrast with

perovskite multilayers in which we observed a fully relaxed epitaxy (see Fig. 5-13). Secondly, the calculated lattice parameters fit ‘well’ to Vegard’s law for Gd³⁺ ≤ 20 %, but for above 20 % the lattice constant decreases slightly as the Gd³⁺ content increases Fig. 7-19(b). This is in agreement with the report of Tianshu and coworkers [230] who observed similar deviation of the Vegard’s law at Gd³⁺ concentrations of 25% in a comparative study on the effect of Gd³⁺ content on CGO ionic conductivities.

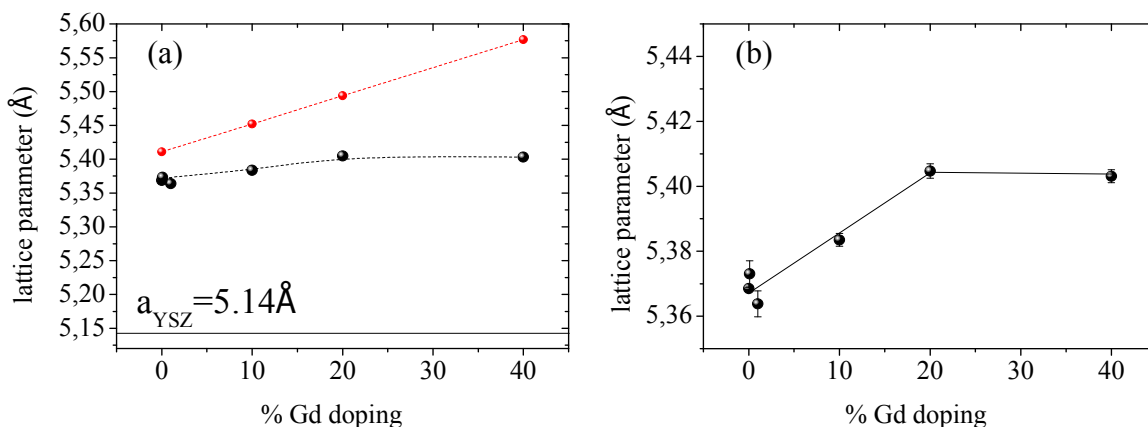


Fig. 7-19 Gd content dependence of lattice constant for CGO cap layer on YSZ single crystal grown at 900°C in Ar/H₂ for 8h (black) compared with Theoretical Vegard’s rule (red). (b) Magnification of experimental dependences of lattice parameter on Gd content.

However, it is interesting to note that other authors have observed differences in the compositions corresponding to the maximum lattice constant depending on the sample preparation methods and sintering conditions [228,231,232]. Nonetheless, based on [183] it seems reasonable to assume that the saturation value above 20% determines the solubility limit and thus, above 20% ceria-based solutions might have a mixed structure or a transition structure combined with both cubic type (C-type polymorphism [197]) resulting from the segregation of gadolinium atoms (Gd₂O₃), and fluorite type [230,213]. In Fig. 7-20 it is shown a representative fluorite –type structure and C-type structure.

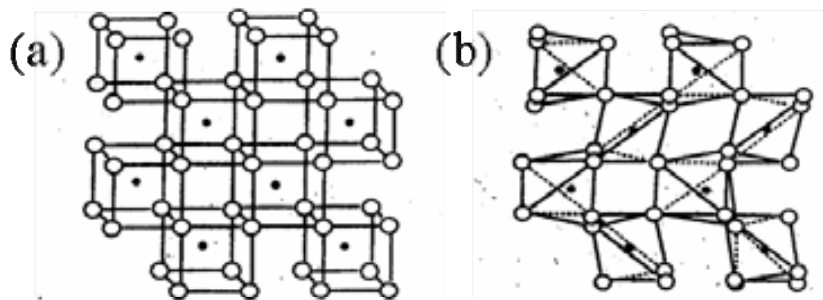


Fig. 7-20 Schematic structure of (a) fluorite-type RO₂. (b) C-type R₂O₃. The solid dots indicate the metal atoms [233].

Unfortunately, XRD analysis cannot confirm the development of C-type structure in ceria-based solutions due to the close relationship between Gd₂O₃ C-type and CeO₂ fluorite structures. It might be more reasonable to suppose that for the composition $x > 0.2$, the lattice constant calculated from XRD patterns provides an average value arising from the fluorite solid solution (dopant ionic size tends to expand the unit cell) and the microdomains of C-type Gd₂O₃ (attractive defect interaction tends to contract the unit cell, it has been proposed the formation of a cluster composed of oxygen vacancies and Gd ions [234]).

For 20% of Gd³⁺ concentration, even though lattice parameter has been increased from 10% of Gd³⁺, it is still altered in comparison with theoretic Vegard's rule. In addition, we recall that from XRD θ - 2θ scan it was deduced a decrease in the epitaxial fraction for this particular composition (see Table 7-III). From these results it is derived that exist a blocking contribution that obstructs (in less extension than CGO40 film) the atomic mobility. Based on reported work we proposed that electrostatic interaction between solute and vacancy could interfere the oxygen diffusivity [213,216]. This regime was already introduced in section 7.2 and it is known as solute drag regime (see 7.2.1). Moreover, these interactions are considered as possible driving force for segregation at higher dopant concentration [235], being consistent with the hypothesis formulated above for CGO40 composition.

In conclusion, the above structural data hints 10% of Gd³⁺ as the most suitable concentration for high quality CGO epitaxial growth. However, for the application of CGO films as cap layer in coated-conductor architectures, the control of surface topography becomes essential. Thus, AFM were performed in these solid solutions. At the same time, this analysis will be complemented with XPS investigations and both would provide more information on the role of Gd³⁺ on CeO₂ films

7.5.1.1.2 Surface morphology characterization

From the AFM images carried out on CGO films shown in Fig. 7-21, we investigated the effect of dopant concentration on its surface morphology. Qualitatively we observed that surface morphology for CGO10, Fig. 7-21(c), exhibits larger and flatter grains in comparison with CGO01, CGO1, CGO20 and CGO40, Fig. 7-21(a),(b),(d) and (e) respectively .

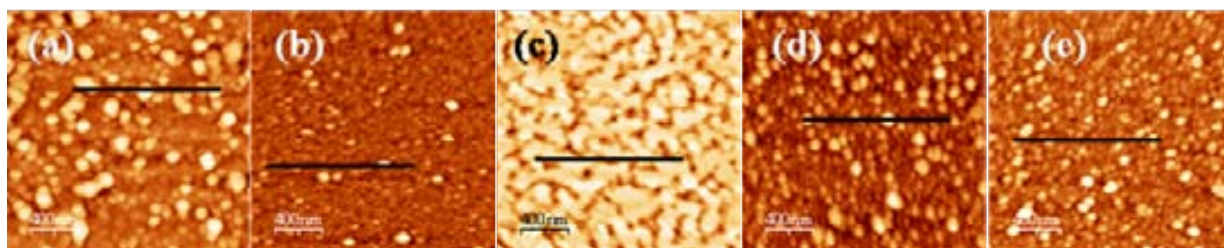


Fig. 7-21 Typical AFM images for CGO solid solution after growth under Ar/H₂ atmosphere (a) $x=0.001$ with a rms=5.6nm, (b) $x=0.01$ with a rms=3.4nm, (c) $x=0.1$ with a rms=4.1 nm, (d) $x=0.2$ with a rms =5.2 nm and (e) $x=0.4$ with a rms=2.2 nm. The scan range is $2 \times 2 \mu\text{m}$.

This trend could be easily distinguished from the corresponding profile scans performed in these topographic AFM images. In Fig. 7-22 are displayed profile scans performed from CGO01, CGO1, CGO20 and CGO40. In Fig. 7-23(a) it is illustrated the profile scan from CGO10. Profile scans in Fig. 7-22 revealed rounded grains and small grain size (their size ranged from $46-61 \pm 2$ nm) with number of small humps indicating a very rough surface. This result resembles the well-known granular surface morphology previously observed on undoped CeO₂ thin films, Fig. 7-7. By contrast, CGO10 surface exhibits much bigger and (001)-flat grains (~ 200 nm) Fig. 7-23 (a). The valleys are very clear, and the depth is about 10-15 nm. This hillock-like morphology seems comparable with the surface morphology reported in previous chapter for Ar/H₂/H₂O processed sputtering-CeO₂ films.

We have computed the percentage of atomically flat area for these set of samples by applying binarization operator and defining a height threshold around 1.5 nm (3 unit cells of CeO₂), as we described earlier in section 2.1.1. Percentage of atomically flat area for binary images displayed in Fig. 7-24 ranges from ~ 13 to 18%. For CGO10 films, Fig. 7-23 (b), $\sim 71\%$ of surface area is occupied by flat terraces, only 10% less than sputtering CeO₂ films and it is far more than the other CGO solid solutions here reported. In this case, we speculate that the minimization of (001) surface energy in Ar/H₂ atmosphere could be due to the incorporation of gadolinium. In reality, we suggest that large concentration of oxygen vacancies created by the incorporation of gadolinium reduces the binding energy of surface oxygen ions in agreement with results from atomistic computer simulations [190,191]. However, a more detailed analysis should be required to confirm this assignment.

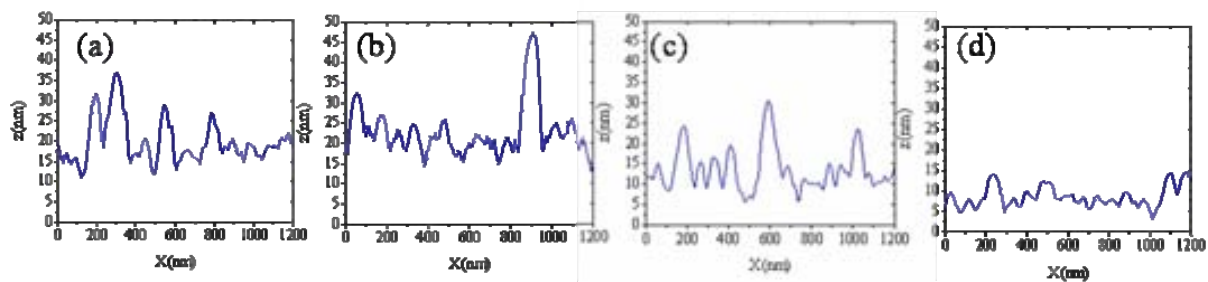


Fig. 7-22 Height profile of AFM topographic images for CGO films with different content of Gadolinium processed under Ar/H₂ atmosphere (a) CGO01, (b) CGO1, (c) CGO20 and (d) CGO40.

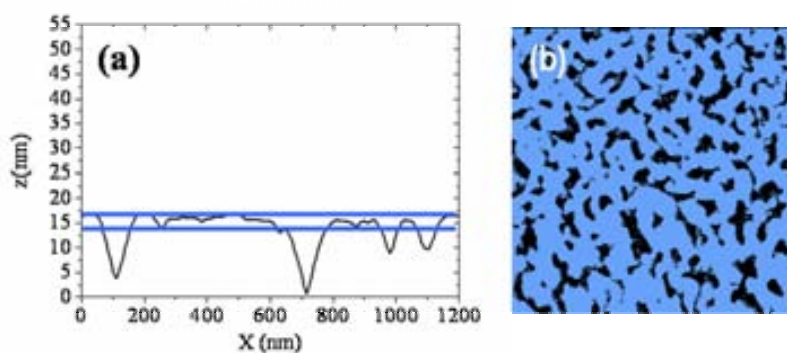


Fig. 7-23 (a) Profile scan of surface ceria 10% doped gadolinium, grown at 900°C for 8 h in Ar/H₂ performed on Fig.7-12(c). Large (001)-terraces of ~200 nm are clearly depicted.

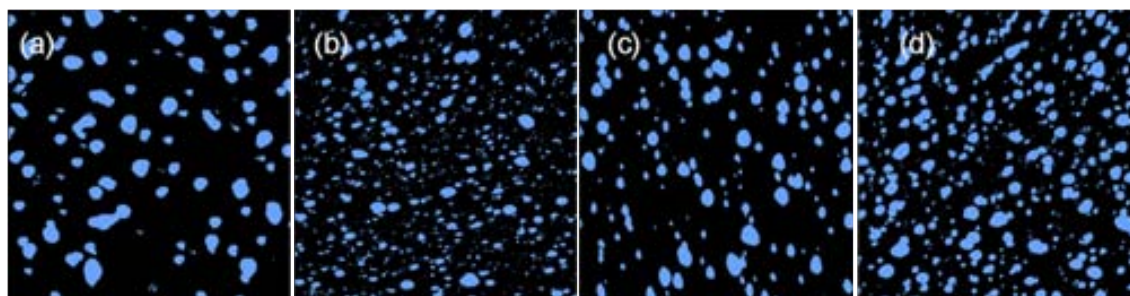


Fig. 7-24 Binary images of the AFM shown in Fig. 7-21 (a) CGO01, (b) CGO1, (c) CGO20 and (d) CGO40.

Before concluding this section we would like to stress the different grain size and morphology found for Gd-CeO₂ solid solution here prepared. Since the driving force for grain growth is the elimination of interfacial energy between grains [207], and grain size distribution for CGO1, CGO01, CGO20, CGO40 is relatively unchanged (recall 46-64 nm versus 200nm in CGO10), it is clear that in these CGO solid solutions impurity effects hinders boundary migration. The nature of these impurity effects could result from sample preparation, i.e. carbon, solute segregation or from solute-vacancy interaction. These results are consistent with XRD analysis presented above in which we detected very low degree of epitaxy.

These proposed impurities have been also detected for other authors in ionic conductivity studies from related systems. For example, Wang and Nowick [236] detected grain boundary resistance at lower dopant concentration due to SiO₂ impurities attributed to sample preparation. On the other hand, Chiang and coworkers [237] found changes in bulk conductivity because dopant was extracted to grain boundaries.

By collecting all data from XRD and AFM investigations of MOD-CGO solid solutions, we have found that the percentage of atomically flat area becomes higher when notably increase the epitaxial fraction. It is interesting to remark that this relationship has been already established for undoped CeO₂.

At this point it is very important to highlight that based on XRD and AFM investigations we have obtained similar film quality doping CeO₂ with 10% of gadolinium in Ar/H₂ atmosphere as undoped CeO₂ film processed in pure oxygen with the advantage that reducing atmosphere could be transferred to Ni substrates for coated conductors fabrication. Moreover, based on preliminary studies of the group on both MOD-CeO₂ [38] and sputtering-CeO₂ (chapter 6) in which we found that for high quality TFA-YBCO growth it was extremely important that cap layer displayed high epitaxial fraction and atomically flat terraced surface, we establish that CGO10 solid solution is the most feasible cap layer for subsequent YBCO growth. Consequently, the rest of CGO films which display rounded grains and have low percentage of epitaxial fraction (< 50 %) are ruled them out as a potential cap layers for YBCO growth, i.e. CGO01, CGO1, CGO20 and CGO40. In any case, detailed analysis of TFA-YBCO growth on MOD-CeO₂ cap layers will be exposed in chapter 8.

To further investigate the nature of impurities, XPS measurements were carried out because these impurities should modify cerium and oxygen environment and this, in turn, could be detected by shifts in its binding energy (BE). Results are presented in the following section.

7.5.1.1.3 Chemical surface composition

We present here, XPS measurements performed for the CGO films above studied, and which have been compared with undoped ceria.

We acquired data for the O(1s), C(1s) and Ce(3d) core levels with an unmonochromatic Mg K_α source. Gd(3d) emission spectra appears at a binding energy higher than 1200 eV, thus we registered O(1s), C(1s), Ce(3d) and Gd(3d) with Al K_α source (1486.6 eV) because MgK_α is not sufficiently energetic (1253.6 eV). The register with Mg source allows us to compare Ce(3d) feature with previous analysis of undoped Ce(3d). On the other hand, acquiring data with Al source allows us to examine Gd and quantify the relative atomic percentage. XPS data processing was carried out following description in section 2.1.3. Like in previous measurements, grown samples have been exposed to air before being introduced into the analytical chamber.

C(1s) spectra are shown in Fig. 7-25, O(1s) spectra are shown in Fig. 7-26, Ce(3d) spectra are shown in Fig. 7-27, and finally Gd(3d) spectra are shown in Fig. 7-28.

C(1s) spectra, show the main peak at 285.4 eV originated from the C contamination, Fig. 7-25. Undoped ceria, as we already investigated in section 7.3.2, developed an additional and intense peak at 282.6 eV assigned to Ce-C bond. Gd-doped CeO₂ with a concentration of 20% and 40% also present this low binding energy feature, indicating that C has not been effectively removed, Fig. 7-25 (c-d). On the contrary, for CGO10 film C_{282.6} peak is not detected indicating no content of carbide in the surface, Fig. 7-25 (b). Carbide content quantification has been determined by calculating the atomic percentage of C, Ce, O and Gd for the different solid solution composition by using the following sensitivity factors: 0.25, 12.06, 0.66, and 12.93 respectively (see 2.1.3.1). For CGO20 film, the carbide content is 3% and for CGO40 film 10%. We anticipate that TEM analyses have been carried out for CGO10 film to investigate if carbon impurities were in fact fully eliminated throughout the film thickness. Results are presented further on in this section.

Even though carbide content detected for these solid solutions are lower than undoped CeO₂ (see 7.3.2), its presence suggests that grain boundary mobility is still blocked and therefore film is not completely epitaxial being consistent with XRD and AFM investigations presented above.

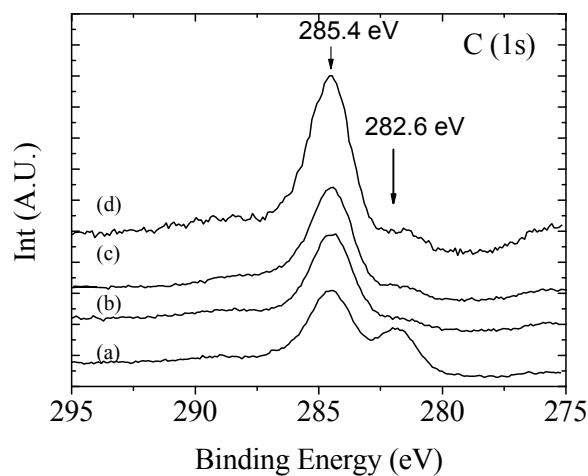


Fig. 7-25 Carbon 1s spectra of CGO grown on YSZ single crystal at 900°C in Ar/H₂ for 8 h. (a) for pure CeO₂, spectrum (b) for x=0.1, (c) for x=0.2 and (d) for x=0.4.

Fig. 7-26 shows the corresponding O(1s) spectra. The binding energy of the O(1s) around 529.0 eV is due to lattice oxygen in ceria film. The shoulder peak at about 532.5 eV originates from hydroxyl groups and water adsorbed on the surface due to environment. It is interesting to note that for CGO40, the O(1s) main peak develops a shoulder at higher binding energy, 530.5 eV, Fig. 7-26 (d). This value is close to the O(1s) binding energy of 530.7 eV measured for the Gd₂O₃ and Ce₂O₃ compounds [105]. This is because Gd contribution into the CeO₂ lattice becomes important, in accordance with modified lattice parameter found above Fig. 7-19(a).

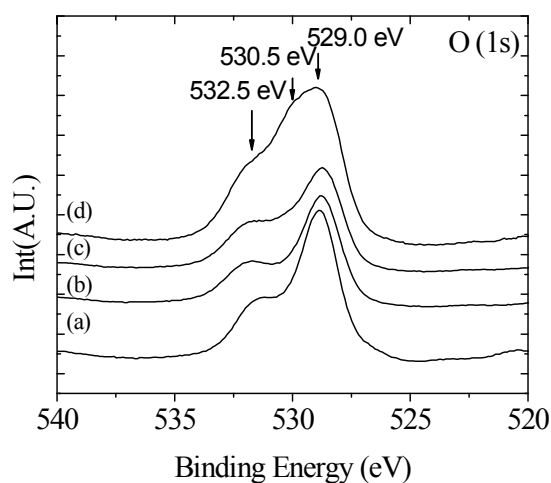


Fig. 7-26 O1s spectra of CGO grown on YSZ single crystal at 900°C in Ar/H₂ for 8 h. (a) for pure CeO₂, spectrum (b) for x=0.1, (c) for x=0.2 and (d) for x=0.4.

Gd contribution is also observed in Ce(3d) spectra, in Fig. 7-27. Ceria surface is fully oxidized with no significant changes except for CGO40, Fig. 7-27(d). In this case, cerium environment has been slightly changed. Again, it is due to the Ce³⁺ that appears as a shoulder in Ce(3d) spectra (indicated by vertical arrows in the picture). Ce³⁺ concentration has been computed following the procedure already described in 2.1.3.1 and we obtained a concentration close to ~19%. In this case, based on O1s and C1s spectra results it is suggested that Ce³⁺ could exist either in the form of Ce₂O₃ or Ce₂C₃. The mechanism by which the incorporation of significative amount of Ce³⁺ has been occurred is not clear and further investigation is required to clarify its origin.

From Gd (3d) spectra, Fig. 7-28, it is observed an increase in peak area from CGO10 to CGO40. In order to strictly determine if this increase is proportional to the amount introduced in the precursor solution, it has been investigated the dependence of Gd/Ce ratio with theoretical Gd³⁺ concentration. Lineal dependence means true solid solution, otherwise it is a clear indication that segregation occurs. Unfortunately, with three samples it is quite difficult to establish one of these two situations, see Fig. 7-29.

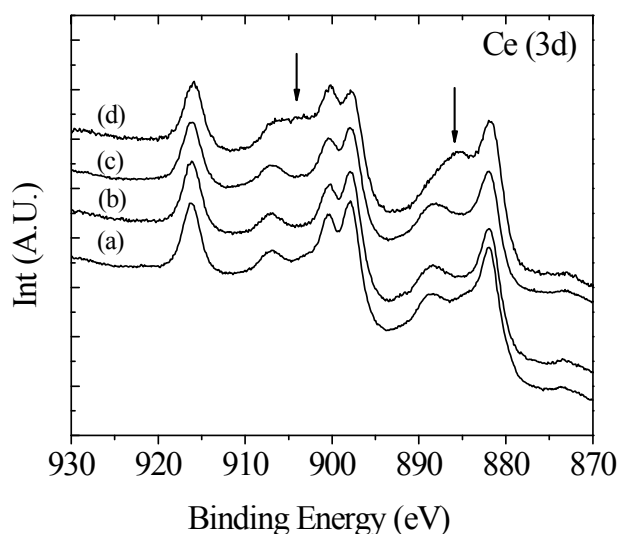


Fig. 7-27 Ce 3d spectra of CGO grown on YSZ single crystal at 900°C in Ar/H₂ for 8 h. (a) for pure CeO₂, spectrum (b) for x=0.1, (c) for x=0.2 and (d) for x=0.4, vertical arrows indicate the shoulder appeared as a consequence of Ce³⁺ concentration.

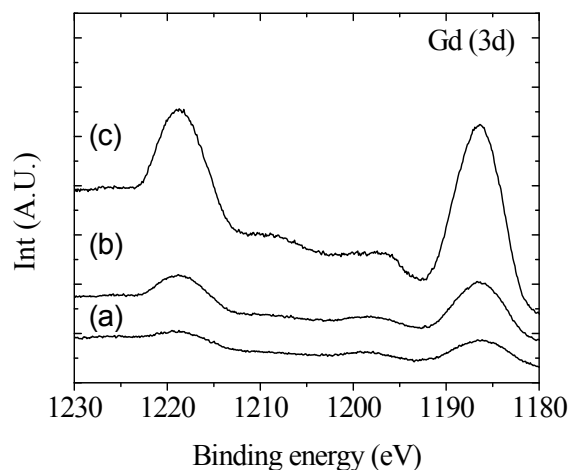


Fig. 7-28 Gd 3d spectra (Al K_α) of CGO grown on YSZ single crystal at 900°C in Ar/H₂ for 8 h. (a) for x=0.1, (b) for x=0.2, (c) for x=0.4.

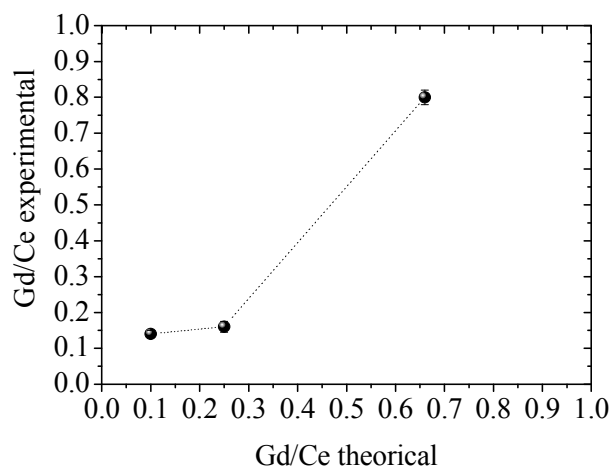


Fig. 7-29 Gd/Ce ratio correlation between experimental and theoretical values for Ce_{1-x}Gd_xO_{2-x/2} solid solutions with x=0.1, x=0.2 and x=0.4.

In conclusion, by XPS measurements we observed that CGO40 spectrum differed from the other analysed samples. Ce and O analysed elements displayed changes in peak shapes resulting of the overall 'charge' by which these elements are surrounded because of Gd. In particular we detected the formation of Ce³⁺ and carbide whereas for CGO10 and CGO20 solid solution, XPS peak shapes for Ce(3d) and O(1s) have not been modified from pure CeO₂, only for CGO20 it was detected traces of carbide (~3%).

Thus, it is clear that to enhance grain boundary mobility and simultaneously eliminate C impurities from MOD-doped CeO₂ films under reducing atmosphere, a compromise between the carbon content and the gadolinium concentration has to be reached. Gd³⁺ concentration higher than 20% results in dopant-vacancy interaction or even secondary phases segregation that disturb atomic mobility. Thus, these impurities coexist with carbon resulting in final CGO solid solution with low degree of epitaxy. A Gd³⁺ content lower than 10% does not provide enough oxygen vacancies to favour the elimination of carbon simultaneously with grain boundary area and again the final film quality is strongly degraded with an epitaxial fraction lower than 40%. In this study, we found that the threshold between both behaviours occurs at a gadolinium concentration ~ 10% which yields a high epitaxial fraction (~77%) and a atomically flat surface (70%), a promising characteristic for high quality YBCO growth. Thus, we will now focus in the study of surface texture and film microstructure of this CGO10 film.

7.5.1.1.4 Surface texture and microstructure of CGO10 films on YSZ single crystal substrate

To verify surface crystallinity of CGO10 film, RHEED patterns have been recorded (shown in Fig. 7-30). Here the diffraction picture contains slightly elongated spots indicative that the surface film is a transition between 3D to 2D. These results agree with the AFM images in which we detected large and smooth terraces (2D) and valleys between them (3D contribution), Fig. 7-21(c). Note that although we did not detect intense background contribution corresponding to grains randomly oriented, from XRD θ -2 θ scan we obtained that this sample is 70% epitaxial. In this case, intense signal for oriented grains disguises 30% of randomly oriented grains. Thus, for our samples, RHEED images complement XRD analysis but do not supply decisive texture information. On the contrary, we have seen that RHEED images are very useful to identify changes in surface morphology.

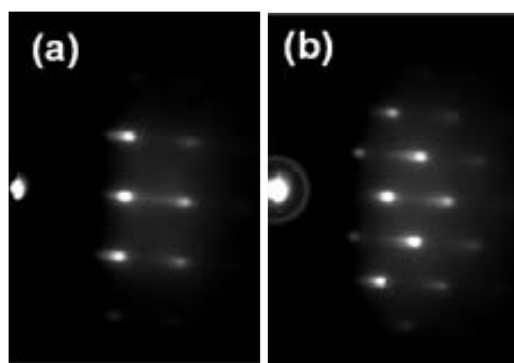


Fig. 7-30 RHEED pattern at 30 keV for a CGO10 cap layer on YSZ single crystal, (a) along the $\langle 100 \rangle$ of the substrate direction (b) along $\langle 110 \rangle$ of the substrate.

TEM analysis was carried out in order to corroborate the apparent changes film undergoes as detected by XRD, AFM and XPS. Indeed, from the cross sectional images displayed in Fig. 7-31 the terraced surface with grain sizes around 100-200 nm similar to those detected previously by AFM, Fig. 7-21(c), are strongly confirmed. Ledges making an angle of 45° to the film normal are also observed, which according to the $\langle 100 \rangle$ viewing direction may correspond either to the $\{111\}$ or $\{011\}$ planes. Fig. 7-31(c) is a characteristic $\langle 100 \rangle$ SAD pattern that includes YSZ demonstrating the cube on cube epitaxial relationship between the whole film and the substrate.

XTEM images also reflect the stabilization of (001) CeO₂ surface, as previously observed by AFM analysis for MOD-CeO₂ film processed in O₂ [38] and sputtering-CeO₂ processed in Ar/H₂/H₂O (previous chapter).

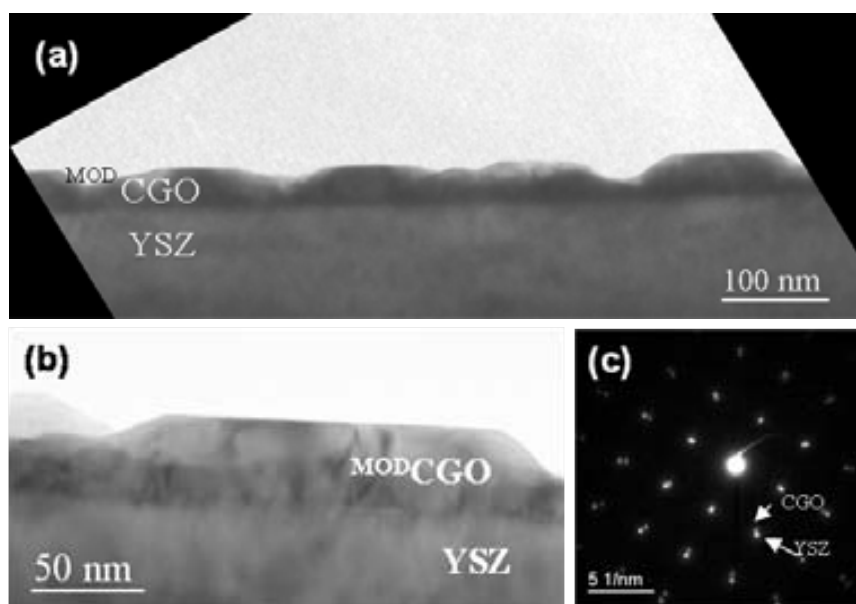


Fig. 7-31 (a) Low magnification XTEM image of a MOD-CGO10 film on YSZ single crystal viewed along the $\langle 100 \rangle$ direction. (b) Detail of (a) exhibiting a (001) terraced surface (c) corresponding SAD pattern

Deepen in a high resolution TEM images from this sample, despite in a general view the microstructure is well developed, some grain boundaries with atomic disorder still remain (Fig. 7-32(a)). This high resolution XTEM image shows a detail of two (00 l) oriented grains. Moiré fringes indicate the superposition of a third grain misoriented. C distribution for this region was studied by electron energy loss spectroscopy (EELS). Fig. 7-32 (b) compares EELS spectra obtained at a grain boundary and in the bulk. Whereas the bulk is free from C impurities, near the grain boundary low concentration of C still embed grain boundaries. This result contrast with C(1s) spectrum of XPS analysis corresponding of CGO10, Fig. 7-25, in which we did not

detect carbide content. However, this fact can be easily understood considering that C impurities detected by TEM were found far from the surface, whereas XPS is a surface analysis.

From these TEM images it has been exemplified why the epitaxial fraction obtained for CGO10 obtained from XRD analysis was only 70% (it remains 20% of fraction that should be improved). C detected by EELS mapping supports that carbon is still retained in grain boundaries and blocks the epitaxial growth of MOD-doped CeO₂ films as we earlier determined in MOD-CeO₂ films [38]

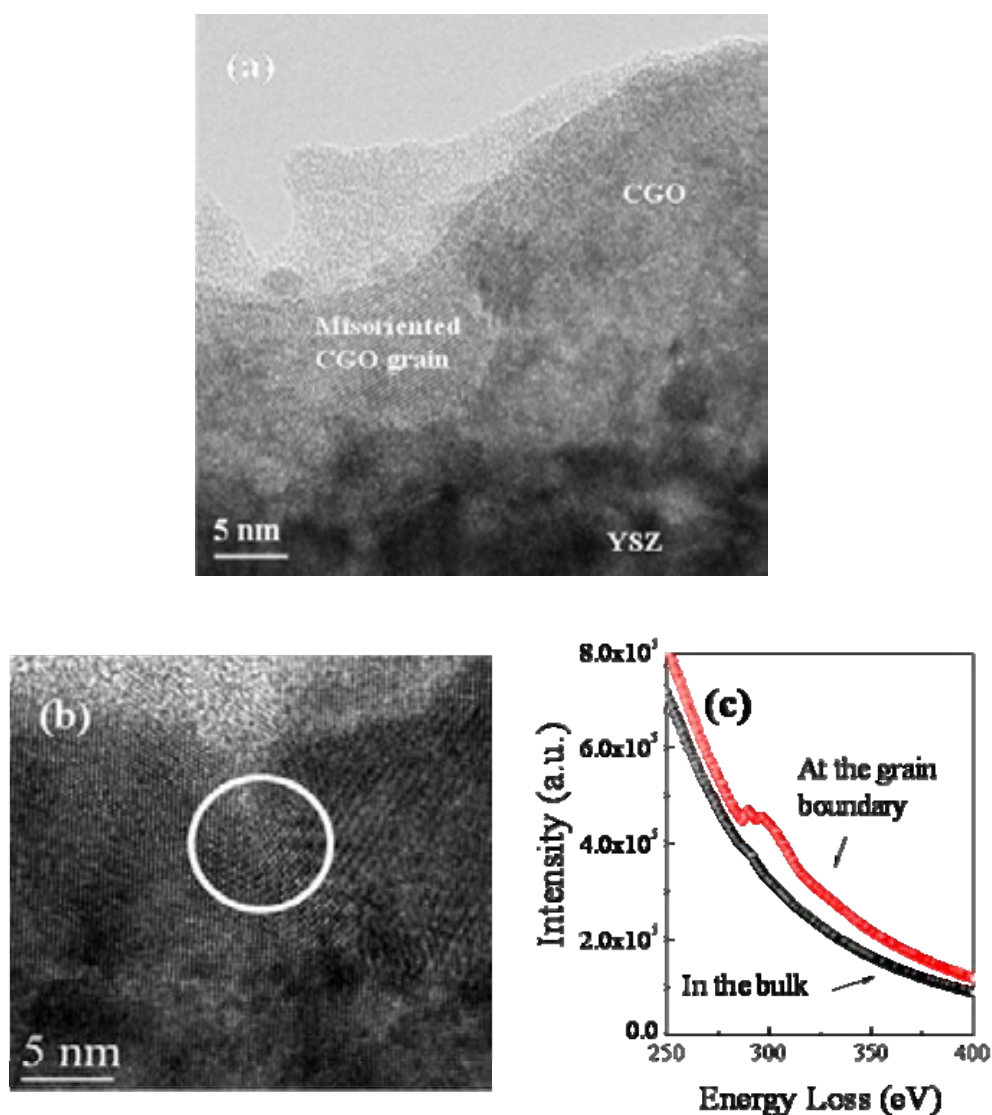


Fig. 7-32 (a) High-resolution XTEM image showing a detail of the grain structure at the topmost region of the film of MOD-10%Gd-CeO₂/YSZ film grown at 900°C for 8 h in Ar/H₂ atmosphere. (b) Detail of a grain boundary of two grains of CGO (c) Comparison of EELS spectra obtained from selected area in (b).

7.5.1.1.4.1 Effect of oxidizing atmosphere

Prompted by the remarkable improvement observed in undoped MOD-CeO₂ film quality processed in Ar/H₂ after oxygen processing due to the elimination of carbon and grain boundaries [38], we also grew CGO10 cap layer with a thickness of 30 nm in oxygen atmosphere, in order to verify if the remaining grain boundaries detected above by TEM could be eliminated and beyond 20% randomly oriented to achieve a highly (100%) epitaxial film.

10%Gd-doped ceria (CGO) on YSZ single crystal was grown using oxygen atmosphere at 900° C for 8 h following the heating profile described in Fig. 3-14(b). We would like to remark that CGO10 film has been synthesized from the same precursor solution as solid solutions described above (section 3.3.3.3).

From the area of (400) CGO peak reflection in XRD θ -2 θ scan, we calculated the epitaxial fraction using the same reference sample as previous doped-CeO₂ films: Zr-doped CeO₂ film grown in pure oxygen atmosphere. From this computation we obtained a value exceptionally high for the epitaxial fraction, 98%, therefore we considered it fully epitaxial. This confirms that when exposed to oxygen atmosphere the epitaxial fraction is being further improved. Actually, we expect that carbon impurities has been completely eliminated, a picture consistent with the previous work [38].

At the same time we have also studied surface morphology by RHEED and AFM techniques. From the AFM analysis, shown in Fig. 7-33, we estimated the percentage of atomically flat surface following the criterion that the height threshold is 1.5 nm. From processing binary image, Fig. 7-33(b), we obtained that 90% of surface area is occupied by flat grains. Additionally, height profile scan, Fig. 7-33 (c), describes (001) terraced surface with a size ranging from 200 to 500 nm. Therefore, from the viewpoint of cap layer applications, oxygen atmosphere has been improved the quality of this buffer in comparison with Ar/H₂ atmosphere, however, as we anticipated, this oxidizing atmosphere could not be transferred on coated conductors because it could oxidize them.

The streaky RHEED pattern in Fig. 7-34 is typical from 2D textured surface. We observe that the 3D contribution (rounded spots) detected in CGO10 processed in Ar/H₂ has completely disappeared, Fig. 7-30 . This result is in excellent agreement with AFM analysis and both reflects an atomically flat surface. Therefore it is observed that oxygen atmosphere further enhances atomically flat surface.

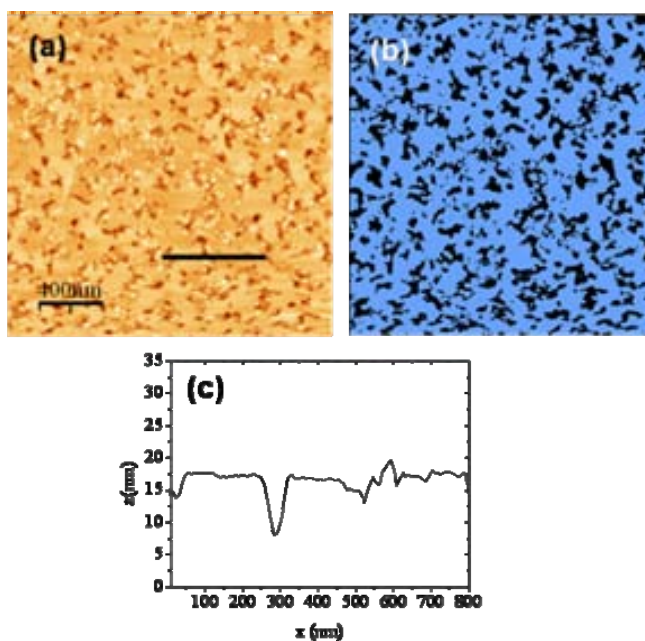


Fig. 7-33 AFM image exhibiting a terraced surface morphology with 90% of atomically flat area of CGO10 film grown on YSZ single crystal at 900°C in O₂ for 8 h.

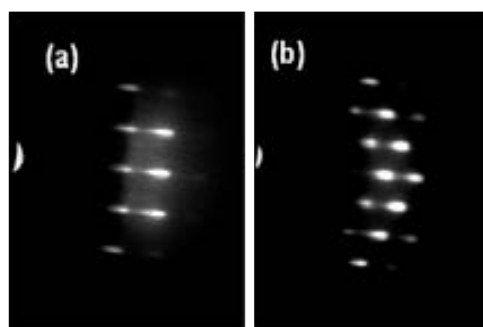


Fig. 7-34 RHEED pattern for a CGO10 cap layer on YSZ single crystal, (a) along the <100> of the substrate and (b) along <110> of the substrate.

In summary, the above results indicate that there exists an evolution to the elimination of grain boundaries (simultaneously with the elimination of C) correlated with an increase of the epitaxial fraction and enhancement of atomically flat surface. Therefore the correlation earlier exposed, first for undoped CeO₂ and then for CGO solid solutions, is again accomplished and illustrated schematically in Fig. 7-35. We have demonstrated that many parameters run in parallel to the elimination of grain boundaries: atmosphere, incorporation of dopant agent, concentration of dopant agent and impurities. In fact, by investigating the as mentioned parameters we have successfully demonstrated that the incorporation of 10% of Gd³⁺ in CeO₂ film considerably

improve its film quality. Considering that oxygen atmosphere has to be ruled out constrained by the oxidation of the metallic substrate, the most feasible conditions for CGO10 growth are: 900°C in Ar/H₂ atmosphere for 8h. However, in the following section will be investigated the influence of growth temperature and residence time at high temperature.

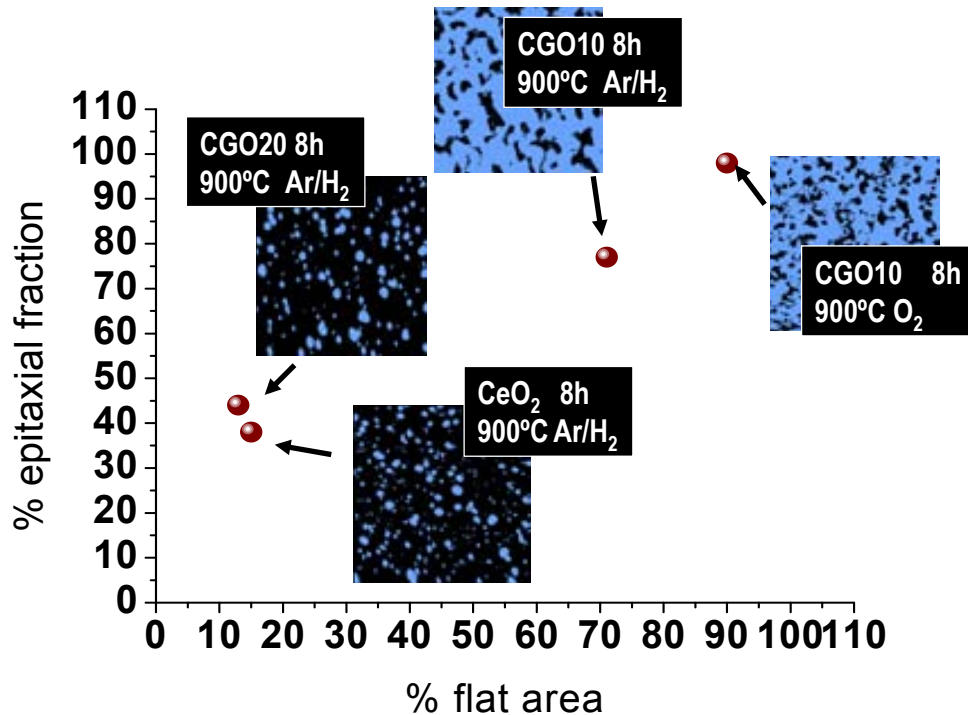


Fig. 7-35 Relationship between percentage of epitaxial fraction and percentage of atomically flat surface from CeO₂ and Gd-doped CeO₂ grown on YSZ single crystals under the same temperature and time conditions.

Before concluding this section we would like to mention that we have also carried out treatments of CGO10 film at 900°C for 8 h in Ar/H₂/H₂O atmosphere, based on the good results obtained in sputtering-CeO₂ films presented in section 6.3.2. Unfortunately, film quality is similar to that of pure CeO₂ film in reducing atmosphere, i.e., low epitaxial fraction and low percentage of flat area. In Fig. 7-36 it is shown AFM analysis where we observe that surface morphology consists in globular grains (~21% of atomically flat area and rms ≈ 6.5 nm). It is likely that in this case hydroxyl groups do not display any additional role in stabilizing (001)-polar surface. This result is not surprising considering that the nature of the MOD- CeO₂ films strongly differs from sputtering-CeO₂ films because of the retention of C from metalorganic precursors.

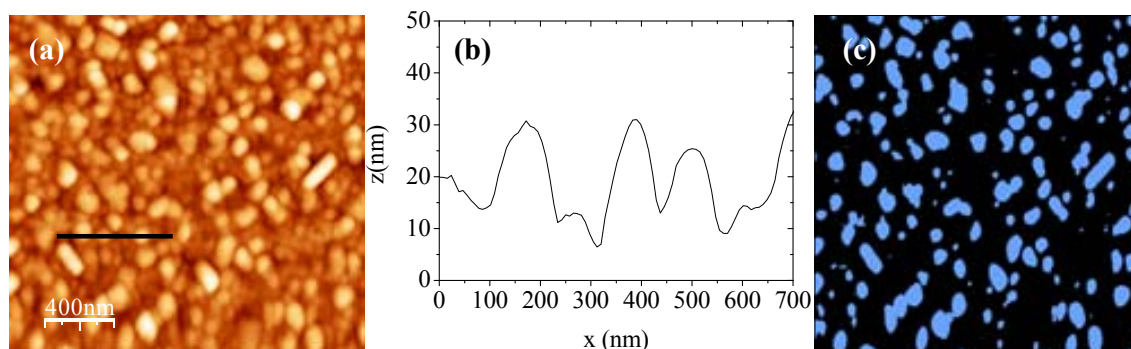


Fig. 7-36 AFM analysis of MOD-CGO10 film grown in Ar/H₂/H₂O at 900°C for 8 h on YSZ single crystal substrate. (a) AFM topographic image, rms \approx 6.5 nm (b) profile scan performed on the topographic image (c) binary image (21% of flat grains).

7.5.1.1.4.2 Effect of time and temperature

In an attempt to reduce the required processing temperature (900°C) and the annealing time (8h) for epitaxial CGO10 films, it has been studied separately the influence of lower growth temperature: 750°C, and the influence of shorter processing time: 4h. Recall that 30 nm-CGO films have been grown following the heating profile described in Fig. 3-14(b).

XRD θ -2 θ scan of samples grown at different times and temperatures on YSZ single crystal with the same thickness, are shown in Fig. 7-37. Only (*h*00) peaks are observed and no secondary phases are detected. From Fig. 7-37(b) it is deduced different I (*h*00) CGO Bragg line reflections. Thus, we have estimated the percentage of epitaxial fraction from the area of (400) CGO10 peak reflection and results have been summarized in Table 7-IV

It can be observed that while epitaxial fraction is kept almost constant for samples grown at 900°C 4h, 900°C 8h and 1000°C 8h, CGO10 grown at 750°C for 8 h shows a noteworthy reduction. From these first structural results it has been deduced that doping ceria with 10% of Gd³⁺ is not enough to obtain highly epitaxial film, growth temperature and time are also critical parameters that govern atomic mobility in CGO films. There is, however, a saturation effect, i.e. very small change is detected by increasing the temperature at 900°C -1000°C.

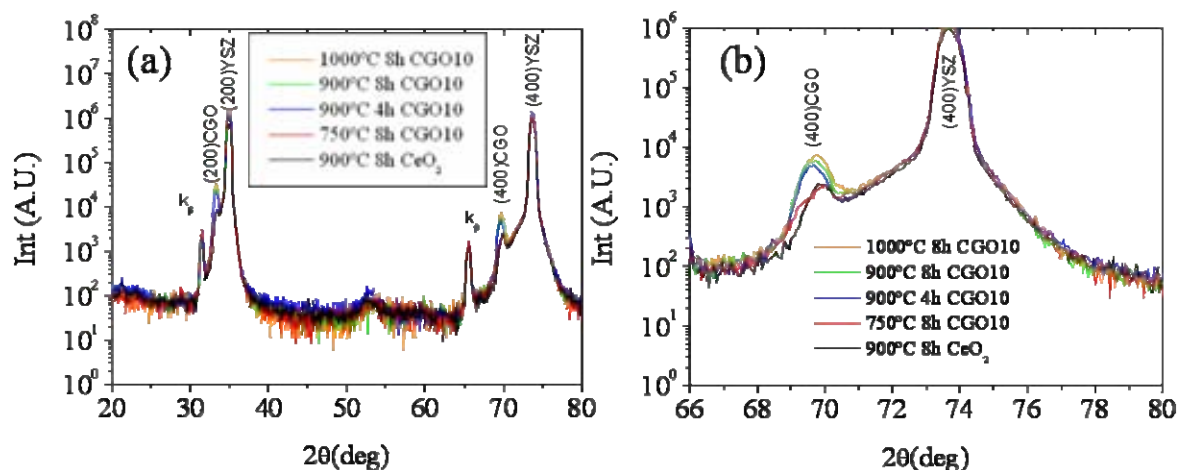


Fig. 7-37 (a) XRD $\theta/2\theta$ scan of CGO10 films grown on YSZ single crystal substrate under Ar/H₂ atmosphere at different time and temperature compared to pure CeO₂ film grown on YSZ single crystal substrate at 900°C for 8 h in Ar/H₂ atmosphere.(b) magnification of Fig.7-36 (a) in the range of 2θ values of 66-80°.

Table 7-IV Evolution of the epitaxial fraction of CGO films grown on YSZ at different growth conditions.

Processing conditions of CGO10	% epitaxial fraction (± 2)
Ar/H ₂ 8h 900°C	77
Ar/H ₂ 4h 900°C	73
Ar/H ₂ 8h 1000°C	80
Ar/H ₂ 8h 750°C	34

Surface morphology analysis for these CGO10 films has been carried out by AFM. In Fig. 7-38 are displayed the AFM topographic images, the corresponding binarized images obtained to quantify the percentage of flatness and, at the bottom a height profile analysis.

CGO processed at 750°C for 8h surface morphology consists of a granular matrix where grains have similar shape and size but some grains, 12%, homogeneously distributed, display larger grain size, see Fig. 7-38(a). By the height profile analysis we detected that larger grains are outgrowth with (001) flat surface. Since no secondary phases were detected from XRD θ - 2θ scan analysis, it has been supposed that these hills are a transition morphology from granular to terraced one in which terraces have just started developing.

Sample grown at 900°C for 4 h, Fig. 7-38(b), surface morphology has similarities to the standard CGO10 film, Fig. 7-21(c). In this case, terraces are smaller (~100nm) and residual rounded grains with pores observed at 750°C have not been completely consumed. This could be appreciated from its line scan displayed at the bottom of the AFM image. From the estimation of percentage of flat area, it has been found that ~ 50% of the surface is atomically flat.

Finally CGO10 film grown at 1000°C for 8 h displays a fully terraced surface, however, careful inspection of height profile scan reveals that terraces are displayed at different heights (around 5-10 nm), Fig. 7-39(a), and some outgrowths have been settled at the upper terrace Fig. 7-39(b).

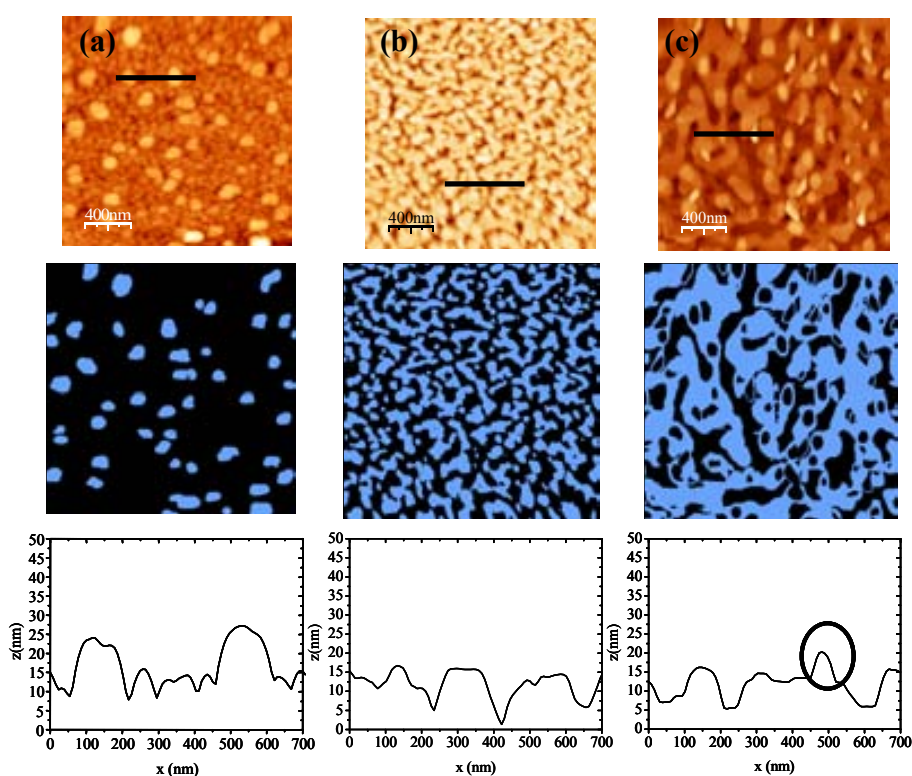


Fig. 7-38 AFM images and its respective scan profile of 10%Gd-doped CeO₂ films grown on YSZ single crystal under Ar/H₂ atmosphere. At 750°C 8 h with 12% of atomically flat area (a), at 900°C 4 h with 50% of atomically flat area (b) and at 1000°C 8 h, with 59% of atomically flat area (c).

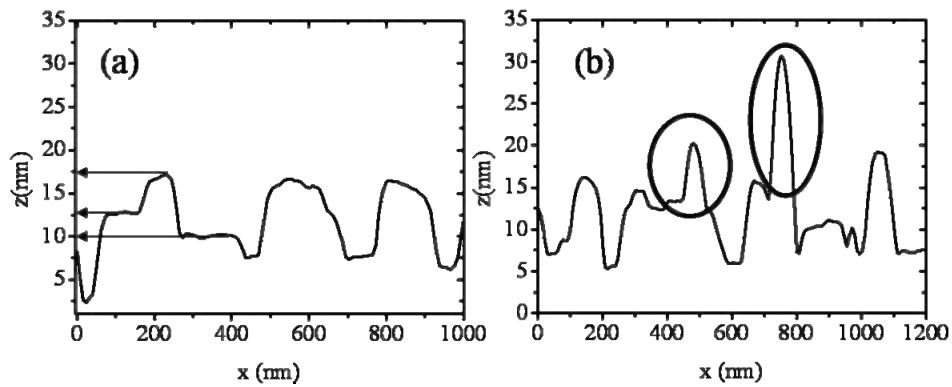


Fig. 7-39 Height profile scans performed on CGO10 solid solution grown at 1000°C for 8 h in Ar/H₂ atmosphere. (a) Exhibits terraces vertically separated by at least 5 nm (b) exhibits outgrowth contributions

It is clear that both contributions will interfere in the computations of atomically flat area for this sample. Therefore, as a first step we should apply a mask in order to subtract the outgrowth contribution (see section 2.1.1). Then, in order to estimate the effective flatness of this film we can only consider the upper floor of terraces, others will be masked. After all these considerations, it results the binarized image displayed below the topographic image, Fig. 7-38(c). This sample has 59% of surface atomically flat.

Collecting all data obtained for these CGO10 films differently processed, we can affirm that improvement in epitaxial fraction is correlated by an enhancement of terraced surface morphology. However, depending on the distribution of these terraces the atomically flat area will not be linearly proportional to the epitaxial fraction, i.e., CGO10 film grown at 1000°C for 8 h in Ar/H₂ although displays similar epitaxial fraction as CGO10 film grown at 900°C for 8 h due to in the former terraces are heterogeneously distributed, effective atomically flat area falls from 71% down to 59%, see Fig. 7-40.

Despite we do not dispose of TEM images for these samples, based on AFM and DRX analysis we suggest that the evolution to high epitaxial and terraced films is strongly related to the elimination of carbon impurities and therefore the grain boundary area. We have observed that besides C contamination, atmosphere and Gd incorporation, growth temperature and growth time also modify the energetic barrier for atomic mobility, however, epitaxial fraction has not been increased beyond 80%, we still have 20% of fraction non epitaxial. We have successfully demonstrated by XRD, AFM, TEM, XPS and RHEED investigations that by tailoring growth conditions and ceria composition (oxygen vacancies) we can modify the activation energy for grain boundary mobility as well as C elimination and obtain high epitaxy and atomically flat CGO10 film.

In terms of YBCO coated conductors applications, the most feasible cap layer is CGO10 film grown at 900°C for 8 h and Ar/H₂ processing atmosphere, since it displays high epitaxial fraction (77%), textured surface and atomically flat area (71%). This proposal will be verified in chapter 8 by depositing YBCO film on top of these CGO10 films.

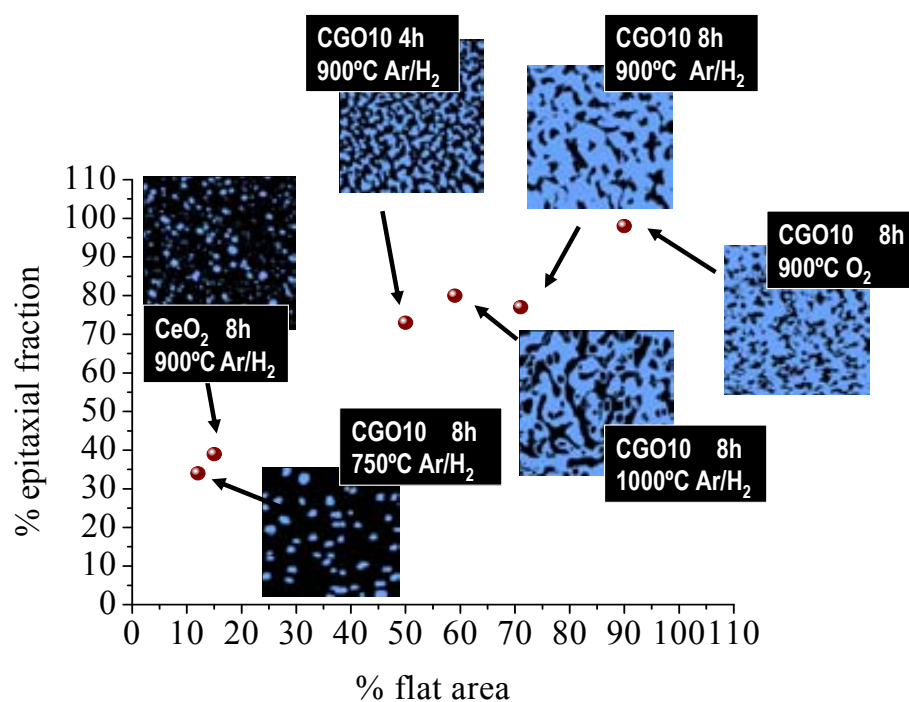


Fig. 7-40 Relationship between percentage of epitaxial fraction and percentage of atomically flat surface from CeO₂ and CGO10 films grown on YSZ single crystal at different time, temperature and atmosphere.

7.5.2 Effect of doping ceria with zirconium

In order to complete this study, now we turn to investigate the effect of isovalent dopant into grain boundary mobility: Zr⁴⁺. In principle, Zr⁴⁺ should not modify oxygen vacancies concentration, (see section 7.2), and therefore from this point of view it should be expected a lower grain boundary mobility and a lower CeO₂ epitaxial fraction.

7.5.2.1 Structural characterization

Zr-doped CeO₂ (CZO) precursor solution was fabricated from propionic acid and isopropanol solvents, following the procedure detailed in section 3.3.3.3. It has been grown on YSZ single crystal substrate under the optimal conditions obtained from CGO films (i.e. 10% Zr⁴⁺, 900°C, in Ar/H₂ for 8h). With this composition, CZO10, solid solution presents a cubic fluorite structure [238]. To evaluate epitaxy and crystallinity of this film with a thickness of 30 nm, XRD θ -2 θ scan and ω -scan were performed and compared to undoped CeO₂ and CGO10 films grown in the same conditions.

Typical XRD θ -2 θ scan for CZO10 film only displays the (*h*00) reflections of the CZO and YSZ specimens, and k_{β} reflections associated to YSZ, as can be appreciated in Fig. 7-41.

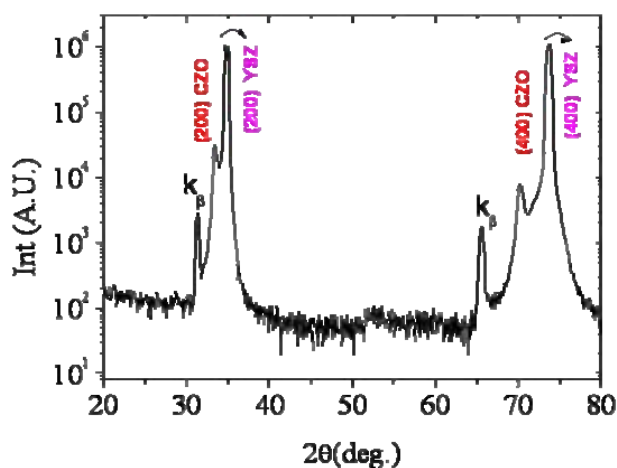


Fig. 7-41 XRD θ -2 θ scan for CZO10 grown on YSZ single crystal.

Comparing (400) peak intensity of CZO10, CGO10 and CeO₂ films grown under the same conditions, maximum intensity is obtained for CZO10 film, contrary to what we initially expected, Fig. 7-42. Moreover it is noticeable that (400) CZO10 peak reflection has been shifted to higher 2 θ values in comparison to pure CeO₂, due to ionic radius of Zr⁴⁺ is smaller than Ce⁴⁺, see Table 7-I. Therefore, the Ce-Zr exchange led to a decrease in the lattice constant of the oxide $a=5.354\text{\AA}$, in agreement with reported XRD results for bulk powders of these compounds [239]

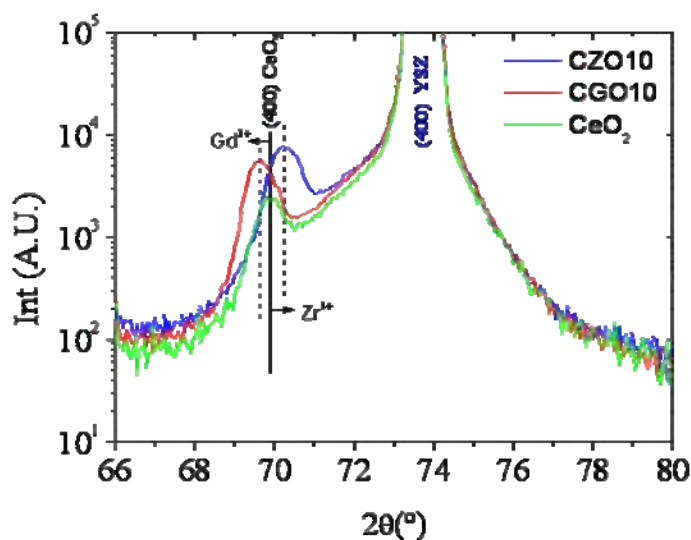


Fig. 7-42 (a) $\theta/2\theta$ XRD patterns of an undoped CeO₂ film, doped with 10% of Gd³⁺ and doped with 10% of Zr⁴⁺ grown on YSZ single crystal substrate under the same conditions (900°C in Ar/H₂).

We estimated the percentage of epitaxial fraction for this sample from integration A(400) peak reflection using CZO10 film grown in O₂ atmosphere as a reference specimen film, described in 7.5.3.4. We obtained a percentage of epitaxial fraction around 50 %. It is interesting to note that despite CZO10 shows an apparent higher intensity from (400) Bragg line reflection, it displays a lower epitaxial fraction than CGO10 film. This can be easily understood by careful inspection of substrate peak position and CZO10 peak position in XRD θ - 2θ scan. As they are very close we can not compare directly without proper evaluation of the background. By deconvolution of both peaks, the true area corresponding to CZO10 peak is even lower than CGO10. The apparent high intensity of the (400) Bragg line reflection is therefore attributed to the contribution of the (400) peak of the YSZ substrate. ϕ -scan corresponding to (202) CZO10 film revealed anomalous shape (two contributions), as we already presented in undoped CeO₂ film, Fig. 7-5. This result is well consistent with 50% of epitaxial fraction.

7.5.2.2. Surface morphology characterization

In Fig. 7-43 it is shown the analysis of surface morphology performed by AFM of CZO10 film. AFM topographic image shows that surface morphology consists in a mixture of interconnected polyhedral grains with atomically flat terraces defined by (001) planes linked through pores at the ledges of these grains. In this case, 30% of surface is atomically flat and the size of terraces is in the range ~50-100 nm, therefore, the surface has not developed a well defined terraced topography as the one found by CGO10 grown in the same conditions, Fig.

7-21 (c). But, surface morphology differs from undoped CeO₂ film which is also an indication (together with XRD data) that the incorporation of Zr⁴⁺ has modified the atomic mobility in CeO₂ film.

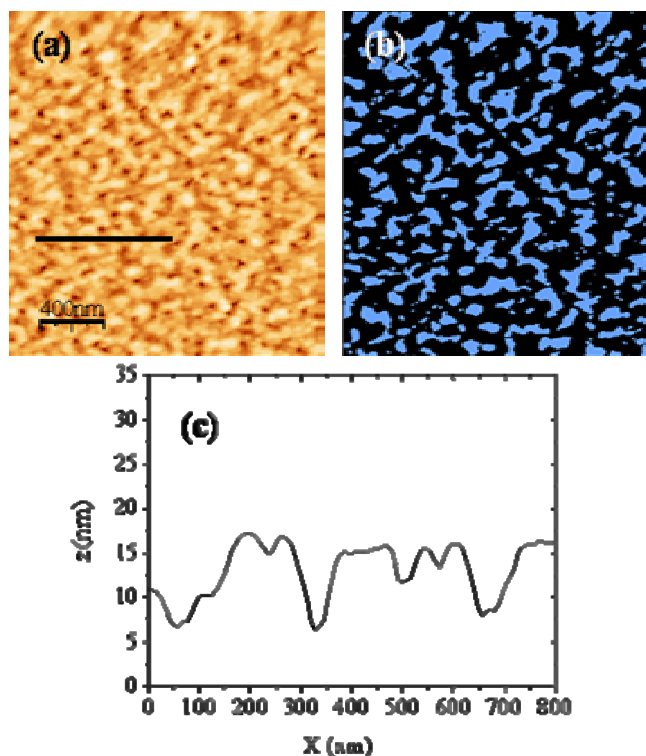


Fig. 7-43 AFM picture of CZO10 grown on YSZ at 900°C for 8 h in Ar/H₂ atmosphere. (b) binary image (c) Profile scan of the topographic image presented in (a)

RHEED pattern shows spot-like diffraction as a result of textured and rough surface, in short, 3D surface, see Fig. 7-44. This result correlates well with AFM and XRD analysis presented earlier.

It is very important to notice that even though by XRD analysis we found that films are 50% epitaxial, RHEED pattern does not show a background contribution due to the randomly oriented grains. Therefore we suggest that this contribution might be present but it is masked by sharp spots due to intense textured contribution as we anticipated for CGO10 film. In any case it has to be mentioned that incorporation of 10% of Zr⁴⁺ under reducing atmosphere, has improved epitaxial fraction and surface morphology from undoped CeO₂. Therefore, in contrast to what we initially expected from charge consideration, Zr⁴⁺ enhanced grain boundary mobility. Thus,

our aim is to find why the incorporation of Zr⁴⁺ has this beneficial effect on CeO₂ microstructure from the view point of cap layer application.

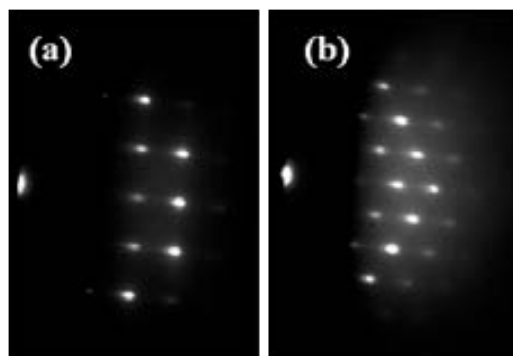


Fig. 7-44 RHEED pattern of CZO10 film on YSZ substrate grown at 900°C in Ar/H₂ for 8h (a) along <100> substrate direction, (b) along <110> substrate direction.

There is a large amount of studies showing that CeO₂-ZrO₂ system is one of the most appealing mixed-metal oxides due to its important role in the operation of automotive catalysts [240,241]. Balducci and coworkers, by computer simulation studies in CeO₂-ZrO₂ solid solutions, found that the introduction of 10% of zirconia in ceria lowers the activation energy for oxygen mobility (from ~ 0.6eV for pure CeO₂ to 0.1 eV for CZO10) [242]. Although we do not have quantitative data from our samples for direct comparison, our XRD analysis are consistent with an enhanced mobility in ceria by the incorporation of Zr⁴⁺ based on epitaxial fraction parameter.

The mechanisms for the doping effects of Zr⁴⁺ remain uncertain and are still a matter of debate but several proposals have appeared. Mamontov and coworkers studied the atomic-level defective structure of nanoscale powders of ceria and ceria-zirconia solid solution using the pulsed neutron diffraction technique and suggested that the smaller ionic radius of zirconium favours the presence of Ce³⁺ ions and associated oxygen vacancies by eliminating the strain associated with their formations [243]. These results are consistent with EXAFS experimental observations from [244] which suggested that structural modifications induced by Zr⁴⁺ promote the formation of mobile oxygen ions. In this context, it is necessary to look into ceria and CZO10 structure, presented in Fig. 7-45.

Fluorite structure can be described as an array of cations forming the face-centered-cubic lattice with oxygen ions occupying the tetrahedral interstitial sites. The octahedral sites in a perfect fluorite structure are empty (marked by a cross in Fig. 7-45). When Zr⁴⁺ is incorporated into CeO₂, tetrahedral sites are under local atomic compressive stress and it becomes difficult that interstitial oxygen reaches the tetrahedral sites and recombines with vacancies. This could

provide necessary oxygen mobility which is crucial in our samples for grain boundary migration and elimination of C.

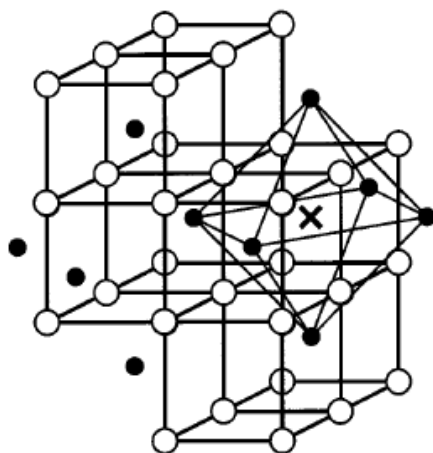


Fig. 7-45 The structure of ceria of cubic ceria-zirconia solid solution. Perfect fluorite structure. Cations (small filled circles) occupy each second interstitial site of the cubes of oxygen ions (open circles). Cation sublattice forms tetrahedral and octahedral sites (one of the octahedral sites is shown). The centers of the tetrahedral sites coincide with the vertexes of the oxygen cubes, while those of the octahedral sites (marked by a cross) coincide with the centers of the oxygen cubes.

7.5.2.3 Chemical surface composition

In attempt to verify if Zr⁴⁺ favors the presence of Ce³⁺ in our samples, which in turn will allow us to roughly explain changes produced in CZO10 films, XPS analysis was performed.

The surface chemical composition of the CZO films was investigated from Ce(3d), O(1s), C(1s) and Zr(3d) core level x-ray photoelectron spectra. It is important to remark that from the survey spectrum we do not have identified Y indicating that we do not have uncovered substrate areas and therefore the Zr(3d) signal is entirely from the film. These spectra have been acquired by the conditions described in section 2.1.3. Binding energy correction and area calibration had to be made in all cases as in the previous systems here studied. According to earlier XPS results, all spectra will be strongly influenced from environment (CO₂, hydrocarbons, H₂O adsorption).

C(1s) spectra presents a single peak at 285 eV indicating, as expected, the incorporation of typical hydrocarbons impurities, Fig. 7-46(a). Surface carbide contribution is not observed in C(1s) spectrum. This is another indication that Zr⁴⁺ into CeO₂ favoured the grain boundary mobility.

O(1s) presents a main peak at 528.8 eV corresponding to structural O-Ce energy. Low intensity shoulder at higher binding energy is formed by the as-mentioned oxygen from the environment (H₂O or OH⁻), namely O_{532.1} in Fig. 7-46(b).

The shape of the Ce(3d) spectra, indicates the presence of Ce³⁺, marked by arrows in Fig. 7-46(c). We have quantified the Ce³⁺ content from the total Ce as described in section 2.1.3.4 and from this compute it figures out 10% of Ce³⁺. Contrasting this result with CGO10 surface chemical composition reported above see Fig. 7-27, we note that in Ce3d spectrum from CGO10 solid solution it is not detected formation of Ce³⁺. Thus, even the pathway formation of Ce³⁺ in CZO solid solutions is still not understood, this result are consistent with mechanism described by Mamontov and Balducci [242,243].

Finally the presence of Zr in the film was detected from registering the binding energy of the Zr(3d) core level. Peak shape and peak position are very similar to the reported value in previous work on 10%Zr-CeO₂ thin film on (100) SrTiO₃, Fig. 7-46(d) [245]. It has been estimated the atomic ratio Zr/Ce from the Zr3d and Ce3d peaks areas and by using the corresponding sensitivity factors (section 2.1.3.1.3). We obtained Zr/Ce= 0.12. This calculated ratio is close to that introduced in the precursor solid solution.

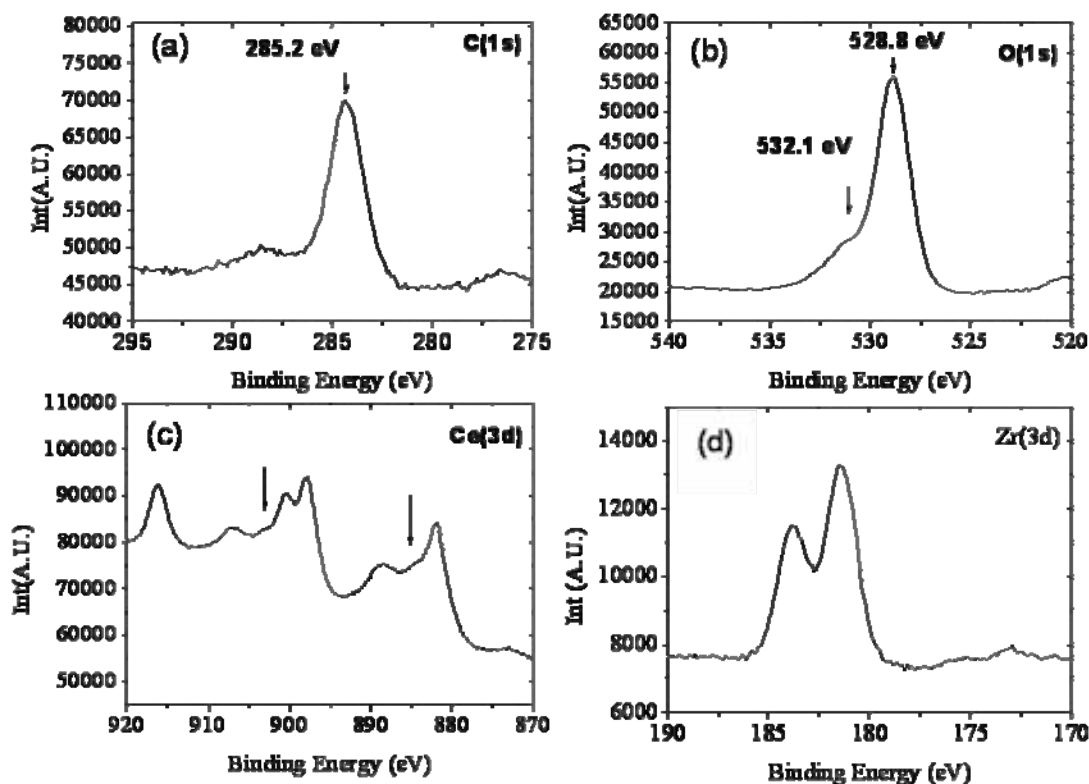


Fig. 7-46 High energy resolution XPS spectra of the C1s (a), O1s (b), Ce3d (c) and Zr 3d (d) for the epitaxial CZO layer on (100) YSZ single crystal.

In conclusion, the incorporation of Zr into CeO₂ lattice introduces the formation of 10% of Ce³⁺ on CeO₂ surface composition. Therefore, we suggest that the incorporation of Zr⁴⁺ in our CeO₂ films favors grain boundary mobility through Ce³⁺ formation and the associated oxygen vacancies formation. It is interesting to notice that both CGO10 and CZO10 enhance grain

boundary mobility by oxygen vacancies, but the mechanisms by which they form are completely different and the final film present different degree of epitaxy and surface morphology.

7.5.2.4 Effect of oxygen atmosphere

With the purpose of possible improvements in surface morphology and texture quality of CZO10, as we already observed by CeO₂ and CGO10 system, CZO10 film has been grown on YSZ single crystal at 900°C for 8 hours in oxygen atmosphere.

Comparison of XRD $\theta/2\theta$ patterns of CZO10 solid solutions grown under oxygen and under Ar/H₂ atmospheres are shown in Fig. 7-47. They revealed a clear increase of the intensity of the (*h*00) peaks when CZO10 is grown in oxygen atmosphere. From Fig. 7-48 we appreciate that in-plane texture was improved changing the processing atmosphere resulting a single and sharp contribution with $\Delta\phi(202) = 1.1^\circ$.

A(400) peak reflection of CZO10 has been calculated by deconvolution of the (400) peak of substrate and (400) peak of film. We obtained maximum area and therefore this sample has been considered 100% epitaxial. This sample, actually, has been utilized as reference specimen for calculations of epitaxial fraction of all other doped-CeO₂ here studied as we already anticipated.

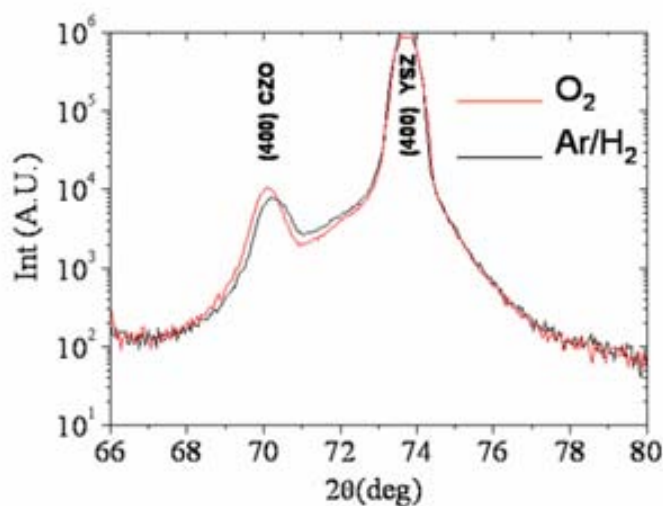


Fig. 7-47 $\theta/2\theta$ scan in the 2θ range of 66 to 80°. In red it is depicted the CZO/YSZ film grown under oxygen and in black it is depicted the film grown in Ar/H₂ atmosphere.

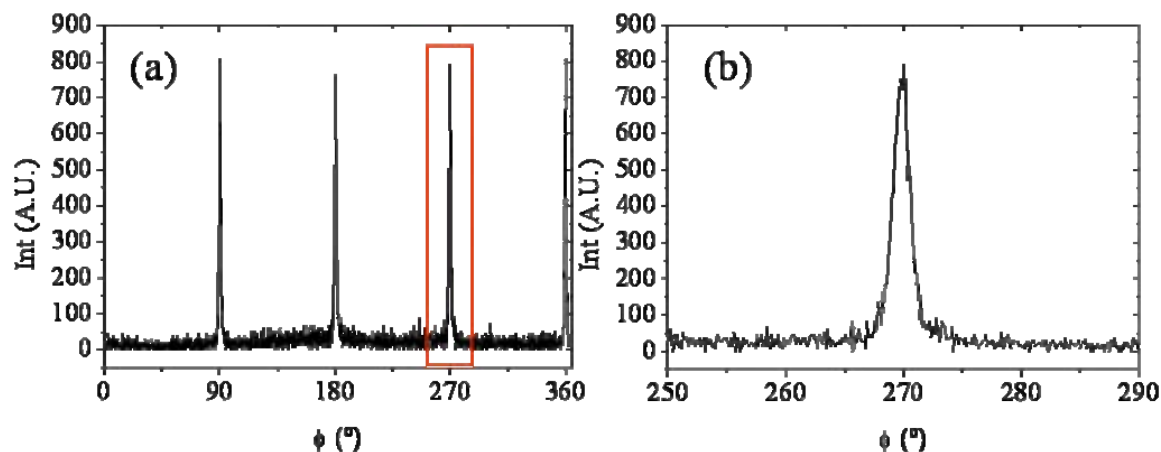


Fig. 7-48 XRD ϕ -scan of (202) reflection from CZO10 film grown on YSZ single crystal substrate (b) magnification of the peak centered at 270° in (a).

It is likely that by using pure oxygen atmosphere we have successfully eliminate grain boundaries and carbon impurities in MOD-CZO film, thus being well consistent with previous results carried out on MOD-CGO and MOD-CeO₂ film under pure oxygen atmosphere.

RHEED pattern shows streak-like diffraction spots indicating a textured surface with very flat islands. There are even indications of ‘real’ RHEED patterns (see view parallel $\langle 100 \rangle$) resulting from a 2D diffraction case. Therefore, the pattern might be described as 2D surface, Fig. 7-49.

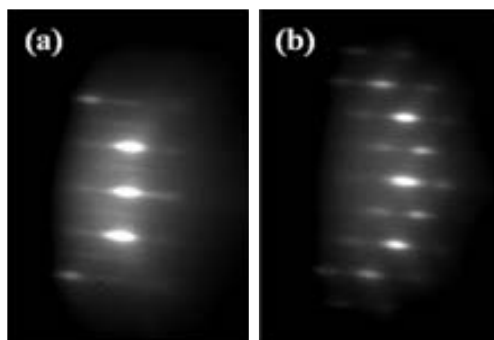


Fig. 7-49 RHEED pattern of 10% Zr-doped Ceria grown on YSZ single crystal (a) along the $\langle 100 \rangle$ substrate direction and (b) along $\langle 110 \rangle$ substrate direction.

AFM of this sample in Fig. 7-50 show that oxygen atmosphere has further enhanced the (001)-terraced surface morphology and this film became much smoother (rms \sim 0.8nm). Indeed, it displays 93% of atomically flat surface, in agreement with 2D RHEED pattern. Based on [38] we suggest the film reconstruction as a possible mechanism to eliminate carbon impurities and stabilization of (001)-polar CeO₂ surface.

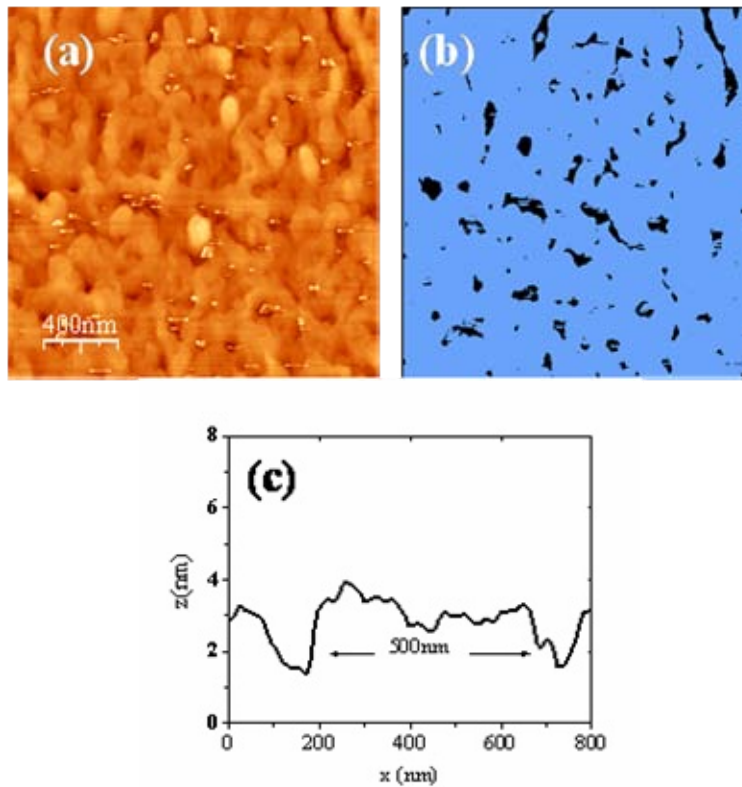


Fig. 7-50 2x2 μ m AFM scan of CZO/YSZ grown under oxidizing atmosphere at 900°C for 8 h.

At this point we would verify if percentage of epitaxial fraction and atomically flat area obtained for MOD-CZO films accomplish the predicted dependence found between these two parameters for MOD- ceria samples studied all along this chapter. The results are displayed in Fig. 7-51. We appreciate that CZO films do follow the predicted dependence. Therefore it seems safe to conclude that this correlation can be explained by the mobility of $V_o^{\bullet\bullet}$ simultaneously with C content elimination and it has been corroborated that depends on the type of dopant, association among defect, concentration of dopants and also growth parameters.

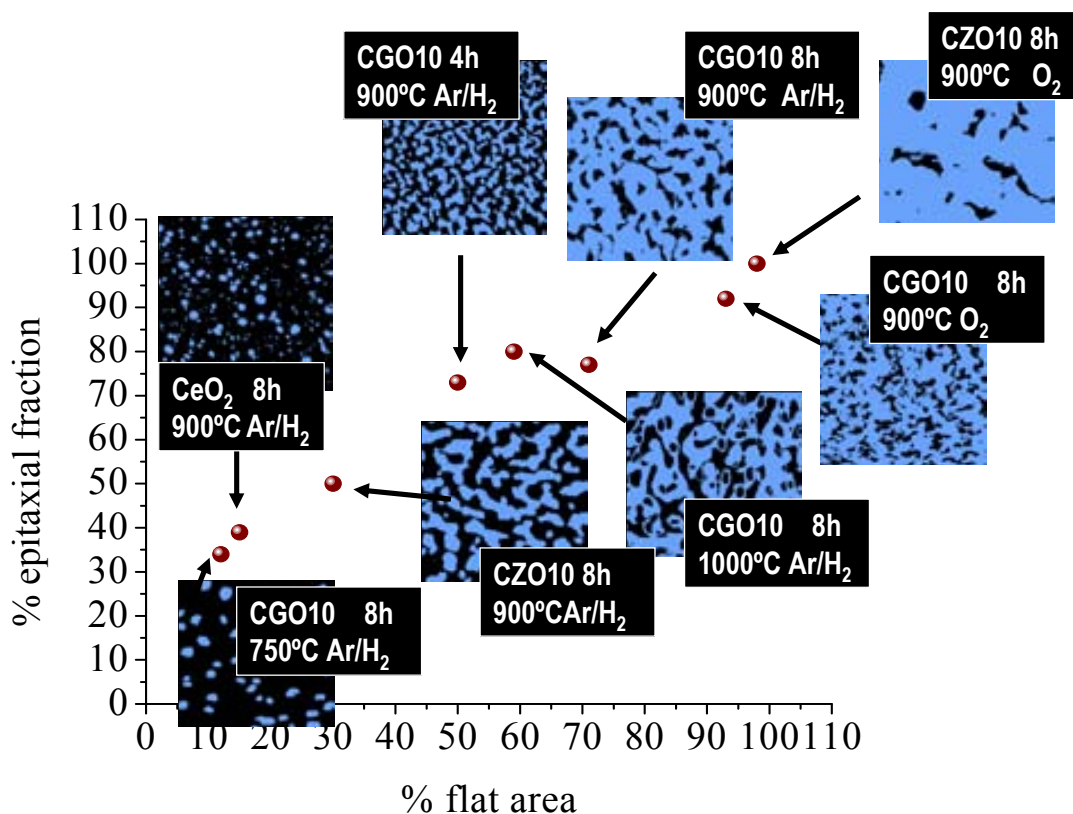


Fig. 7-51 Dependence of percentage of epitaxial fraction on percentage of flat area for modified-CeO₂ films deposited on YSZ single substrate.

7.6 Conclusions

In this chapter, we have investigated the growth mechanisms and microstructure of doped-CeO₂ films grown by chemical solution deposition as feasible cap layer for TFA-YBCO coated conductors. Based on recently work performed in our group on MOD-CeO₂ cap layer in which it was demonstrated that CeO₂ film grown under reducing atmosphere is inherently granular as a result of grain growth inhibition induced by grain-boundary contamination with C impurities, we have focused on increasing grain boundary mobility avoiding pure oxygen atmosphere to overcome this blocking mechanism and obtain highly textured and atomically flat (001)-terraced surface MOD-CeO₂ films.

Here we have analysed three approaches to increase mobility in CeO₂ lattice. Reducing conditions has been preserved to be further transferred on metallic substrate: (1) modification of growth conditions (atmosphere, time and temperature) (2) modification of precursor solution and (3) incorporation of dopant agents into CeO₂.

By investigating the influence of growth atmosphere (Ar/H₂/H₂O or O₂+Ar/H₂) on 30nm CeO₂ film quality, we have found by XRD and RHEED analysis that films are partially or

completely untextured. AFM study reflected that in all cases films conserve granular surface morphology and around 18% of surface is atomically flat. Additionally, we have found by XPS measurements that some C is still trapped in grain boundaries, probably as Ce₂C₃ or CeC₄, inhibiting grain growth.

By varying the precursor solution (acetates have been replaced by propionates), we obtained two significant improvements. On one hand the solution lifetime was increased from several hours to several months. This is due to the chelate effect of new precursors. On the other hand we have observed a significant increase in epitaxial fraction (from ~19% to ~38%). This improvement has been related to the decomposition pathway of organic precursor through formation of isoprene. AFM analysis illustrated that surface morphology has not been modified, rounded grains govern surface morphology.

Finally, we have studied the effect of dopant agents: Gd³⁺ and Zr⁴⁺ into cerium oxide epitaxy and surface morphology. We have detected that both dopants have increased mobility in CeO₂ lattice, but it seems that different mechanisms are followed in each case. Whereas for Gd-doped CeO₂ it has been suggested that mobility is introduced through oxygen vacancies formation by charge compensation, it is likely that in Zr-doped CeO₂ the key parameter is the small ionic radius of Zr⁴⁺. It has been proposed that it reduce the strain generated in the lattice due to Ce⁴⁺ to Ce³⁺ conversion and the corresponding oxygen vacancies. Although epitaxial fraction has been improved to ~77% for Gd-doped CeO₂ and to ~50% for Zr-doped CeO₂ in Ar/H₂ atmosphere, carbon has not been effectively removed. Thus, there is room for further improvement of film quality.

We have found that there are other factors affecting the complex mechanism of elimination C impurities to achieve high quality CeO₂ film: concentration of dopant, growth temperature, time and processing atmosphere.

Optimization of dopant concentration has been deeply investigated by Gd³⁺ incorporation. We have observed that the original granular regime detected in pure CeO₂ film is successfully suppressed by doping CeO₂ with 10% of Gd³⁺ (77% of epitaxial fraction). In addition, by the incorporation of this percentage we have stabilized (001)- flat terraced surface leading to ~70% of atomically flat surface. By contrast, we assume that lower percentage of Gd³⁺ generates few oxygen vacancies and therefore we could not enhance the atomic mobility. Ce₂C₃ still surround misoriented grains and poor degree of epitaxy and surface morphology with ~ 13% of atomically flat area were observed. Higher percentage of Gd³⁺ (≥20%), incorporated with a primary intention to increase the mobility, resulted as a blocking agent because strong interaction between solute and oxygen vacancies occurs and consequently hinders the atomic mobility in ceria. In addition, at very high concentration of Gd³⁺, above the solubility limit, it is

likely that this strong interaction might evolve to phase segregation. We have obtained percentages of epitaxial fraction ranging from ~30 to 44% .

We have also observed that time and growth temperature conditions could also influence the mobility in 10% Gd-doped CeO₂ films. It is worth of remark that no influence of adding H₂O in the gas flow was detected in this case. It is likely that in this case hydroxyl groups do not play any additional role in stabilizing (001)- terraced surface.

Finally, by the combination of CeO₂, CGO and CZO results we have demonstrate that exist a gradual increase in the epitaxial fraction and the percentage of atomically flat area running in parallel to the elimination of carbon content.

CHAPTER 8

YBa₂Cu₃O₇ deposition on MOD- CeO₂ based cap layer buffered YSZ single crystal

8.1 Motivation

High J_c was observed for YBCO film prepared by TFA-MOD route on vacuum CeO₂-buffered YSZ single crystal in chapter 7. The next goal that must be achieved now for all chemical CC technology to be competitive is to reproduce high J_c values for TFA-YBCO on MOD-CeO₂ buffered YSZ single crystal. To do that, in the previous chapter, we developed MOD- 10%Gd-CeO₂ (CGO10) cap layer processed in 95%Ar/5%H₂ (Ar/H₂) reducing atmosphere that fulfils the requirements as cap layer for YBCO CC fabrication.

However, achieving high J_c values on MOD-CeO₂ is not straight forward. In fact, our preliminary studies of TFA-YBCO film with a thickness of 150 nm grown on MOD-CeO₂ /YSZ single crystal substrate were negative. These YBCO films carried a J_c of only 10⁵ A cm⁻² at 5K [139]. One of the main drawbacks reported by several authors is the interface reaction between YBCO and CeO₂ with the BaCeO₃ formation which is evidenced in both vacuum and non vacuum deposition techniques [246,247].

In this work, we conducted a systematic investigation of the effect of the underlying surface and texture of the modified-CeO₂ buffer layers on the properties of the subsequently

deposited YBCO film. As a first step we considered YBCO deposition by pulsed laser deposition (PLD) due to vacuum deposition methodologies can certainly reproduce high-performance coated conductors [248,36]. Subsequently, we optimized the growth conditions of TFA- YBCO on MOD- ceria cap layer with specific focus placed on BaCeO₃ formation.

8.2 PLD- YBCO on MOD- (doped)- CeO₂ /YSZ single crystal

Among all modified MOD-CeO₂ buffer layers prepared in the previous chapter, those films which presented higher epitaxial fraction and flat-(001) terraced surface were selected as the most appropriate for high quality YBCO growth in accordance with [38], whereas those that presented granular surface morphology with low epitaxial fraction were excluded. To easily verify this proposal, in collaboration with Dr.R.Hühne in IFW-Dresden, optimized PLD-YBCO were deposited on (1) granular MOD-CeO₂ and (2) terraced-like MOD-doped CeO₂ cap layers. We would like to reiterate that CeO₂ and doped-CeO₂ films were fabricated from propionates precursor (described in 3.3.3.3). Optimal PLD-YBCO deposition conditions were:

T= 810°C

Laser energy density=220 kV

Deposition rate=1Å/pulse

Repetition rate = 5Hz

P(O₂) Deposition step =0.03 kPa

P(O₂) Oxygenation step = 40 kPa

Standard thickness= 300 nm

8.2.1 PLD- YBCO on MOD-CeO₂ cap layer

PLD-YBCO film was first deposited on pure MOD-CeO₂ cap layer grown under Ar/H₂ atmosphere. We would like to bring to mind that this cap layer displayed a surface morphology dictated by rounded grains (13% of atomically flat area) and from the structural analysis two contributions were detected: a textured and a random fraction. They are clearly illustrated in XRD pole figure shown in Fig. 8-1(a).

After depositing PLD-YBCO film, x-ray diffraction was employed to study the phase purity and texture of the superconducting film. J_c was determined by inductive measurements.

From XRD θ - 2θ scan, illustrated in Fig. 8-2, we denoted that YBCO films are c-axis oriented on the CeO₂ buffered YSZ single crystal substrate. In addition, we also detected an impurity peak at $2\theta \approx 41.8^\circ$ indexed as BaCeO₃ phase [198]. The presence of this phase together with weak CeO₂ reflections is an indication that exist interaction between CeO₂ and YBCO layers. Note that in this case BaCeO₃ is present in a single texture whereas for TFA-YBCO/vacuum-CeO₂/YSZ single crystal system it showed two orientations (recall Fig. 6-13).

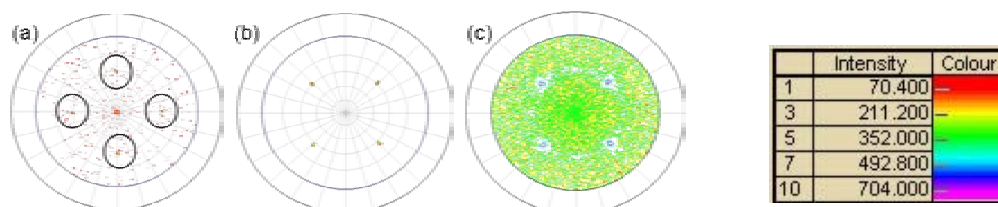


Fig. 8-1 X-ray pole figure measurements (CuK α) taken from the layer sequence of PLD-YBCO/MOD-CeO₂(Ar/H₂)/YSZ (a) (220)CeO₂ reflection and (b) (103)YBCO reflection (c) (103)YBCO reflection in log scale.

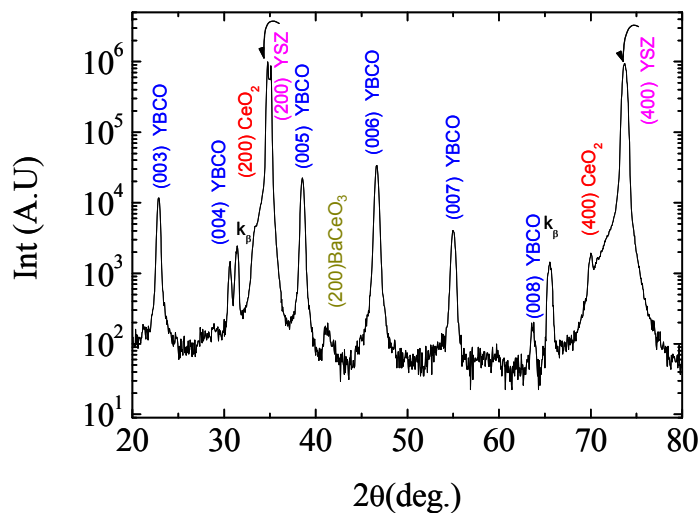


Fig. 8-2 X-ray diffraction pattern of PLD-YBCO/MOD-CeO₂/YSZ single crystal substrate.

In chapter 6 it could not be estimated the amount of BaCeO₃ formed in YBCO/CeO₂ interface because of the poor resolution of the XRD θ -2 θ scan. In order to overcome this problem, as we previously announced, from chapter 7 to now, we used another XRD instrument (Philips PW3710 MRD Control Diffractometer) which allows us to quantify BaCeO₃ content, C_{BCO} , defining a general formula in Eq. 8-1,

$$C_{BCO} = \frac{(I(110)_{BCO} + I(200)_{BCO})}{(I(110)_{BCO} + I(200)_{BCO} + Ik_{\beta})} \quad \text{Eq. 8-1}$$

where $I(110)$, $I(200)$ and $I_{k_{\beta}}$ contributions represent the X-ray θ -2 θ scan intensities of the Bragg line reflections here indicated: The first two correspond to the two possible orientations earlier detected for pseudocubic BaCeO₃ phase (section 6.4) and the latter corresponds to the k_{β} reflection associated to YSZ substrate. In this particular case, $I(110)_{BCO}$ is assumed to be zero since it has not been detected in XRD θ -2 θ scan from Fig. 8-2. After computing the above equation we obtained $C_{BCO} \sim 0.21$.

The XRD pole figure was measured on the YBCO film, using the (103) YBCO reflection. From Fig. 8-1(b) it is easily seen that CeO₂ layer leads to fibre texture in the YBCO layer. For better appreciation of this low degree of YBCO texture, pole figure from (103) YBCO reflection is shown in Fig. 8-1(c) in logarithmic scale. Pole figures from CeO₂ and YBCO film show an epitaxial relationship with a 45° in-plane rotation which can be easily understood considering that with this configuration the lattice mismatch between the cap layer and the superconducting layers is $\varepsilon = -0.52\%$.

Critical current density was measured from this sample and $J_c < 10^5$ A/cm² at 77K was obtained indicating poor superconducting properties being in well agreement with XRD analysis presented above. Thus, this result reflects that partially epitaxial CeO₂ film (38%) with granular surface (13 % of atomically flat area) transfers poor texture to the superconducting film which affects the overall quality of the YBCO film, as we predicted in chapter 7 from the study of MOD-CeO₂ cap layers.

8.2.2 PLD-YBCO on MOD-doped CeO₂ cap layer

PLD-YBCO film was deposited on 10%Gd-CeO₂ film (CGO10) and 10%Zr-CeO₂ film (CZO10) grown under two different atmospheres (a) 95%Ar/5%H₂ (Ar/H₂) and (b) pure O₂ atmosphere. As we observed earlier in chapter 7, they are distinguished by the epitaxial fraction of CeO₂ and the surface morphology (evaluated from the statistical parameter: rms roughness and percentage of atomically flat area), recall Fig. 7-51.

After deposition PLD-YBCO film, XRD analysis, electrical resistivity and critical current densities were carried out for all samples.

A typical XRD θ - 2θ scan of PLD-YBCO film grown on MOD-doped CeO₂ cap layer is shown Fig. 8-3(a). Interestingly, XRD θ - 2θ scans for PLD-YBCO film on MOD-(Gd,Zr)CeO₂/YSZ single crystal substrates do not present significant differences for different dopant or buffer growth atmosphere. Therefore, the scan in Fig. 8-3(a) is representative for all films studied in this section 8.2.2. The intense YBCO (00 l) peaks indicate that YBCO film has a strong c-axis texture. Strong ($h00$) CeO₂ Bragg line reflection and only single weak peak of BaCeO₃ phase indicates that there is little interaction between doped-CeO₂ and YBCO layers. Indeed, we have calculated the concentration of BaCeO₃ formed in this sample, C_{BCO} , through Eq. 8-1 defined previously. From this computation we obtained $C_{\text{BCO}} \sim 0.11$, considerably less than PLD-YBCO/MOD-CeO₂/YSZ single crystal substrate. Out-of-plane texture of the PLD-YBCO on the MOD-doped CeO₂ buffered YSZ single crystal substrate was also measured by the X-ray ω -scan of the (005)YBCO reflection (see Fig. 8-3 (b)). The FWHM values for these films were $0.3^\circ \pm 0.1$. Subsequently, we have also measured YBCO in-plane texture from (103) YBCO reflection. FWHM values for this set of samples are relatively constant at 1.2° , indicating a good transference of the biaxial texture from the CeO₂ buffer layer to the YBCO film, as could be observed from the list in Table 8-I. The pole position of the YBCO (103) plane rotated 45° from CeO₂ (220) plane shows again that the epitaxial relation between YBCO and CeO₂ is: YBCO (00 l) // CeO₂ (00 l) and YBCO[100] // CeO₂ [110], Fig. 8-4.

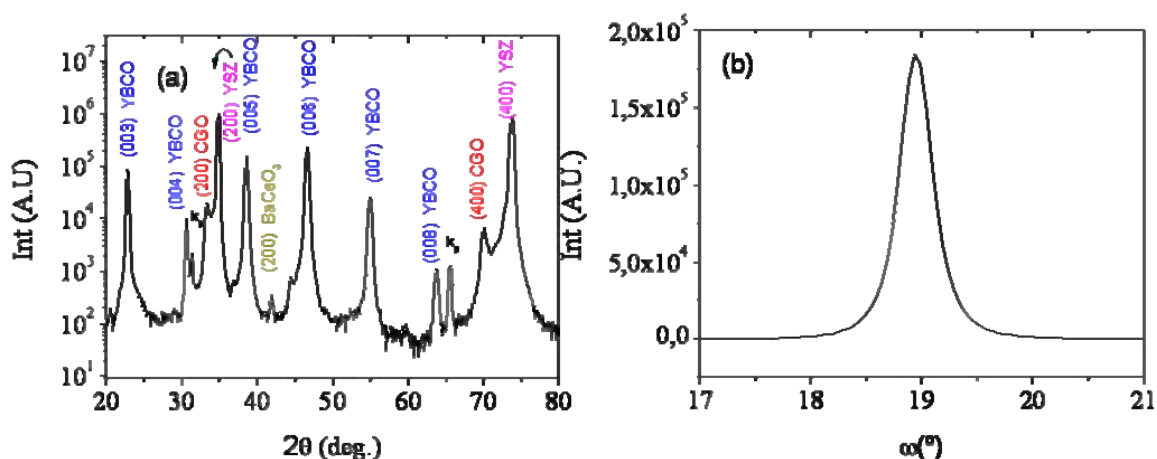


Fig. 8-3 (a) A typical XRD θ - 2θ scan for a YBCO film with a thickness of 300 nm deposited by PLD on MOD-CGO10(Ar/H₂)/ YSZ system.(b) XRD ω -scan for YBCO(005) of the same film, FWHM=0.32°.

Table 8-I XRD FWHM values for in-plane texture of PLD-YBa₂Cu₃O₇ films on MOD-doped-CeO₂ buffered YSZ.

Sample	Buffer layer	$\Delta\phi(103)$ YBCO (deg) ±0.1	$\Delta\phi(220)$ CeO ₂ (deg) ±0.1
Mu425	CGO Ar/H ₂	1.2	1.1
Mu412	CGO O ₂	1.1	1.1
Mu407	CZO Ar/H ₂	1.2	1.2
Mu408	CZO O ₂	1.2	1.2

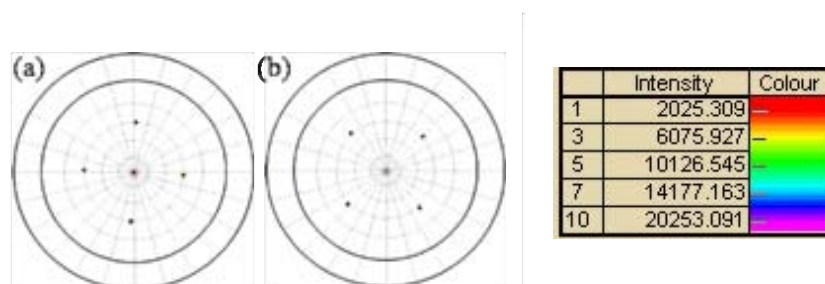


Fig. 8-4 XRD pole figures of (a) (220) MOD-CGO10 buffer layer grown on YSZ single crystal (b) (103) PLD-YBCO grown on MOD-CGO10 buffer layer.

Typical surface morphology of the PLD-YBCO layer deposited on doped-ceria cap layers, determined by SEM, shows a homogeneous surface microstructure with a high pore density, see Fig. 8-5. It is important to mention that other groups [96,200] have obtained PLD-YBCO film on CeO₂ cap layer significantly denser. In order to densify our PLD-YBCO films, it should be required a detailed optimization of deposition parameters.

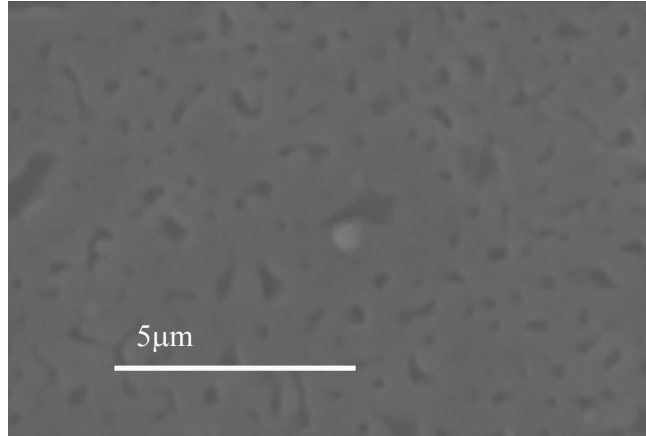


Fig. 8-5 SEM micrograph of 300 nm thickness PLD-YBCO film annealed at 810°C in 0.03 kPa oxygen on MOD-CGO/YSZ single crystal substrate.

PLD-YBCO layer grown on doped-CeO₂ cap layers typically showed a superconducting transition between 88.9 and 89.8 K with a transition width ΔT_c between 1 and 1.6 K, indication of good film quality. These results are consistent with that of XRD texture analysis in which YBCO films displayed good biaxial texture. Critical current density values measured at 77K for the PLD YBCO films are listed in Table 8-II. It is noticeable that no significant changes exist in J_c values achieving an average value of around 3.3 MA cm⁻², similar to that obtained on YBCO/LAO single crystal substrates [34].

Table 8-II Characterization of MOD-derived CeO₂ cap layers surface quality and the corresponding values of J_c and T_c for the PLD-YBCO film deposited on top.

Sample	Buffer layer	CeO ₂ surface rms (nm)(scan 2x2 μ m) ± 0.3	Flat area grains (%) (scan 2x2 μ m)	J_c (MA/cm ²) 77K	T_c 90(K)
Mu425	CGO Ar/H ₂	4.4	71	3.33	89
Mu412	CGO O ₂	3.0	90	3.34	89
Mu407	CZO Ar/H ₂	4.3	30	3.42	90
Mu408	CZO O ₂	1.2	92	3.79	90

Therefore, exist a clear difference between the quality of PLD-YBCO film grown on undoped (section 8.2.1) and doped CeO₂ film indicating that the quality of cap layer do influence the subsequent growth of PLD-YBCO film. In Fig. 8-6 (a) we have represented the dependence of atomically flat area of (doped)-CeO₂ film on the critical current density for the superconducting layer. By increasing the percentage of flat area from 18% to 31% J_c values strongly improve from $\sim 0.1 \text{ MA cm}^{-2}$ to 3 MA cm^{-2} at 77K. By contrast, from 31% to 92% J_c values remain almost constant. By considering the correlation found in the previous chapter between percentage of atomically flat area and percentage of epitaxial fraction, Fig.7-47, we assume that J_c values also depends in a similar way on the microstructure quality of (doped)-CeO₂ cap layer.

However, if we now compare J_c evolution with rms parameter determined in the previous chapter from CeO₂ surface we observe that highest rms value does not correspond with lowest critical current density, Fig. 8-6 (b). Therefore, it corroborates that rms is a non meaningful parameter to evaluate CeO₂ surface quality for biaxially PLD-YBCO growth, similarly to TFA-YBCO/vacuum-CeO₂/YSZ architecture analysed in chapter 6.

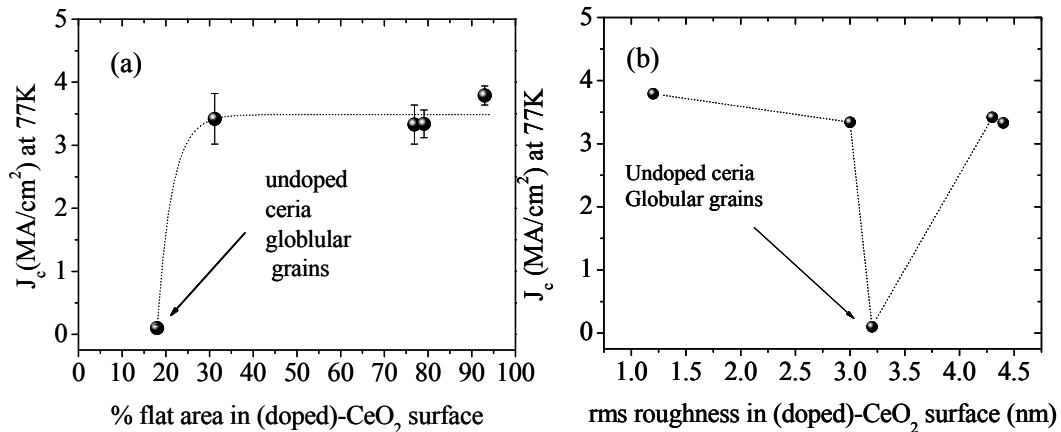


Fig. 8-6 Dependence of J_c at 77K for PLD- YBCO films (a) as a function of atomically flat area of the underlying MOD-modified CeO₂ buffer layer (b) as a function of the statistical rms surface parameter.

In addition, we would like to note that (doped)-CeO₂ cap layer presenting a percentage of atomically flat area over 30% not only improve YBCO film quality, it also leads to lower interface reaction (recall $C_{\text{CBO}} \approx 0.11$ versus $C_{\text{CBO}} \approx 0.21$). These results also suggest a correlation between atomically flat area in CeO₂ film and interface reaction as we previously detected in TFA-YBCO film grown on vacuum-deposited CeO₂ films. However, more experimental work

is needed in order to draw a conclusion on the role of BaCeO₃ phase on YBCO/CeO₂/YSZ system.

8.3 TFA- YBCO on MOD-CGO10 /YSZ single crystal

In order to transfer the knowledge acquired from PLD-YBCO film grown on MOD-doped-CeO₂ film to TFA-YBCO film growth, we first started with CGO10 cap layer grown under reducing atmosphere since this processing atmosphere could be further transferred on metallic substrate (Ni). As a first step we have considered the set of CGO10 samples grown under different growth conditions ((1) 780°C for 8 h, (2) 900°C for 4 h, (3) 1000°C for 8 h and finally (4) 900°C for 8 h) which led different surface morphology (recall section 7.5.1.1.3.2). Therefore, we expect that they influence in a different way the TFA-YBCO growth.

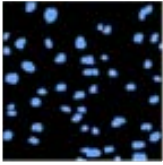
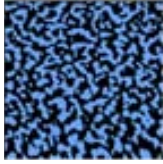
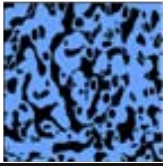

TFA-YBCO films were prepared from anhydrous precursor solution (1.5M) using conditions detailed in the experimental procedure in section 3.1.1.2. Pyrolysis conditions had to be modified for this system otherwise cracked and buckled films were obtained. In this particular case, it was followed the schematic profile described in Fig 3-3(b) but oxygen gas flow rate was increased to 0.075 l min⁻¹.

Initially, processing conditions used for YBCO conversion are based on the optimal results obtained for TFA- YBCO grown on vacuum-CeO₂ (780 °C, 180 min, P(H₂O)= 0.6kPa, P(O₂) = 0.02 kPa and gas flow rate =2.03 x10⁻² m s⁻¹), Fig. 6-12.

In Table 8-III are summarized the most significant results of these films, the relationship between surface morphology of CGO10 cap layer (rms and percentage of atomically flat area) and critical current density of subsequent TFA-YBCO film. We present J_c values at 5K since at 77K it is reduced by two or three orders of magnitude for most of them, indicating poor YBCO film quality.

These results evidence a dramatic dependence of TFA-YBCO film quality on doped-CeO₂ cap layer quality, emphasizing once more that the key parameter to evaluate the quality of CeO₂ surface morphology is the percentage of atomically flat area, indeed, highest J_c value, 1.5 MA cm⁻² at 5K, was obtained on CGO10 cap layer with ~71% of atomically flat area. Therefore, in the following section we have presented a complete characterization of this TFA-YBCO film. However, it is noteworthy that the critical current density for this film is still one order of magnitude below of the current carried for PLD-YBCO on the same CGO10 cap layer.

Table 8-III Processing parameters for CGO10 films, surface morphology properties of CGO10 and critical current density of TFA-YBCO deposited on top

CGO processing conditions	Binary image of CGO10	rms roughness (nm) ±0.3 (2x2µm scan)	% atomically flat grains (±2)	J _c (5K)A cm ⁻²
750°C 8h Ar/H ₂		7.2	12%	<10 ⁵
900°C 4h Ar/H ₂		3.1	46%	<10 ⁵
1000°C 8h Ar/H ₂		4.2	59%	0.3x10 ⁶
900°C 8h Ar/H ₂		4.4	71%	1.5x10 ⁶

8.3.1 TFA-YBCO film on MOD-CGO10 (900°C, 8 h in Ar/H₂)/YSZ

From X-ray θ -2 θ scan, Fig. 8-7 (a), it was noticeable YBCO film with c-axis texture and no detection of intermediate phases such as BaF₂ which indicates that precursors are fully converted to YBCO. However, (200) CGO10 peak reflection has been almost disappeared and high intensity peaks of BaCeO₃ (110) and (200) were detected. This suggests that reaction between YBCO and CGO10 buffer layer during the high-temperature anneal has occurred. By computing the BaCeO₃ formation from X-ray diffraction θ -2 θ Bragg line intensities, Eq. 8-1, we have obtained C_{BCO} ≈ 0.50. This value is quite high in comparison with PLD-YBCO on MOD-derived CeO₂ films presented earlier (C_{BCO} = 0.11 and C_{BCO} = 0.21). Thus, it points that all-chemical multilayers tend to react in more extension than vacuum deposited films.

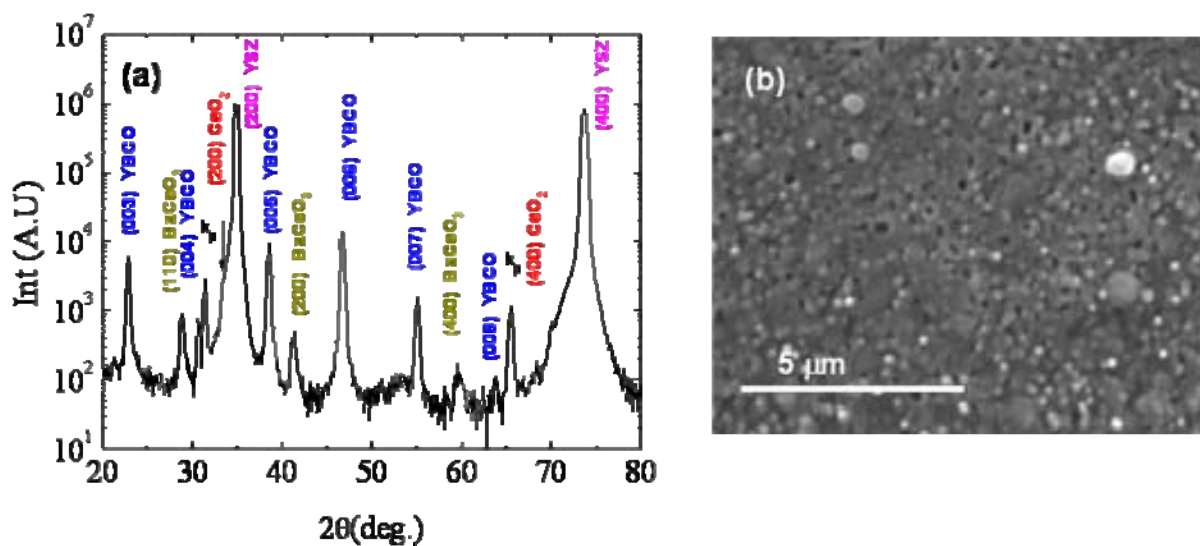


Fig. 8-7 (a) Typical XRD θ - 2θ scan of TFA-YBCO film grown on MOD-CGO10 (Ar/H₂)/YSZ single crystal substrate and (b) SEM micrograph of the as described sample.

From the presence of BaCeO₃ we would expect the detection of secondary phases in YBCO film such as Y₂O₃ or Y₂Cu₂O₅ to compensate Ba deficiency. Unfortunately the most intense reflections for these phases are overlapped with 2θ reflections of YSZ or CeO₂. It is interesting to note that XRD 2θ values for BaCeO₃ reflections are slightly shifted from ‘pure’ BaCeO₃ phase due to the presence of gadolinium. This is not surprising since early studies performed in doped-CeO₂ films, we already detected that the incorporation of aliovalent cation into ceria lattice slightly modify the cell parameter, Fig.7-16.

X-ray ω -scan and ϕ -scan was performed for the YBCO (005) and (103) reflection respectively, $\Delta\omega \approx 2.4^\circ$ and $\Delta\phi \approx 2.1^\circ$, indicating low degree of texture.

SEM image, Fig. 8-7 (b), showed a uniform surface with granular structure decorated with small porous feature. This surface morphology contrasts with the one observed from PLD-YBCO films, probably due to the different YBCO growth mode[100,71]. Under this conditions, as earlier mentioned, J_c value for TFA-YBCO film on MOD-CGO10/YSZ single crystal substrate was 1.5 MA/cm² at 5K but at 77K J_c value fall down to 10^5 A cm⁻², indicating a strong degradation of the film.

Due to TFA-YBCO film properties are not as high as the ones observed in YBCO vacuum deposited systems (see section 8.1.2), efforts are carried out to optimize YBCO growth parameters. As already mentioned at the beginning of this work, a lot of parameters influence the YBCO growth from trifluoroacetate precursors and most of them have to be varied

simultaneously. With these previous results in mind we proceeded on improving TFA- YBCO film quality on MOD-CGO10 buffered YSZ single crystal.

8.3.2 Optimization of TFA-YBCO film on CGO10(Ar/H₂)/YSZ single crystal substrate

8.3.2.1 Study of the residence (wet) time at high temperature

As a first approach, we investigated the influence of holding time under wet atmosphere at the YBCO crystallization temperature on BaCeO₃ formation and YBCO film quality. Dry dwell time was kept constant in 30 minutes. At the same time we increased YBCO growth rate through P(H₂O), based on $R \propto P(H_2O)^{1/2}$ dependence [85]. Both parameters have been investigated with the purpose to reduce the residence time between CeO₂ and YBCO precursors but preserving a fully converted YBCO film. Thus, we increased P(H₂O) from 0.6 kPa to 2.2kPa and wet dwell time was investigated in the range of 45 to 150 min.

Samples were annealed at 780°C in P(O₂)=0.02 kPa, P(H₂O) =2.2kPa and gas flow rate of 2.03 x10⁻² ms⁻¹. The film thickness of YBCO on CGO10 buffered YSZ was measured by profilometry and was in the range 150 nm ± 30.

8.3.2.1.1 Structural and morphological characterization of TFA-YBCO films

To examine the phase development, XRD θ -2 θ scans of YBCO films were carried out, Fig. 8-8. Note that all spectra have been shifted vertically to easily appreciate variations in intensity and secondary phases. All the YBCO (00 l) diffractions peaks are present indicating that YBCO is c-axis oriented. Peaks from YSZ substrate, CeO₂ buffer layer, and BaCeO₃ (BCO) were also observed. We would like to emphasize since (111) BaF₂ Bragg line reflection did not appear in any XRD 2 θ scan, 2 θ = 28.8 and 41.2°, are assigned to BaCeO₃ phase. Secondary reflection at 2 θ = 44.67, 50.96, 52.86 and 58.06° are indexed as Y₂Cu₂O₅, BaCuO_{2+x} and CuO respectively. They can be formed as a result of two pathway reactions: On one hand secondary phases resulting from YBCO conversion [71] and on the other hand as subproducts of interface reaction [198].

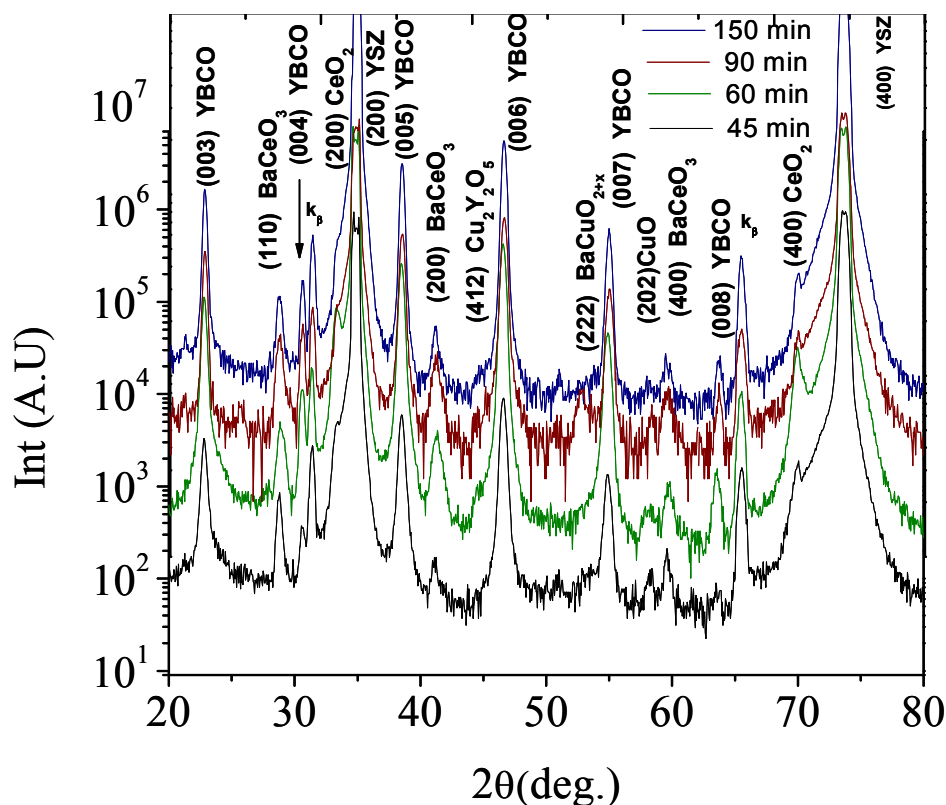


Fig. 8-8 X-ray θ - 2θ reflections of YBCO film on CGO-buffered YSZ substrate. Samples were converted at 780°C in 0.02kPa oxygen for different wet dwell time.

To estimate in a simplified way the evolution of YBCO epitaxy on the wet dwell time, it has been normalized $I(005)$ YBCO peak reflection with $I(k_{\beta})$, similarly to the equation defined for BaCeO₃ quantification (Eq. 8-1). Concomitantly, we have studied BaCeO₃ content evolution on the wet dwell time and results are shown in Fig. 8-9. In both phases it is reflected a similar behaviour, at $t(\text{wet})=60$ minutes, Bragg line intensity saturates. This indicates that YBCO conversion on MOD-CGO10 finishes after 60 minutes exposure in wet atmosphere. On the other hand, BaCeO₃ formation stops after 60 minutes. Therefore from this dependence it is likely that YBCO conversion is correlated to BaCeO₃ formation. This correlation is not surprising considering that for the formation of both it is required that H₂O decompose BaF₂ phase. Additionally, in the same figure it has been anticipated values of $t=0$ obtained from a quench study presented forth. It is interesting to evaluate these results because the existence of a fraction of 0.45 of YBCO (00 l) oriented at $t=0$ indicates that YBCO c -axis oriented grains started to grow during the heating rate. By contrast, low fraction of BaCeO₃ phase (lower than 0.2) suggested that interface reaction takes place mostly in dwell step at 780°C rather than during the heating rate.

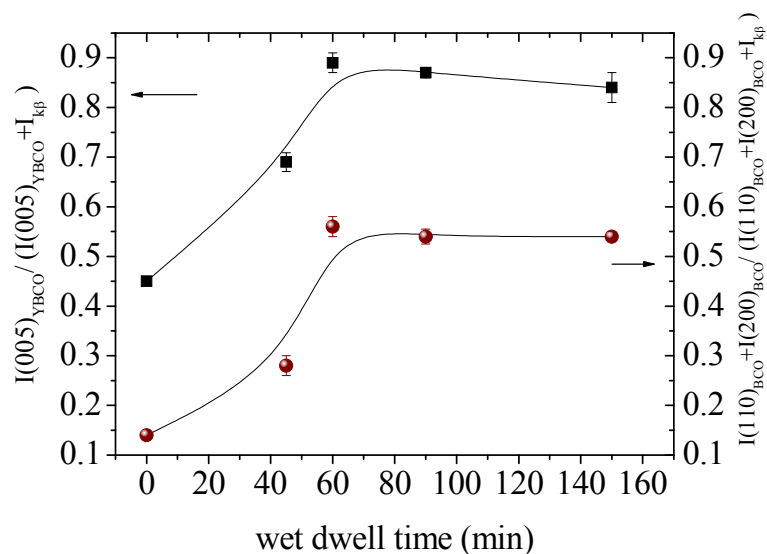


Fig. 8-9 Evolution of YBCO epitaxy and BaCeO₃ formation on the wet dwell growth time.

Nevertheless, by further texture analysis from ω -scan of (005) YBCO reflection, we detected a slight film degradation at prolonged heat treatment, as could be seen in FWHM values listed in Table 8-IV. Since C(BCO) is maintained nearly constant at $t(\text{wet}) \geq 60$ min we could not assign YBCO texture degradation to BaCeO₃ formation, indeed, based on the work reported by Xu [128] we suggest that it is due to long exposure to wet atmosphere at high temperature.

Therefore, based on this structural data, at $T=780^\circ\text{C}$, highest degree of crystallinity and epitaxy is obtained by processing YBCO during 60 min wet+30 min dry despite large interface reaction.

Table 8-IV Processing parameters and dependence on wet dwell time of (TFA) YBCO films deposited on (MOD)CCGO10 cap layer

Sample	T(growth) (°C)	P(H ₂ O) (kPa)	P(O ₂) (kPa)	Wet dwell (min)	Dry dwell (min)	YBCO(005) FWHM (deg) ±0.1	$\frac{I(005)_{\text{YBCO}}}{[I(005)_{\text{YBCO}}+I_k]}$	C _{CBO}	J _c (A/cm ²) 5K	T _c (K)
YCYt45	780	2.2	0.02	45	30	1.6	0.74	0.28	1.05x10 ⁶	90
YCYt60	780	2.2	0.02	60	30	0.9	0.92	0.56	8.32x10 ⁶	90
YCYt90	780	2.2	0.02	90	30	1.4	0.82	0.54	1.44x10 ⁶	87
YCYt150	780	2.2	0.02	150	30	1.8	0.86	0.54	2.55x10 ⁶	88

From the surface morphology studied by SEM we do not observed any significant microstructural evolution of the YBCO film with the wet dwell time. In Fig. 8-10 it is shown a typical SEM top-view micrograph of TFA-YBCO film on MOD-CGO10 /YSZ substrate. We observe a continuous and dense film. Small grains with spheroidal morphology decorate the surface of the film, no a-axis grains were observed. By previous μ -Raman measurements performed in our group we presume that these grains are BaCuO₂ [121].

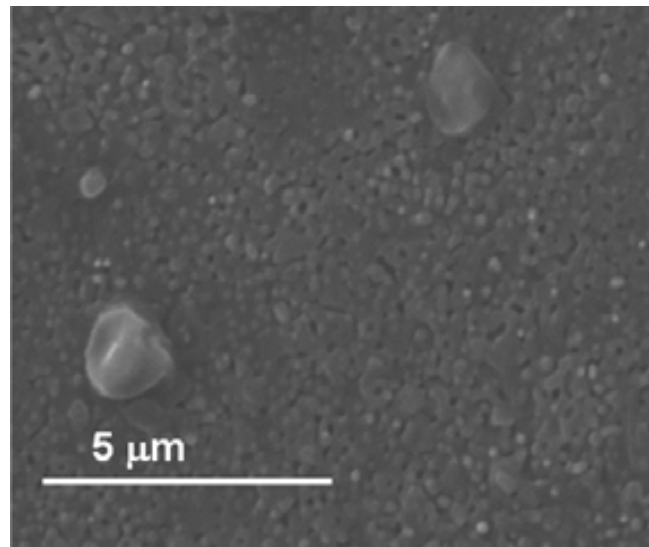


Fig. 8-10 SEM micrograph of TFA-YBCO film on MOD-CGO10 deposited on YSZ single crystal grown at 780°C for 150 min (wet dwell).

8.3.2.1.2 Superconducting properties

From critical current density measurements at 5K it can be clearly seen that superconducting property follows the same trend as the degree of crystallinity of YBCO: In the initial period (45min) J_c increased with annealing dwell time and crystallinity. At a time of 60 min wet dwell, J_c and film crystallinity reached about the maximum. When we continued to prolong the high-temperature annealing time I(005)YBCO and I(BaCeO₃) remain almost constant but J_c decreased slightly correlating with YBCO texture analysis. Thus, film degradation is not due to BaCeO₃ formation at prolonged growth time being consistent with XRD analysis. Film degradation occurs due to contact with wet atmosphere at high temperature. Similar dependence was also found for TFA-YBCO/LAO model system [249,99].

In conclusion, 60 min anneal in humid atmosphere resulted in the best developed texture, crystallinity and highest J_c value despite BaCeO₃ formation

8.3.2.2 Study of the influence of P(H₂O)

Optimistic by the important improve in J_c value when P(H₂O) was slightly increased to 2.2 kPa for 90 minutes growth (60 wet and 30 dry dwell), we inspected the water partial pressure influence. Temperature was fixed at 780°C for a total residence time of 90 minutes, P(O₂) = 0.02 kPa, gas flow rate = $2.03 \times 10^{-2} \text{ m s}^{-1}$ and P(H₂O)–values have been varied from 0.6 to 3.3 kPa. In addition, it was investigated the influence of water partial pressure during the heating ramp. To do that, we carried out an experiment in which the flow of humid gas was injected into the furnace once the furnace temperature reached 780°C. Results have been compared to sample grown at 2.2 kPa previously characterized.

8.3.2.2.1 Structural and morphological characterization

X-ray diffraction patterns, out-of-plane texture analysis and J_c have evidenced some evolution of the microstructure of the films with P(H₂O). Fig. 8-11 shows a comparison of XRD θ -2 θ scan of final YBCO films obtained at different water partial pressure.

As a general trend, all the YBCO films display the (00 l) diffraction peaks indicating that they are c-axis oriented. (110) and (200) reflections of BaCeO₃ simultaneously with slight decrease of (h 00) CGO10 peak reflections, point out the existence of interface reaction. In certain growth conditions other secondary phases have been observed like Ba_{1-x}Y_xF_{2+x} (BYF), BaCuO₂, BaF₂, CuO and Y₂Cu₂O₅. The reasons why they exist are considered below after analyzing the evolution of the degree of YBCO crystallinity and BCO formation.

In Fig. 8-12 we studied the degree of YBCO epitaxy and texture dependence on P(H₂O) from samples grown in the same processing conditions (i.e. humid gas injected at the beginning of the heating rate, ~100°C). In this figure we observed that at lower P(H₂O), i.e. 0.6kPa, degradation of the film quality is evidenced by very low I(005)YBCO peak reflections and high FWHM value from ω -scan. On the other hand, for YBCO film grown at higher P(H₂O) no important variations have been detected in a change in the relative heights of the YBCO reflections and FWHM (005) comparing with P(H₂O)=2.2kPa.

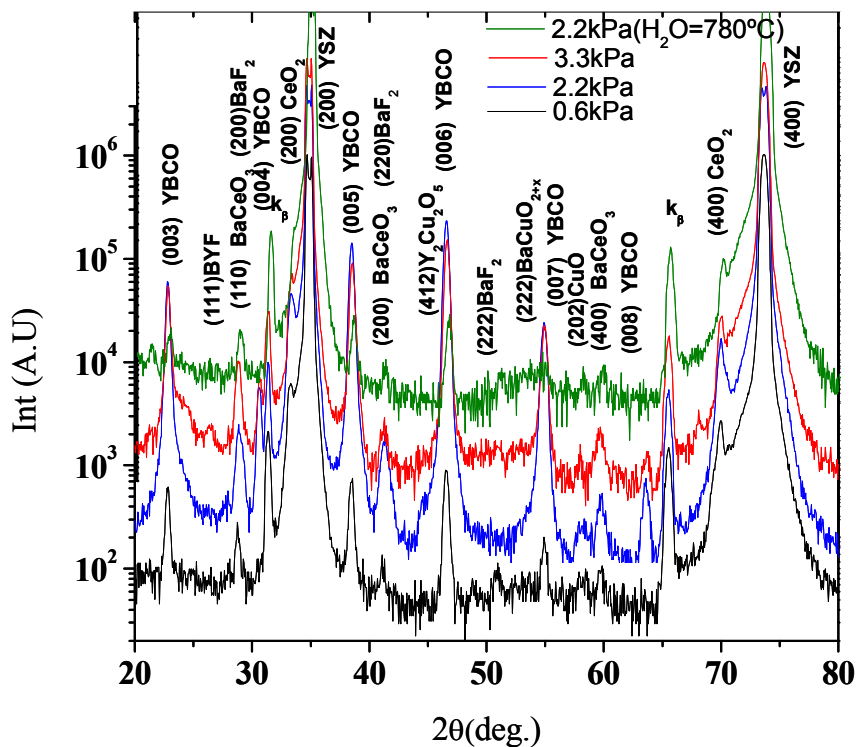


Fig. 8-11 TFA-YBCO on MOD-CGO grown at 780°C for 90 min (60 min wet +30 min dry) at different water partial pressure.

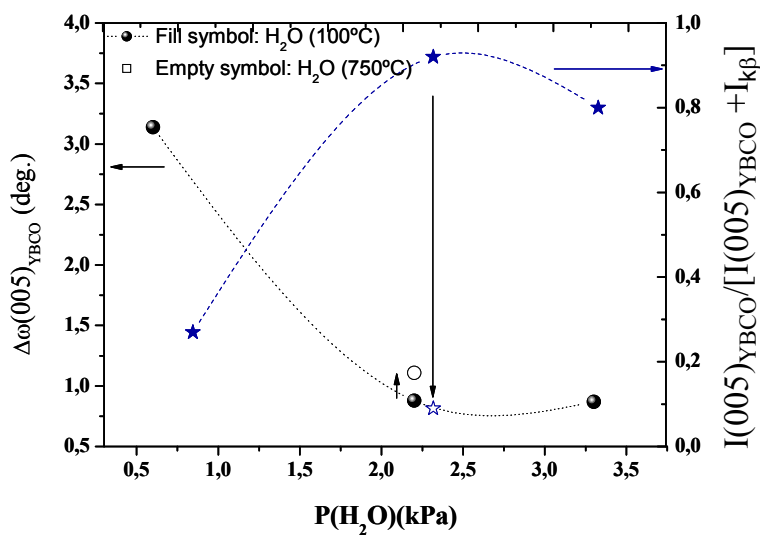


Fig. 8-12 Dependence of the normalized ratio of YBCO(005) peak intensity to $I(k_{\beta})$ and the $\Delta\omega(005)$ YBCO on $P(H_2O)$ -value.

For these films we have also studied the tendency of BaCeO₃ on P(H₂O)-values and results are listed in Table 8-V. Given that (111) BaF₂ reflection has been detected in θ -2 θ scan for P(H₂O) = 0.6 and 3.3 kPa values, the computation of BaCeO₃ content for these samples could be masked. Recall that the most intense reflections of BaCeO₃ matches with those from BaF₂ phase.

In order to minimize BaF₂ contribution on BaCeO₃ quantification, we have subtracted I(200) BaF₂ from I(110) BaCeO₃ (overlapped at $2\theta \sim 28^\circ$) following the methodology proposed recently by Wesolowski [201]. It consists of calculating I(111)BaF₂/I(200)BaF₂ ratio from a quench sample in which neither YBCO nor BaCeO₃ phases are present. Then, since BaF₂ intensity ratio is constant, when (111) BaF₂ peak reflection appears in XRD θ -2 θ scan and I(200)BaF₂ peak reflection matches with (110) BaCeO₃ peak reflection, it can be figure out the intensity for (200) BaF₂ Bragg line reflection from the previously calculated ratio (I(111)BaF₂/I(200)BaF₂). Finally, I(200)BaF₂ is subtracted from total intensity of Bragg line reflection at $2\theta \sim 28^\circ$ and results I(110)BaCeO₃ contribution.

Similarly to the wet dwell time study discussed before, we can observe that BaCeO₃ follows YBCO tendency. Taking into account that for sample grown at P(H₂O)=0.6kPa we identified intense reflections of BaF₂ from XRD θ -2 θ scan, we suggest that YBCO texture degradation could be related to an uncompleted YBCO formation due to insufficient supply of H₂O at the growing interface [137,99]. This proposal is also consistent with low content of BaCeO₃ since interface reaction could not take place if BaF₂ does not decompose providing Ba²⁺ cations [201]. At high P(H₂O)-values it was also found a microstructural degradation in YBCO film, which could not be attributed to BaCeO₃ since C_{BCO} value has not increased from P(H₂O)=2.2kPa. Based on preliminary studies [99] we suggest that it could be related to the high HF concentration accumulated at the growing interface. It might happen that gas flow becomes insufficient to fully evacuate the high concentration of HF gas generated at high P(H₂O), and therefore it is supposed that some gas stagnancy occurs [85]. However, this correlation has to be verified in J_c studies.

We now turn to study the sample which has been grown under dry heating rate. From X-ray diffraction θ -2 θ scan, Fig. 8-11 (green trace), we observe an important decrease in (00 l) YBCO and in BaCeO₃ reflection peaks. Once more (00 l) YBCO formation was correlated to BaCeO₃ formation, Eq. 8-1. Moreover, from Fig. 8-12 (empty symbols) we have also detected YBCO texture degradation. It suggests that the incorporation of H₂O at 780°C delayed the YBCO conversion and also interface reaction. Therefore, 60 min in wet atmosphere leads to uncompleted YBCO formation.

Table 8-V Processing parameters and dependence on water partial pressure of (TFA) YBCO films deposited on (MOD)CGO10 cap layer

Sample	T(growth) (°C)	P(H ₂ O) (kPa)	P(O ₂) (kPa)	Wet dwell (min)	Dry dwell (min)	YBCO(005) FWHM (deg)±0.1	$\frac{I(005)_{\text{YBCO}}}{[I(005)_{\text{YBCO}}+I_{\text{CP}}]}$	C _{CBO}	J _c (A/cm ²) 5K	T _c (K)
YCYP06	780	0.6	0.02	60	30	>3.1	0.27	0.09	<0.1x10 ⁵	-
YCYt60	780	2.2	0.02	60	30	0.9	0.92	0.56	8.32x10 ⁶	90
YCYP33	780	3.3	0.02	60	30	0.9	0.80	0.35	5.59x10 ⁵	85
YCYP22H*	780	2.2	0.02	60	30	1.1	0.09	0.12	<0.1x10 ⁵	-

* Water has been introduced into the furnace at 780°C, i.e, dry heating ramp.

From the SEM micrographs, shown in Fig. 8-13, we can find that increasing water partial pressure from 0.2kPa to 2.2 kPa (Fig. 8-13(a-b)), the granular structure evolves to smoother and denser one with some precipitates on top corresponding to BaCuO₂ phase. No differences have been detected in surface morphology between the sample grown at P(H₂O) =2.2kPa and P(H₂O)=3.3 kPa. Note that no a-axis oriented grains appeared in YBCO films. YBCO film grown in dry heating ramp (Fig. 8-13(d)) displays similar surface morphology as sample grown at P(H₂O)= 0.6kPa, following similar behaviour as XRD results.

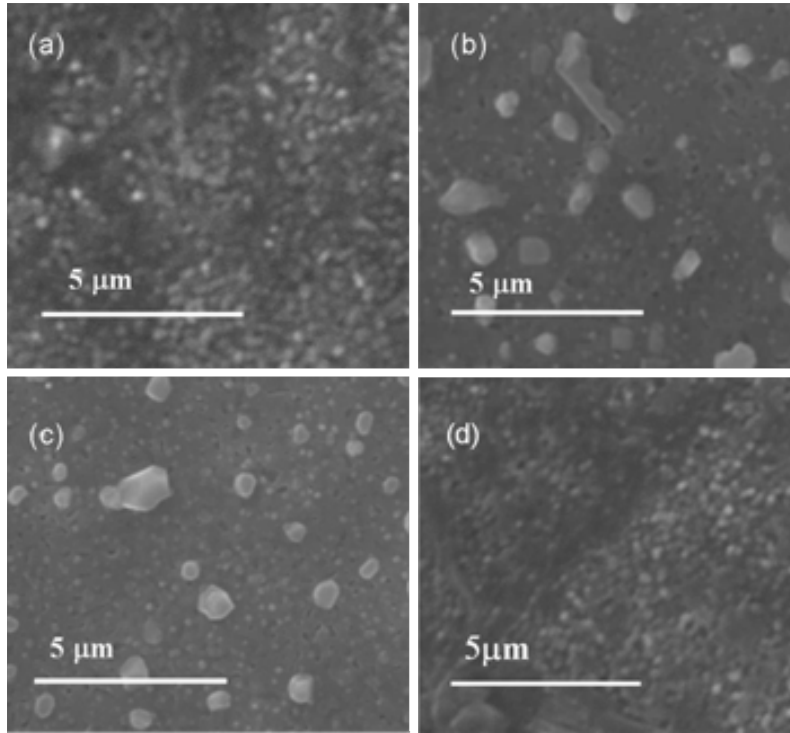


Fig. 8-13 SEM micrographs of 0.15 μm TFA-YBCO film annealed at 780°C at different P(H₂O)-values (a)0.2 kPa (b) 2.2 kPa (c) 3.3 kPa (d) 2.2kPa (H₂O=780°C)

8.3.2.2.2 Superconducting properties

Superconducting measurements were also performed for these set of samples and it was found maximum J_c value for sample grown 90 min (60+30) at P(H₂O)=2.2kPa in excellent agreement with structural and microstructural data presented above. It is interesting to remark that the highest J_c value (5K) has been obtained for the sample that displays higher I(005) YBCO from XRD θ -2 θ scan and simultaneously higher C_{BCO} . On the other hand, samples grown at P(H₂O)=0.6kPa, 3.3kPa and 2.2kPa (H₂O 780°C) showed lower J_c values as well as lower degree of YBCO texture and lower C_{BCO} . Thus, it allows us to correlate degraded film

quality with uncompleted conversion or ineffective evacuation of high concentration of residual products (HF).

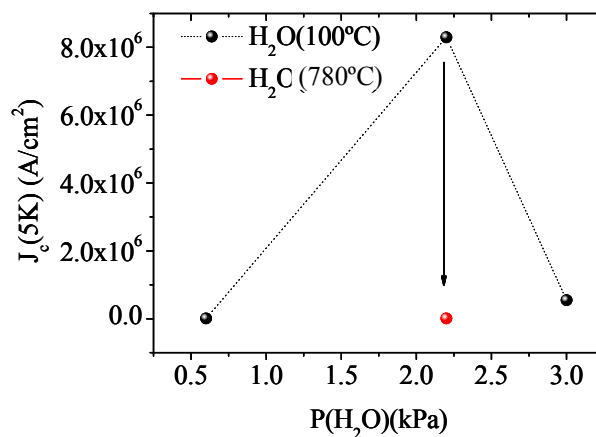


Fig. 8-14 Water partial pressure dependence on J_c (5K) for TFA-YBCO films grown on MOD-CGO10/YSZ substrates.

In conclusion, we observed that $P(\text{H}_2\text{O})$ parameter play a non-negligible role on TFA-YBCO grown on MOD-CGO10 films according to previous studies performed on LAO single crystal [99]. From the range of investigated conditions at 780°C, we could not detect BaCeO₃ formation from YBCO growth. However, it is very important to remark that TFA-YBCO film grown on MOD-CGO10 cap layer can be biaxially textured despite BaCeO₃ formation. This is a clear indication that BaCeO₃ should take place after YBCO nucleation on CeO₂ surface and therefore, efforts have to be made on YBCO nucleation step. Thus, based on this hypothesis we have focused on studying the YBCO film quality as well as interfacial reaction at different growth temperatures.

8.3.2.3 Quench study

Finally, in this study we tried to establish when TFA-YBCO initially forms on MOD-CGO10 cap layer in order to find a ‘sweet spot’ where YBCO nucleates c-axis oriented and interface reaction has not extensively occurred.

We have prepared TFA-YBCO quenched films by cooling rapidly during crystallization at 780°C and at 770°C. Experimental conditions are described in detail in Fig. 8-15.

To investigate phase evolution, a series of XRD θ - 2θ scan of quenched films were performed and compared to a film completely grown (780°C 90 min), as can be seen in Fig. 8-15. Film quenched from 770°C exhibit only broad features identified as BaF₂ [71]. In sample quenched from 780°C, detection of (00 l) YBCO reflection confirms the initial formation of the YBCO phase. Increase of intensity of diffraction peaks $2\theta \approx 28.8$ and 41.2° initially assigned to BaF₂ phase, together with slight decrease of I(200)CGO peak reflection are consistent with formation of BaCeO₃. Thus, $2\theta \approx 28.8$ and 41.2° can be indexed as BaF₂ and BaCeO₃. As we anticipated in section 8.3.2.2.1, intensity of both contributions can be elucidated. By comparing XRD patterns of film quenched from 780°C and film quenched after holding 90 min at 780°C, we observed that after holding 90 min at 780°C all intermediate phases have been consumed, I(YBCO) Bragg line reflections have strongly increased and it is odd that I(BaCeO₃) is almost constant.

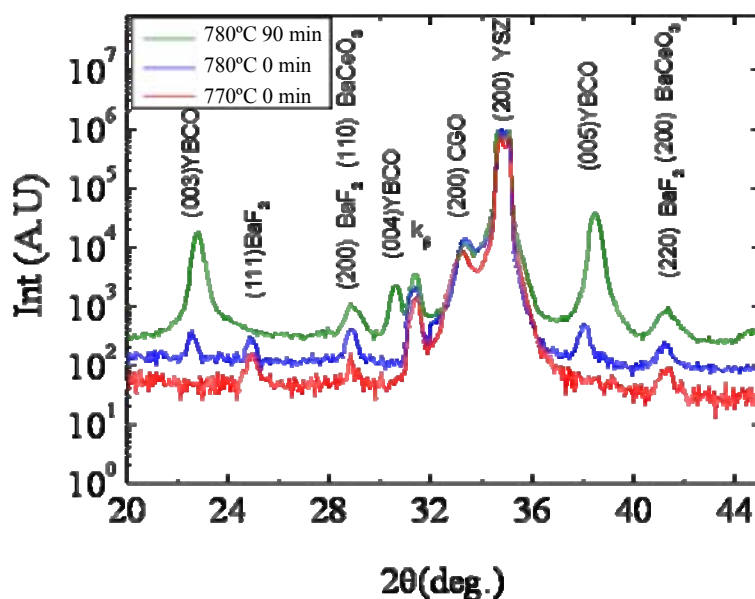


Fig. 8-15 X-ray diffraction patterns of TFA-YBCO film on MOD-CGO10/YSZ quenched from 770°C, from 780°C and quenched after holding 90 min at 780°C.

Interestingly, TEM investigations performed on sample quenched from 780°C revealed a highly oriented and dense YBCO film in which BaCeO₃ formation extends almost all the 30 nm Gd-CeO₂ thickness, see Fig. 8-16. According to XRD analysis, two different orientations for BaCeO₃ are also detected. The remaining areas were occupied by the epitaxially aligned (200)Gd-CeO₂ as exhibited in Fig. 8-16(b). These are the earlier observation of the propensity for the alignment of the (00 l) YBCO despite being under layered by BaCeO₃, and at the same time, this evidences that YBCO should nucleate onto Gd-CeO₂ layer and afterwards starts

interface reaction considering its lattice mismatch parameter (Table 1-I). HRTEM suggests that YBCO growth initially starts from interface of the precursor film and CeO₂. The atomically flat terraced areas are usually viewed as the place where the nucleation energy is less than on a rougher surface and thus may provide ideal position for YBCO nuclei. We propose that interface reaction should begin in hillocks/grain boundaries (space between terraces) where Ba-rich precursor could diffuse to CeO₂ and form BaCeO₃ phase.

Due to YBCO follows an island growth mode, it is suggested that once YBCO nuclei have been formed on atomically flat surface, by coarsening the film covers CeO₂ surface and therefore, the subsequent BaCeO₃ formations does not much influence on the quality of YBCO epitaxy. Moreover, this hypothesis would support the strong influence of percentage of atomically flat surface on YBCO growth.

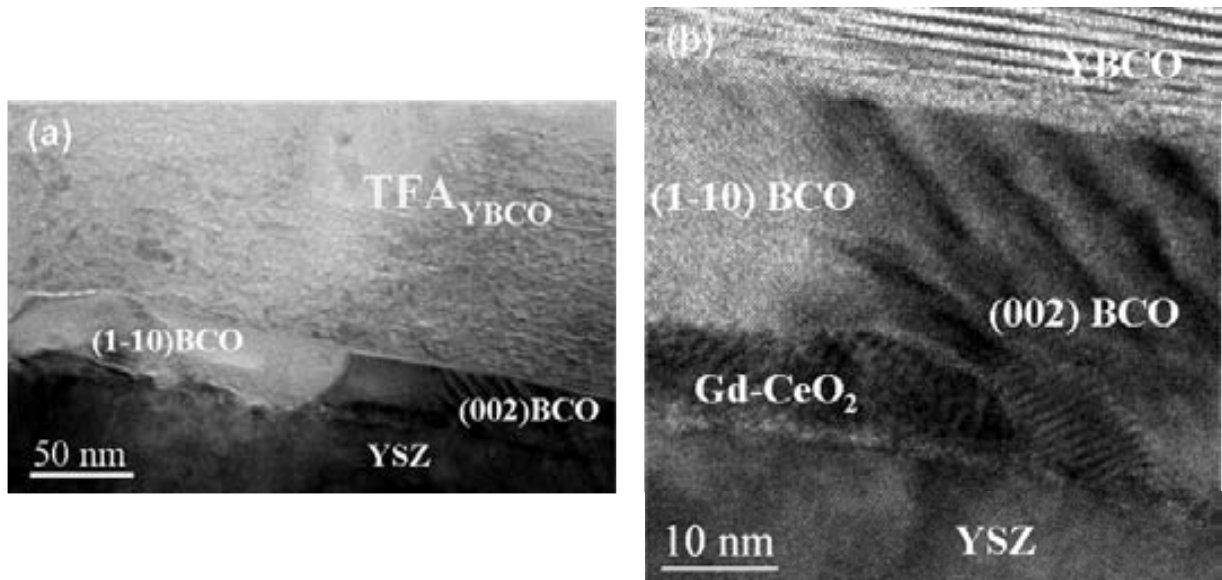


Fig. 8-16 Cross-sectional TEM images viewed along (110) axis of TFA-YBCO quenched film prepared by cooling rapidly after holding at 735°C for 10 minutes.

Finally, this massive transformation to BaCeO₃ at 780°C explains the fact that in the study of influence of residence time at 780°C, BaCeO₃ content did not increase much further after 60 minutes (wet dwell) at high temperature. From these XRD and TEM investigations we have proposed to replace 780°C to 770°C as growth temperature to sluggish interface reaction and therefore improve YBCO epitaxial growth.

8.4 Optimal TFA-YBCO growth process on MOD-CGO10/YSZ single crystal substrate

In accordance with the optimized values found above we settled the following growth parameters: $P(\text{O}_2) = 0.02\text{kPa}$, $P(\text{H}_2\text{O}) = 2.2\text{kPa}$, gas flow rate = $2.03 \times 10^{-2} \text{ m/s}$, $t = 80 \text{ min}$ wet+30 min dry and in Fig. 8-17 it is shown a schematic diagram of the followed heating profile.

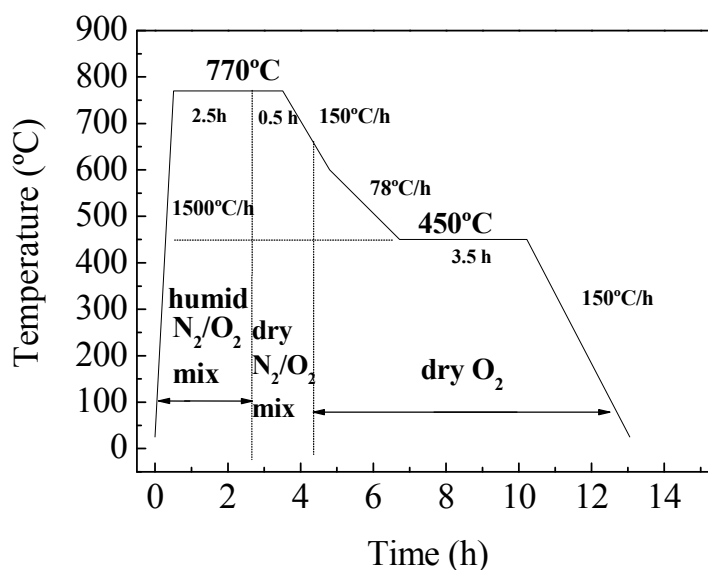


Fig. 8-17 Heating profile for the high-temperature anneal of TFA-YBCO on MOD-CGO10/YSZ substrate.

8.4.1 Structural characterization

XRD θ - 2θ scan for this sample, Fig. 8-18, yields stronger (00 l) YBCO peak reflections indicating good YBCO films. There is evidence of the formation of BaCeO₃ at the end of the process besides CuO and Y₂Cu₂O₅ phases. In this case we have been obtained $C_{\text{BCO}} = 0.54$, it does not strongly differ from the previous TFA-YBCO/CGO10/YSZ samples.

However, the high crystalline perfection of the YBCO is demonstrated by the rocking curve value, $\Delta\omega=0.5^\circ$, measured on the (005) reflection, similar value to the CGO cap layer (0.3°). Moreover, this film also shows a good in-plane texture by ϕ -scan of (103) YBCO= 1.4° , Fig. 8-19. It is a clear improvement in degree of epitaxy from previous TFA-YBCO films. In reality, we achieved similar degree of texture as PLD-YBCO films presented at the beginning of this chapter.

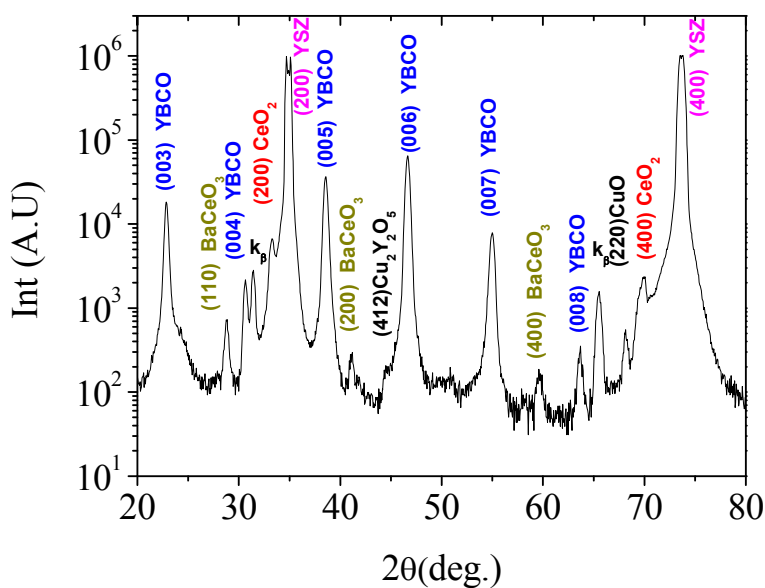


Fig. 8-18 TFA YBCO grown on MOD-CGO/YSZ substrate at 770°C

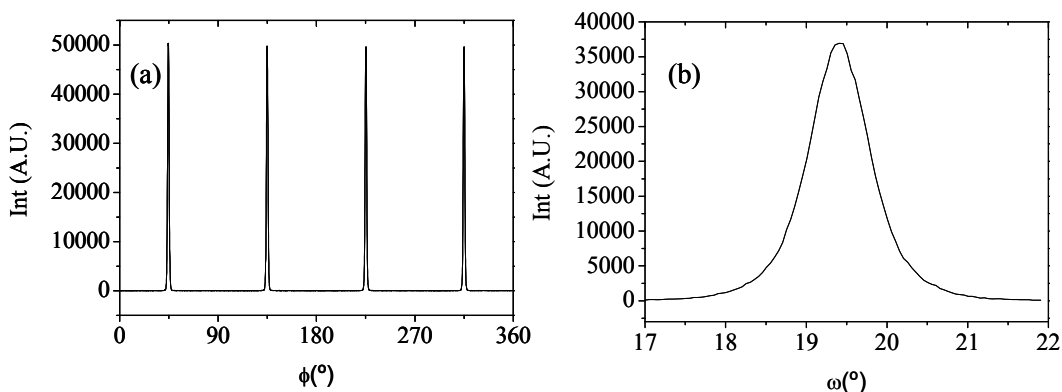


Fig. 8-19 XRD texture analysis of TFA-YBCO film (a) $\Delta\phi(103)YBCO = 1.3^\circ$, (b) $\Delta\omega(005)YBCO = 0.7^\circ$

By means of transmission electron microscopy (TEM), it was further investigated YBCO interface quality. Fig. 8-20 shows cross-sectional TEM images of the YBCO film grown on 10%Gd-doped ceria. Well textured YBCO film has been formed coinciding with the results observed in XRD data. BaCeO₃ covers nearly the entire YSZ surface (~30 nm thick) in well agreement with the massive transformation of Gd-CeO₂ to Gd:BaCeO₃ anticipated in the previous quench studied and in the above XRD θ -2 θ scan, Fig. 8-15. In all the areas observed there is no traces of CGO phase, contrasting with XRD θ -2 θ scan. However, the interface between the YBCO and Gd-CeO₂ is flat and sharp. Taking into account the large mismatch between YBCO and BaCeO₃ (Table 1-I), these TEM images are again an evidence that confirm BaCeO₃ reacts after YBCO nucleation. HRTEM suggests that YBCO growth initially starts from interface of the precursor film and CeO₂. Similar results are recently reported by Matsuda et al.[199] who carried out transmission electron microscopic studies on crystallization of TFA-YBCO film on PLD-CeO₂ cap layer.

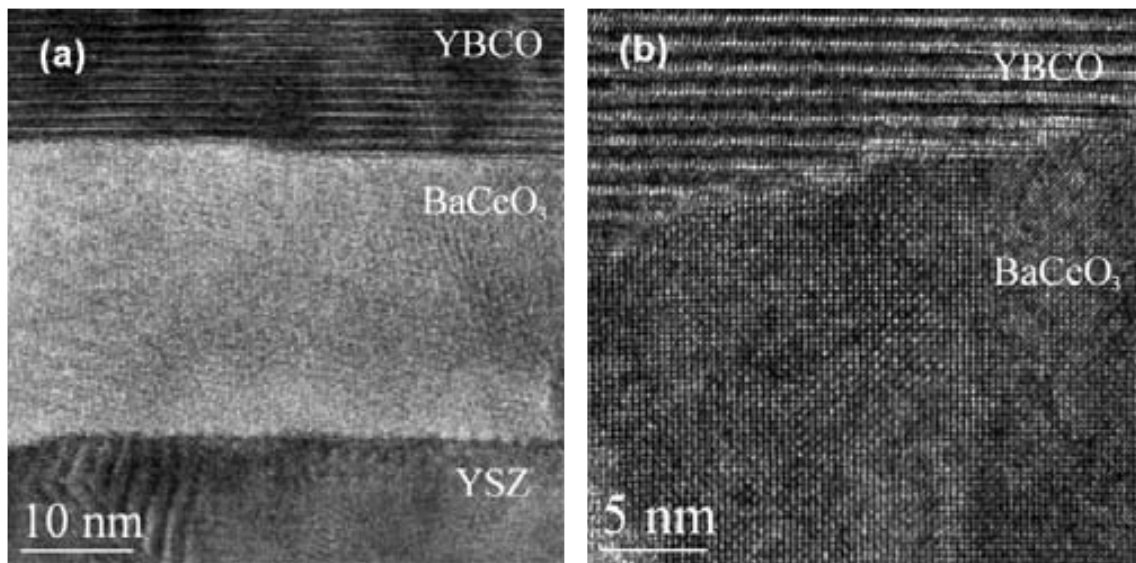


Fig. 8-20 Cross-sectional TEM images of TFA-YBCO film grown at 770°C by high temperature heating profile on MOD-CGO buffered YSZ.

Notice that these cross sectional TEM images strongly differ from the one observed for TFA-YBCO/sputt-CeO₂ (Ar/H₂/H₂O)/YSZ sequence in Fig. 6-16(b). There, it was hardly observed BaCeO₃ phase even if YBCO heating profile was not optimized. This further confirms that interface reaction occurs in less extension between vacuum deposited layers in the TFA-YBCO-CeO₂ system. We do not have a clear explanation by such differences between sputt-CeO₂ and MOD-CGO10 films but we suggest that high interface reaction in chemical layers is

probably due to an enhanced porosity of the films and hence of the contact surface area among the cap layer and the YBCO film [38,176]. Indeed, considering AFM height profile analysis of both sputtering- CeO₂ and MOD-CGO10 films (see Fig.6-3(c) and Fig. 7-23(a)), they can be distinguished by the deepness of voids and hillocks being higher in MOD-CGO10 films.

8.4.2 Superconducting and electrical properties

We found that TFA-YBCO film grown on MOD-CGO10 cap layer through heating profile described in Fig. 8-17 showed the most remarkable effect of improvement in the J_c value at 77K in comparison with YBCO grown on MOD-CeO₂ cap layer, as can be seen in Fig. 8-21 In fact, for TFA-YBCO/MOD-CGO10/YSZ single crystal substrate we have calculated J_c ratio of $J_c(5K)/J_c(77K)=12.4$. This is typical value of high quality and stoichiometric YBCO film. We would like to mention that this ratio has not been computed in the previous samples since all displayed $J_c(77K)<10^4$ A cm⁻² which indicates beforehand that the film quality is degraded. Critical current density of TFA-YBCO/MOD-CGO10/YSZ lead highest J_c value of 2.3 MA/cm² at 77K and the transition temperature is found to be $T_c\sim 90$ K.

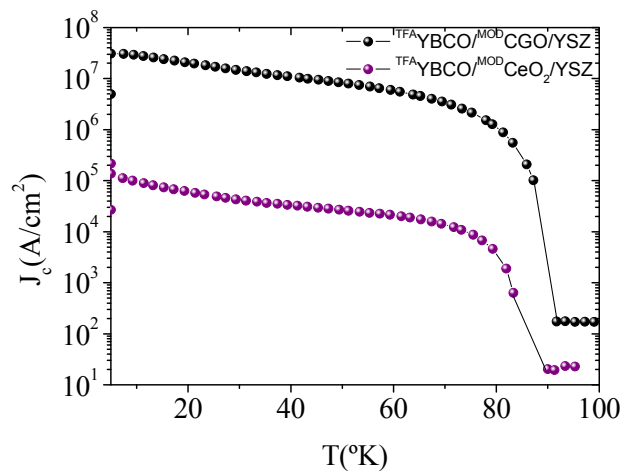


Fig. 8-21 Critical current as a function of temperature of TFA-YBCO thin films grown on MOD-CGO10/YSZ (in black) and MOD-CeO₂/YSZ single crystals (in purple).

From Fig. 8-22 we observed that these films presented a critical temperature of 90 K and that both residual and normal state resistivity values are similar to that obtained for YBCO/LAO model system [34,83] being well consistent with high critical current density showed above.

Therefore, this allows us to conclude that MOD-CGO10 cap layer grown at 900°C for 8 h in Ar/H₂ atmosphere, despite carbon impurities were not fully removed and consequently epitaxial fraction was 77%, it is a very good cap layer to obtain biaxially textured TFA-YBCO film with J_c value of 2.3 MA cm⁻² at 77K. Thus, this is a feasible cap layer for all-chemical YBCO coated conductors in particular for Ni-RABiT substrates.

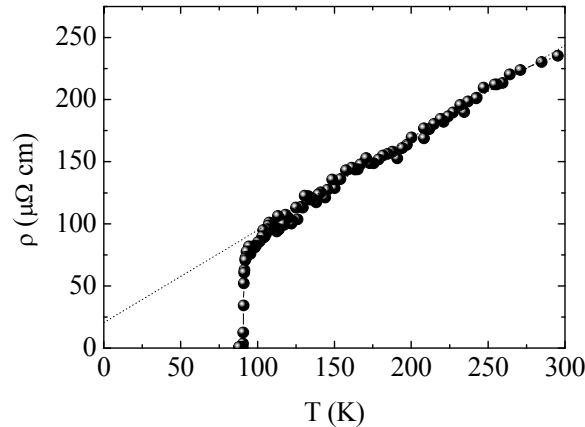


Fig. 8-22 Temperature dependence of resistivity of TFA-YBCO thin film deposited on MOD-CGO10/YSZ single crystal.

Finally, we have studied the dependence of J_c at 77K of TFA-YBCO film on the percentage of atomically flat area of differently processed MOD-modified CeO₂ cap layer on YSZ single crystal, similarly to the study carried out on PLD-YBCO films (see section 8.1.2). It is shown in Fig. 8-23. We observe a gradual increase in the J_c value from 0 to $\geq 70\%$ contrasting with a sharp transition in PLD-YBCO films, see Fig. 8-6. In this case, 30% of atomically flat area is not enough to obtain fully biaxial YBCO film and it is reflected by J_c (77K) ~ 1.8 MA cm⁻². Further investigation is required to determine if beyond 80% of atomically flat area, J_c value saturates. Anyway, this demonstrates that TFA-YBCO film is more sensitive to the percentage of atomically flat area of CeO₂ cap layer than PLD films. These effects are not surprising considering that growth mode of PLD (bi-dimensional growth) and CSD films (island coalescence) are completely different as well as deposition route as we anticipated in section 1.2.3.2.2). Therefore, parameters like contact surface area, residence time at high temperature as well as pathway reaction make CSD film more sensitive to quality of the underlying film. However, we have demonstrated that by modifying TFA-YBCO growth parameters we can

favour the accommodation of *c*-axis nuclei on CeO₂ surface and achieve high quality film similar to vacuum deposited films.

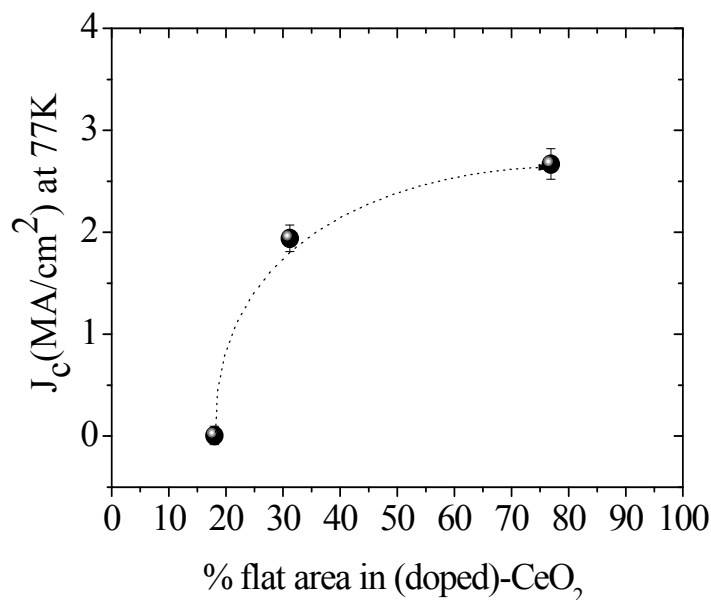


Fig. 8-23 Dependence of J_c at 77K for MOD-YBCO films as a function of atomically flat area of the underlying MOD-modified CeO₂ buffer layer

8.5 Conclusions

In this chapter we have described an important advance in processing TFA-YBCO films on MOD-doped ceria buffered YSZ single crystal with J_c value of 2.3 MA/cm² at 77K.

We have analyzed the influence of MOD-CeO₂ cap layer quality on both PLD and TFA YBCO epitaxy and superconducting properties. In particular we have presented evidences that percentage of atomically flat area and high texture of CeO₂ cap layer determine YBCO film quality, rather than BaCeO₃ formation.

We have observed that CeO₂ films with low percentage of atomically flat area (~18%) and fibre texture induce partially epitaxial PLD-YBCO films and BaCeO₃ formation ($C_{BCO} \approx 0.21$). As a result, J_c values fall down to 10⁵ A cm⁻² at 77K. By contrast, doped CeO₂ with 10%

of Gd³⁺ or Zr⁴⁺, which improved epitaxial fraction and increase the percentage of flat area above 30% leads to biaxially textured PLD-YBCO film with J_c values of 3MA cm⁻² at 77K. In this case, interface reaction has been minimized ($C_{\text{BCO}} \sim 0.11$).

We have investigated the influence of 10% Gd³⁺-doped-CeO₂ cap layer quality (grown at different time and temperature) on TFA-YBCO growth. It is particularly remarkable that TFA-YBCO film is more sensitive to the underlying surface layer than PLD-YBCO film. Around 70% of atomically flat area in CGO10 was required to obtain J_c values around 1.5 MA cm⁻² at 5K which is quite far from the values obtained for PLD-YBCO film grown on the same cap layer. Additionally, we observed that BaCeO₃ phase has been formed in more extension in these all-chemical deposited systems ($C_{\text{BCO}} \approx 0.54$). This has been mainly attributed to the different growth mode of YBCO. However, TFA-YBCO film quality grown on the optimal CGO10 cap layer (grown at 900°C for 8h in Ar/H₂) has been strongly improved by modifying growth parameters (time, temperature and P(H₂O)).

We have carried out a systematic study of the influence of residence time (wet) at high temperature on YBCO film quality. We have investigated the range of 45-150 min in wet atmosphere and optimal results have been obtained for t (wet)= 60 min. Shorter time (45 min) the quality of the YBCO film is degraded due to intermediate phases have not been fully converted. By contrast, at long processing time ($t=150$ min), the main consequence of film degradation is the long exposure to wet atmosphere at high temperature.

Then, we have carried out a systematic study of the influence of P(H₂O) on TFA-YBCO film quality at 780°C and total residence time of 90 min (60 min wet and 30 min dry). Once more we have observed high interface reactivity. Low J_c observed for P(H₂O)=0.6 and 3.3 kPa has been associated to poor YBCO texture induced by uncompleted reaction and HF gas stagnancy respectively. Concomitantly, it has been analysed the influence of H₂O during the heating rate incorporating H₂O in the gas flow at 780°C (we usually switch on wet atmosphere at 100°C). For this case, we have also detected an incomplete conversion. Optimal film quality has been detected for P(H₂O)=2.2 kPa.

By TEM analysis of quenched sample from 780°C we have observed that c-axis YBCO grains have been nucleated and grown and 30nm-thick CGO10 cap layer has nearly converted to Gd:BaCeO₃. High alignment of YBCO grains has suggested that c-axis YBCO firstly nucleates on CeO₂ films which provide lower lattice mismatch than BaCeO₃ and then, interface reaction occurs. From this study we have lowered growth temperature from 780°C to 770°C and we have successfully improved the epitaxial growth of TFA-YBCO film. We have found TFA-YBCO film carrying J_c (77K) ~ 2.3 MA cm⁻² and excellent texture even CGO10 cap layer has fully

converted to Gd:BaCeO₃. Therefore, it has been verified that despite CGO10 film grown at 900°C for 8 h in Ar/H₂ atmosphere still retained some carbon and therefore it was not fully epitaxial, it can be a potential cap layer for all-chemical YBCO coated conductor.

We have confirmed that when YBCO growth is carried out on different substrate than LAO [99], growth temperature, P(H₂O) and time of growth have to be shifted due to modified relative interfacial energies and chemical compatibility.

By contrasting YBCO film grown on MOD-CGO10 and sputt-CeO₂ we have found that in the latter interface reaction occurs in less extension. We have suggested that this is due to MOD-CGO10 films displays higher surface imperfections (hillocks, porosity, voids). However, by optimizing TFA-YBCO growth parameters we have overcome those surface problems obtaining higher critical current density than no-optimized TFA-YBCO film on sputt-CeO₂ cap layer.

CHAPTER 9

GENERAL CONCLUSIONS

We have successfully demonstrated that chemical solution deposition (CSD) is a very competitive technique for obtaining epitaxial buffer and superconducting layers of high quality and with high critical currents for coated conductor fabrication.

Several conductor architectures based on YBCO are possible. However, the optimum oxide buffer combination depends on the metallic substrate. Two types of metallic substrates have been considered in this Thesis: polycrystalline stainless steel and Ni-RABiT. For these substrates, SrTiO₃ and CeO₂ are the cap layers which have attracted more attention and consequently, we have investigated the growth conditions of these buffers based on CSD to obtain high quality interfaces in multilayered systems. We have also investigated the stability and growth of TFA-YBCO film over the underlying cap layers

We have first investigated the stability of YBCO film deposited by the trifluoroacetate (TFA) route on single crystal substrates: SrTiO₃ (STO) and LaAlO₃ (LAO) or buffered single crystal substrates: BaZrO₃/LaAlO₃ (BZO/LAO) as model systems of multilayered architectures. In this study we have given for the first time evidence that a homogeneous structure of heteroepitaxial TFA-YBCO films is unstable. We have demonstrated that under certain conditions of film thickness, growth or post-processing annealing strongly dewetted films can be generated. TEM investigations have confirmed that the YBCO migration process from the interface is complete in the dewetted areas. These areas display well defined geometrical features with parallelepipedic-like shapes in order to stabilize low energy surfaces. Moreover we have established that the film instability is a mechanism to relief the stress induced at the interface by the lattice misfit between the YBCO film and the single crystal substrates LAO, STO and BZO buffer layers.

Finally, we have been able to describe this phenomenon on the basis of free-energy analysis which is of general validity for YBCO films.

Then, we have focused our work on investigating the influence of the quality of the interface of cap layers on the superconducting properties of TFA-YBCO films. We have considered two different cap layers which are promising candidates for the production of all-chemical coated conductors because they properly match the criteria of protection of the metallic substrates from oxidation, they display low lattice mismatch with YBCO and they can develop high-quality interfaces: STO, with perovskite structure, and CeO₂, with fluorite structure.

We have investigated mechanisms to control the interfacial quality of perovskite STO cap layer grown by CSD on single crystal substrates (STO and LAO) and on MOD-BZO buffered LAO single crystal as model systems for conductors. We have focused on reducing atmospheres which can be used in architectures for Ni-RABiT.

We have obtained epitaxial films, with homogeneous surface morphology consisting in rounded nanometric grains even when high lattice mismatches must be overcome, as in the case of STO/BZO/LAO. Because of this surface morphology consisting on connected globular grains, the surface quality can be determined either by rms roughness or from the percentage of atomically flat area. We have found a certain range of variability in surface roughness in the case of STO/BZO/LAO architecture which can actually be controlled through modifying buffer layer growth temperatures. We have observed that surface roughness has direct implications in the growth and properties of TFA-YBCO films. We have proved that an increased roughness leads to an enhancement of the nucleation of a/b axis oriented grains, and, as a consequence, the residual porosity of TFA-YBCO films is increased with the subsequent deterioration of the superconducting properties.

Control of the interfacial quality of CeO₂ cap layer has also been investigated in detail. We have studied first the influence of annealing treatments on highly epitaxial vacuum deposited CeO₂ cap layer on the final quality of TFA-YBCO films and this knowledge has been used to achieve highly epitaxial and atomically flat CeO₂ cap layers grown by chemical solution deposition.

We have observed that (001)-terraced surfaces in CeO₂ greatly improve the superconducting properties of the TFA-YBCO overlayers grown on them. This feature, not detected in perovskite cap layers, stressed the difference between a statistical parameter such as rms roughness and the percentage of atomically flat area to quantify the surface quality. In this case, the use of rms roughness is a non meaningful parameter and the critical factor to evaluate the quality of ceria surface morphology is the percentage of atomically flat area.

Oxygen atmosphere stabilizes (001)-flat terraced surfaces through some kind of film reconstruction in both vacuum and chemical solution deposited CeO₂ cap layers. However, this

atmosphere cannot be used on Ni substrates because it oxidizes them. Alternatively, as a first approach, we have investigated the influence of other processing atmospheres on highly epitaxial sputtering-CeO₂ films. Whereas Ar/H₂ atmosphere degrades the surface morphology resulting in an inhomogeneous topography, Ar/H₂/H₂O atmosphere has successfully stabilized (001)-flat terraces. It is likely that in this wet atmosphere hydroxyl groups play a special role in stabilizing the (001)-polar CeO₂ surface.

Epitaxy development and stabilization of (001)-flat surfaces in MOD-CeO₂ films have not been straightforward in reducing (95%Ar/5%H₂) atmosphere. This atmosphere, actually, hinders the elimination of carbon content from metalorganic precursors and it blocks the fully epitaxial growth (~18% of epitaxial fraction). To reduce carbon content in film we have investigated different alternatives: (1) the use of partial oxidizing atmospheres (2) the nature of precursor solution (3) the incorporation of dopant agents.

Ar/H₂ atmosphere with different contents of oxygen (Ar/H₂/H₂O, O₂+Ar/H₂) have not provided enough mobility and chemical exchange to remove all carbon (Ce-C) trapped in grain boundaries. On the other hand, by modifying chemical precursors we have slightly improved the epitaxial fraction from ~18% to ~38%) but without stabilizing the (001)-surface. This improvement has been related to a modification of the decomposition pathway of organic precursor through formation of isoprene.

Then, we have explored an alternative route: the incorporation of dopant agents (Gd³⁺, Zr⁴⁺). Interestingly, both cations introduce and enhance atomic mobility by creation of oxygen vacancies, however, the mechanism of oxygen vacancy formation strongly differs in both cases. Whereas for Gd³⁺ it appears to be related with charge compensation effect, while by Zr⁴⁺ the small ionic radius emerge as the key parameter to stabilize interstitial defects.

We have demonstrated, after detailed optimization of Gd-doped CeO₂ films, that many parameters influence the atomic mobility in CeO₂ films: carbide impurities, dopant concentration and growth conditions (atmosphere, time and temperature). Indeed, we detected a gradual increase in the epitaxial fraction and the percentage of atomically flat area running in parallel to the elimination of carbon content.

The films with optimum performances obtained in Ar/H₂ atmosphere have been 10%Gd-doped CeO₂ (CGO10) grown at 900°C for 8h. Under these reducing conditions we obtained ~77% of epitaxial fraction and ~71% of (001)-atomically flat area. No influence of adding H₂O in the gas flow was detected in this case. It is likely that in this case oxygen vacancies already stabilize the (001) polar surface and the hydroxyl groups do not play any additional role. Improving the epitaxy (> 80% of epitaxial fraction) simultaneously with stabilizing (001)-flat terraced surface could only be achieved under pure oxygen atmosphere.

Highly biaxially TFA-YBCO films have been successfully grown on high quality (001)-terraced CeO₂ films. We have obtained self-field J_c values at 77K of 1.5MA cm⁻² in sputtering-CeO₂/YSZ single crystal substrates and 0.3MA cm⁻² in sputtering-CeO₂/YSZ/CeO₂/Ni-RABiT substrates. We have been able also to develop high quality TFA-YBCO films on MOD-(001)-10%-Gd-CeO₂ cap layer, after a detailed optimization of growth parameters, displaying very promising superconducting performances, J_c of 2.3MA cm⁻² at 77K. Interestingly, TFA-YBCO films are more sensitive to the quality of the underlying cap layers and we have shown that a higher percentage of atomically flat area (~70 versus ~30%) is needed to obtain similar film properties as YBCO films deposited by pulsed laser deposition (PLD), J_c of 3MA cm⁻² at 77K. In both systems we have detected interface reaction between YBCO film and CeO₂ cap layers, leading to BaCeO₃ formation.

Chemical reactivity has been found higher in all-chemical multilayers, this is probably due to an enhanced porosity of the films and hence of the contact surface among the cap layer and the YBCO film. However, we have demonstrated that interfacial reaction does not preclude the attainment of high J_c values because it generally occurs after the nucleation of the epitaxial YBCO film at the interface with the cap layer. Our work shows then that a high percentage of atomically flat area in CeO₂ cap layers is the key parameter to favor c-axis YBCO grain nucleation and therefore reaching biaxially textured YBCO film and high critical currents.

FUTURE WORK

Our work has risen, on the other hand, several issues that still remain unanswered, and therefore it suggests new research areas that should be investigated in the future. It would be very appealing to reach a deeper understanding of the process involved in the carbon content elimination in CeO₂ films, keeping a reducing atmosphere. The interplay between the nature of precursor solutions and defect structure of the fluorite CeO₂ seems to be the key issue here. More specifically it would be interesting to study an alternative way to increase the atomic mobility in ceria films in order to beyond 80% in epitaxial fraction and ~77% in atomic flatness and hence, achieve a final film quality similar to that obtained under pure oxygen atmosphere. To reach this objective it is needed to understand the mechanism by which the incorporation of Gd³⁺, or even other dopant agents, enhances the C elimination.

Another issue that remains to be investigated is the relationship between the TFA-YBCO growth conditions and the surface quality of CeO₂ cap layers. We can wonder if the sensitiveness of TFA-YBCO layers to the cap layer quality could be decreased to values similar to those found by PLD growth.

Finally, the other field in which an extensive work still remains to be done is in MOD-STO cap layers. This regard the issue that we consider more appealing to improve the STO cap layer surface quality (develop terraced surfaces for instance) and hence to further optimize the YBCO texture quality and critical currents when growth is performed on this perovskite cap layer.

We would like to conclude this work by indicating that the knowledge generated in the preparation of the different CSD multilayers can be now transferred to metallic substrates, particularly to the RABIT substrates fabricated by Nexans Superconductors, and so it is expected that in a very near future long length 'all chemical' coated conductors will be achieved with high performances.

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